

**Łukasiewicz**

Instytut  
Mikroelektroniki  
i Fotoniki

# Secondary Ion Mass Spectrometry

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31.05.2022

# Contents

**1. Principles of SIMS**

**2. Basic applications**

**3. Quantitative analysis**

**4. CAMECA SC Ultra**

**5. Examples**

**6. Conclusions**

# Contents

**1. Principles of SIMS**

**2. Basic applications**

**3. Quantitative analysis**

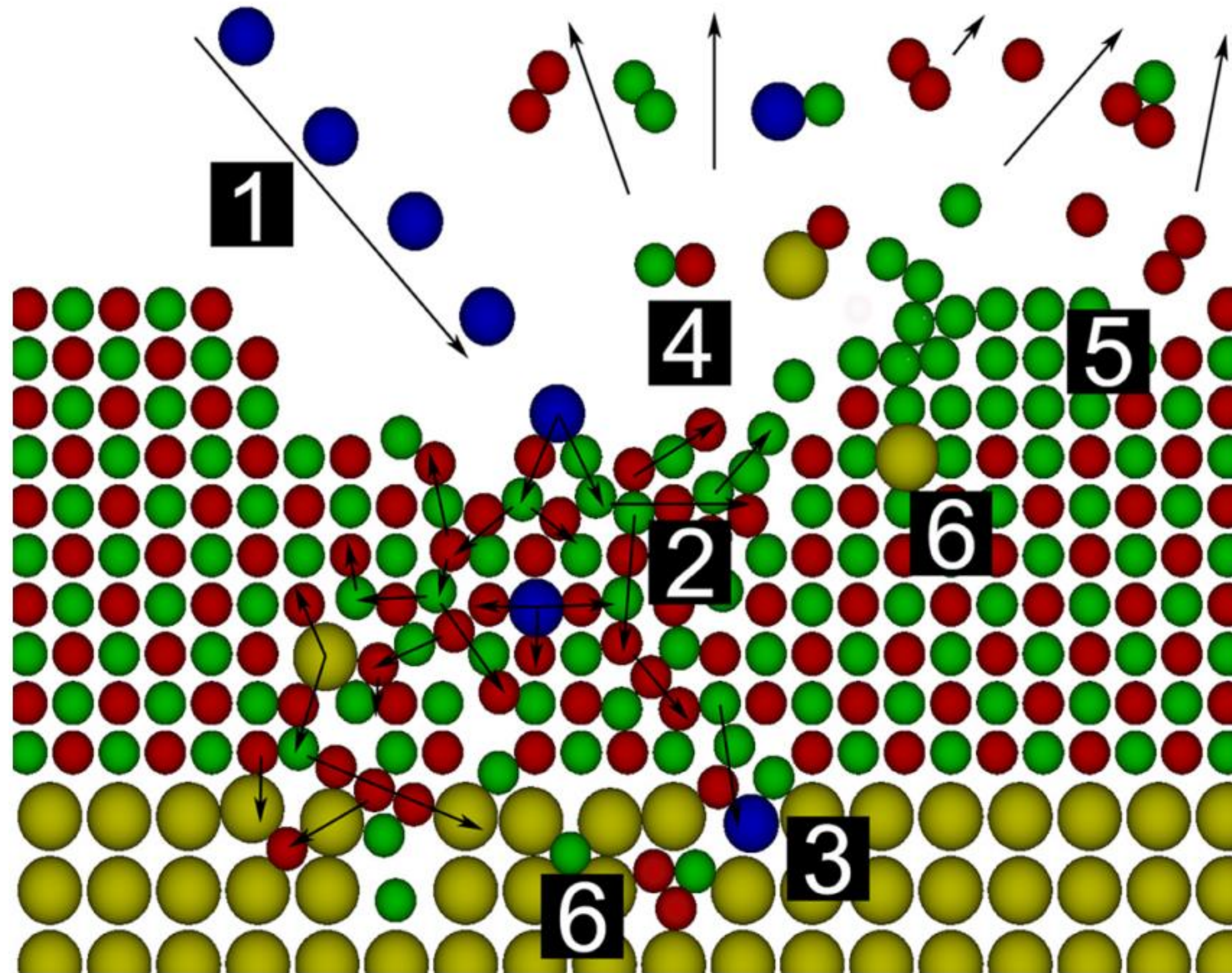
**4. CAMECA SC Ultra**

**5. Examples**

**6. Conclusions**



# Fundamentals – Ion Bombardment



1. Primary beam
2. Collision cascade
3. Implantation
4. Sputtering and ionization
5. Preferential sputtering
6. Mixing



# Fundamentals – two sources

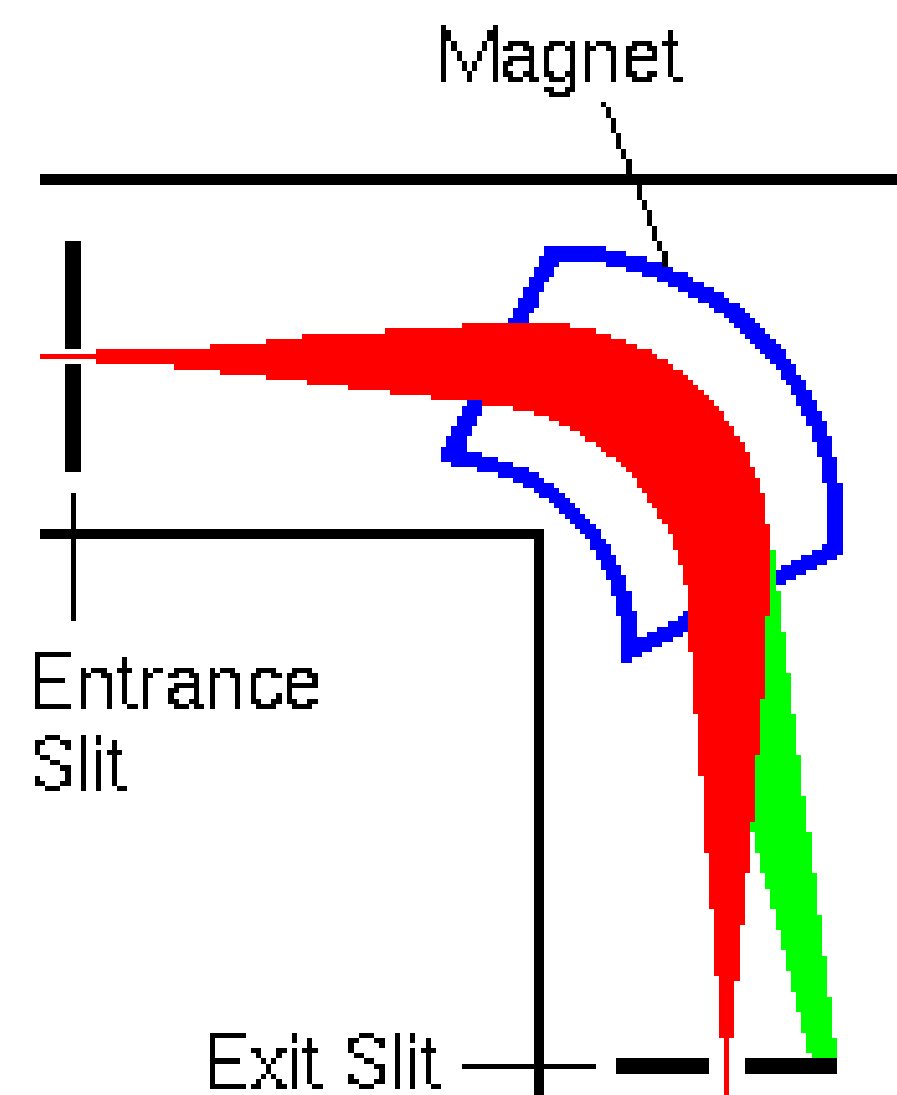
H 1,0079	O <sub>2</sub> <sup>+</sup> P <sup>+</sup>																He 4,0026																												
Li 6,941	Be 9,0122	Cs <sup>+</sup> P <sup>-</sup>										B 10,811	C 12,011	N 14,006	O 15,99	F 18,998	Ne 20,179																												
Na 22,989	Mg 24,305	Cs <sup>+</sup> P <sup>+</sup>										Al 26,98	Si 28,085	P 30,973	S 32,066	Cl 35,452	Ar 39,948																												
K 39,098	Ca 40,078	Sc 44,955	Ti 47,88	V 50,941	Cr 51,996	Mn 54,938	Fe 55,847	Co 58,933	Ni 58,693	Cu 63,546	Zn 65,39	Ga 69,723	Ge 72,61	As 74,921	Se 78,96	Br 79,904	Kr 83,8																												
Rb 85,467	Sr 87,62	Y 88,905	Zr 91,224	Nb 92,906	Mo 95,94	Tc 98	Ru 101,07	Rh 102,9	Pd 106,42	Ag 107,86	Cd 112,41	In 114,82	Sn 118,71	Sb 121,75	Te 127,6	I 126,9	Xe 131,29																												
Cs 132,9	Ba 137,32	La 138,9	Hf 178,49	Ta 180,94	W 183,85	Re 186,2	Os 190,2	Ir 192,22	Pt 195,08	Au 196,96	Hg 200,59	Tl 204,38	Pb 207,2	Bi 208,98	Po 209	At 210	Rn 222																												
Fr 223	Ra 226,02	Ac 227,02	Rf 261	Db 262	Sg 263	Bh 264	Hs 265	Mt 266																																					
<table border="1"> <tr> <td>Ce 140,11</td> <td>Pr 140,9</td> <td>Nd 144,24</td> <td>Pm 145</td> <td>Sm 150,36</td> <td>Eu 151,96</td> <td>Gd 157,25</td> <td>Tb 158,92</td> <td>Dy 162,5</td> <td>Ho 167,93</td> <td>Er 167,26</td> <td>Tm 168</td> <td>Yb 173,04</td> <td>Lu 174,96</td> </tr> <tr> <td>Th 232,03</td> <td>Pa 231,03</td> <td>U 238,02</td> <td>Np 237,04</td> <td>Pu 244</td> <td>Am 243</td> <td>Cm 247</td> <td>Bk 247</td> <td>Cf 251</td> <td>Es 252</td> <td>Fm 257</td> <td>Md 258</td> <td>No 259</td> <td>Lr 260</td> </tr> </table>																		Ce 140,11	Pr 140,9	Nd 144,24	Pm 145	Sm 150,36	Eu 151,96	Gd 157,25	Tb 158,92	Dy 162,5	Ho 167,93	Er 167,26	Tm 168	Yb 173,04	Lu 174,96	Th 232,03	Pa 231,03	U 238,02	Np 237,04	Pu 244	Am 243	Cm 247	Bk 247	Cf 251	Es 252	Fm 257	Md 258	No 259	Lr 260
Ce 140,11	Pr 140,9	Nd 144,24	Pm 145	Sm 150,36	Eu 151,96	Gd 157,25	Tb 158,92	Dy 162,5	Ho 167,93	Er 167,26	Tm 168	Yb 173,04	Lu 174,96																																
Th 232,03	Pa 231,03	U 238,02	Np 237,04	Pu 244	Am 243	Cm 247	Bk 247	Cf 251	Es 252	Fm 257	Md 258	No 259	Lr 260																																

O<sub>2</sub><sup>+</sup> - electronegativity –  
formation of cations

Cs<sup>+</sup> - decreases work function of  
electrons – formation of anions

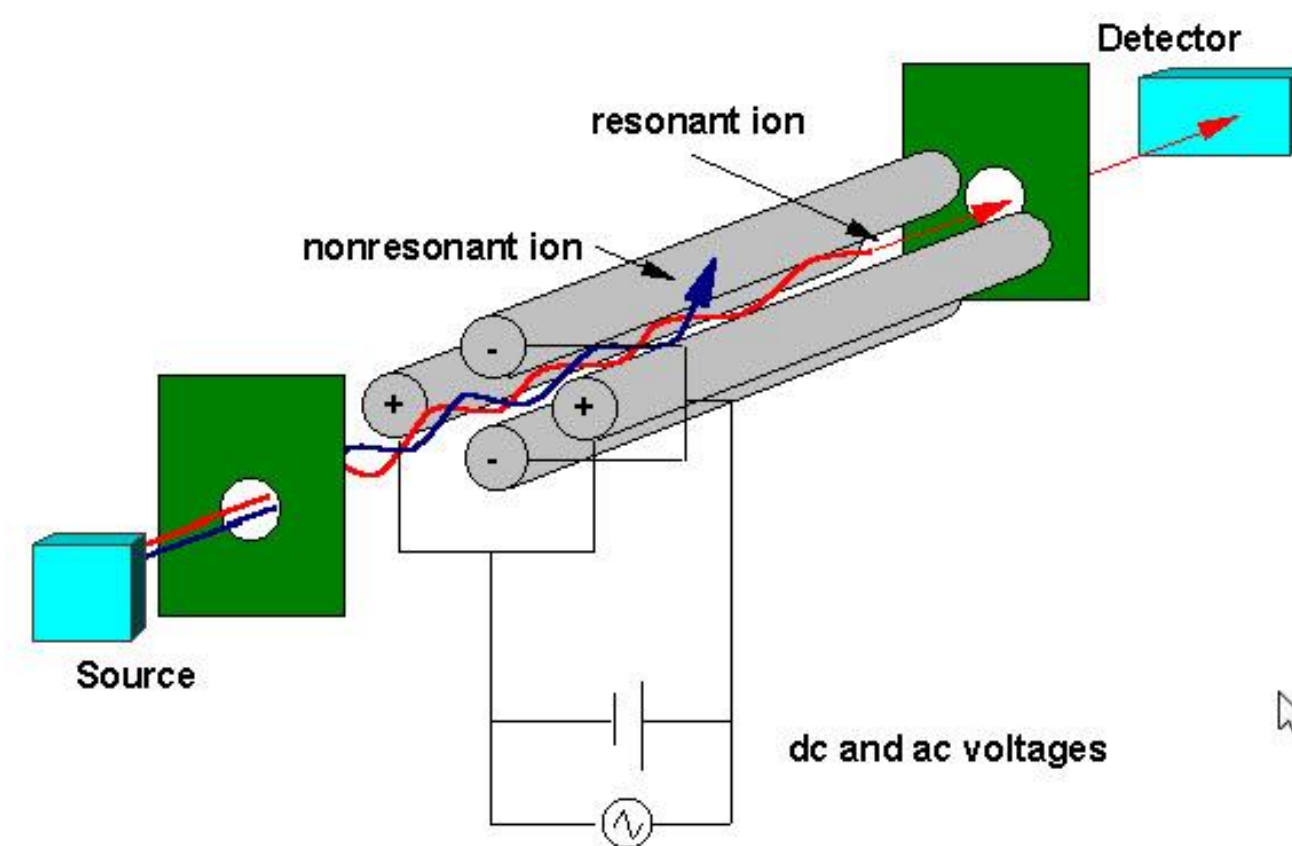
Four order of magnitude  
difference!!!

# Fundamentals – detectors



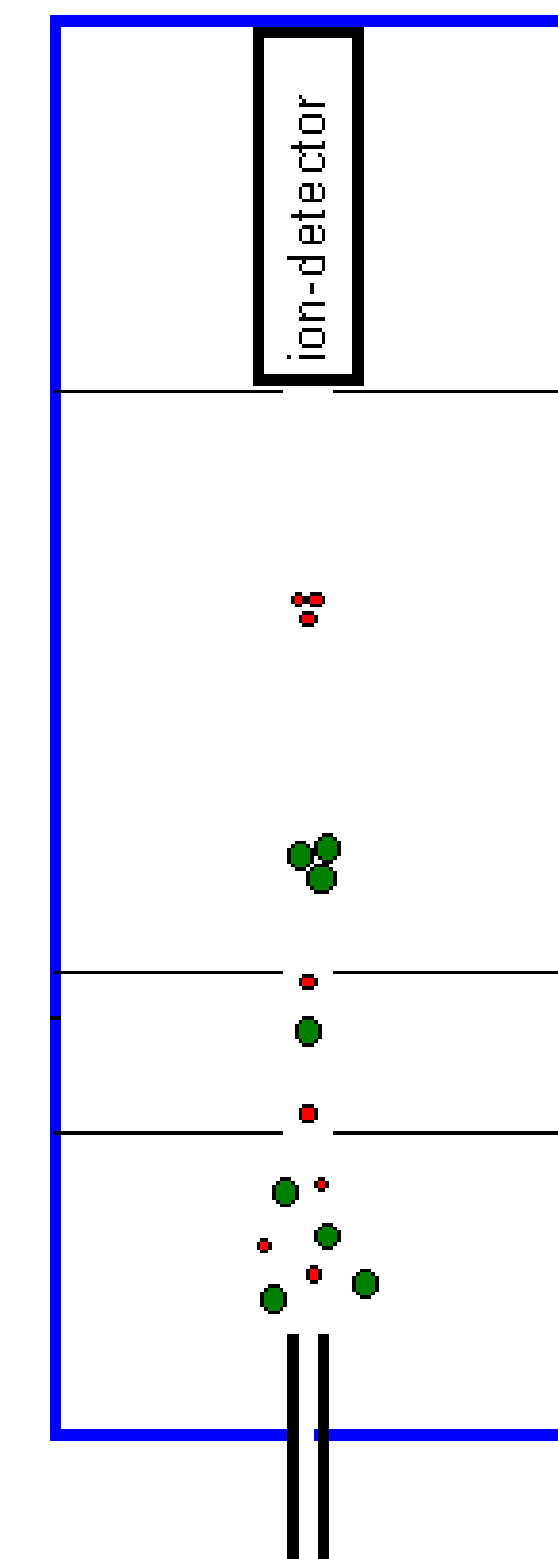
## Magnetic sector

Best detection limits  
Quantitative analysis



## Quadrupole

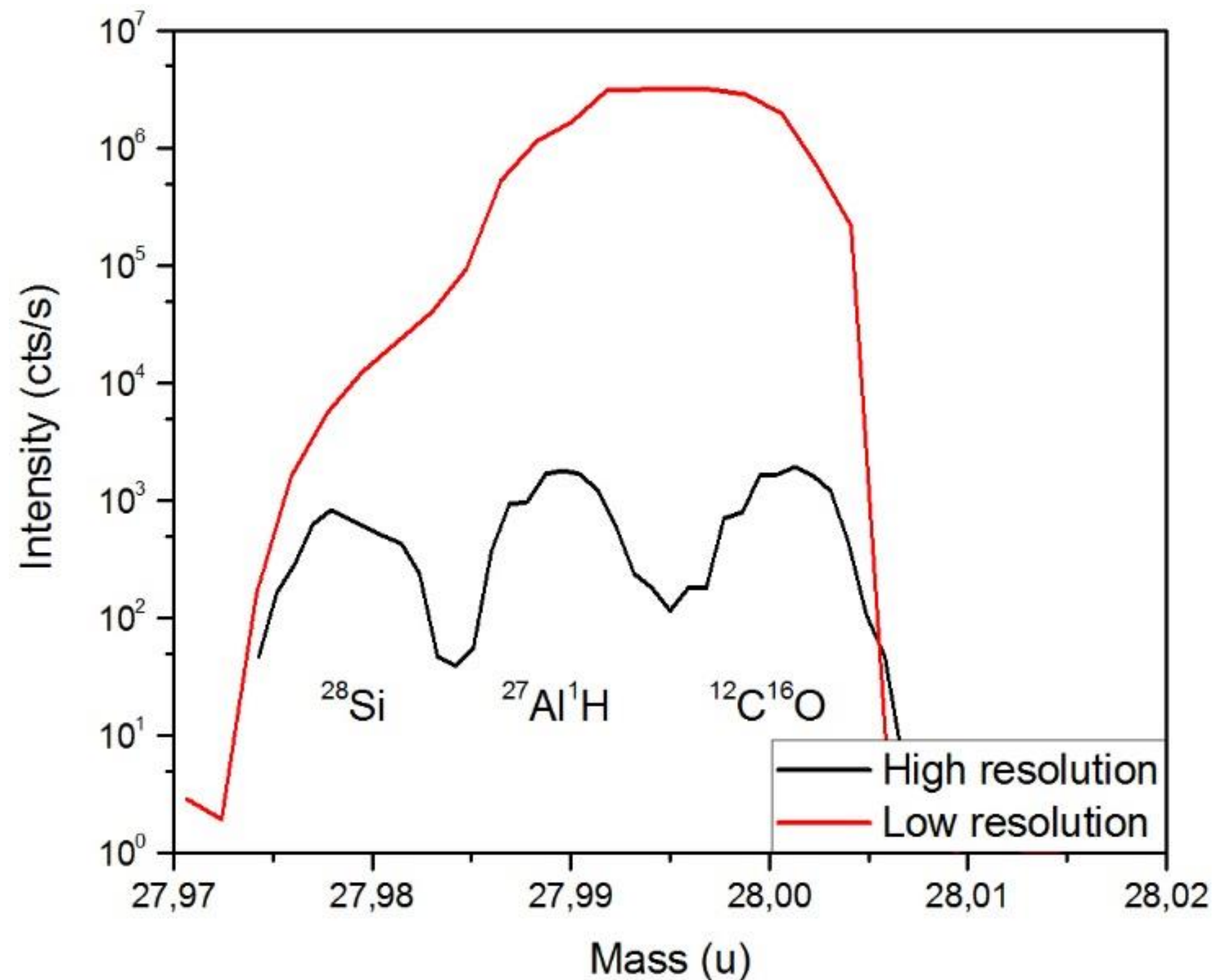
Insulators



## Time-of-Flight

Organic materials  
Simultaneous  
measurements

# Fundamentals – mass interferences



## Solutions

- High mass resolution
- Different isotopes
- Monoatomic ions

Lower sensitivity!

$$\text{MRP} = m/\Delta m$$

$$^{28}\text{Si} - ^{12}\text{C}^{16}\text{O} \quad \text{MRP} = 1246$$

$$^{28}\text{Si} - ^{27}\text{Al}^1\text{H} \quad \text{MRP} = 2231$$

$$^{31}\text{P} - ^{30}\text{Si}^1\text{H} \quad \text{MRP} = 3116$$

$$^{104}\text{Ru} - ^{104}\text{Pd} \quad \text{MRP} = 74452$$



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# Basic applications

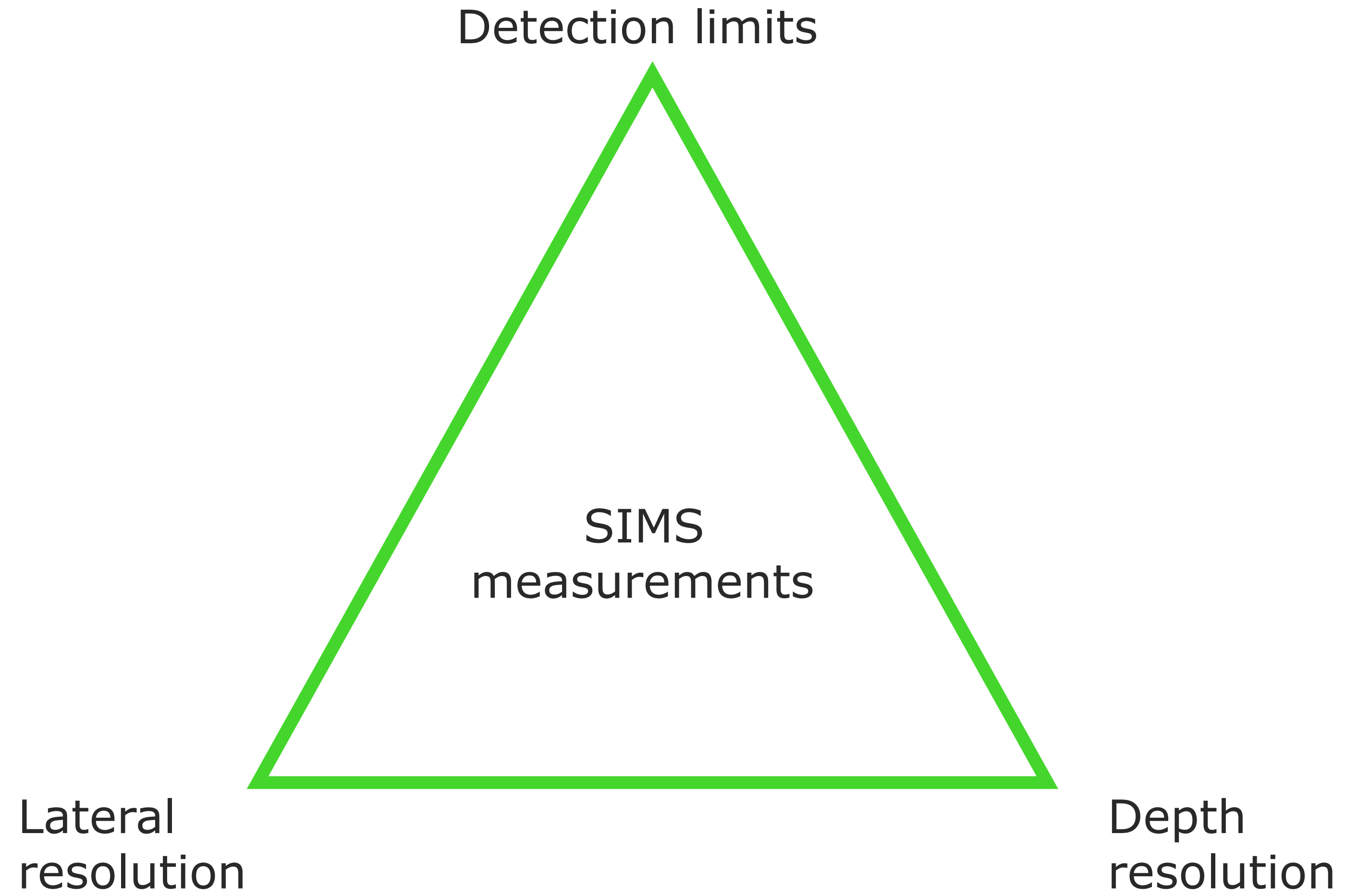
Detection Limits in Si

O <sub>2</sub> <sup>+</sup> Primary Ion Beam Positive Ions		Cs <sup>+</sup> Primary Ion Beam Negative Ions		Cs <sup>+</sup> Primary Ion Beam Positive Ions (MCs <sup>+</sup> )	
Element	DL (atoms/cm <sup>3</sup> )	Element	DL (atoms/cm <sup>3</sup> )	Element	DL (atoms/cm <sup>3</sup> )
He	5E+17	H	1E+17	Ar	1E+17*
Li	5E+12	B	1E+15	-	-
B	2E+13	C	1E+16	-	-
Na	5E+12	N	1E+15	-	-
Mg	5E+12	O	5E+16	-	-
Al	2E+13	F	5E+15	-	-
K	5E+12	P	1E+14	-	-
Ca	1E+13	S	1E+15	-	-
Ti	1E+13	Cl	5E+15	-	-
Cr	2E+13	Cu	2E+15	-	-
Mn	2E+13	As	5E+13 – 2E+15	-	-
Fe	5E+13 – 2E+15	Ge	2E+14	-	-
Ni	5E+14	Sb	1E+14 – 2E+15	-	-
Cu	2E+14	Au	5E+13	-	-
Zn	5E+15	-	-	-	-
As	5E+16	-	-	-	-
Mo	1E+14	-	-	-	-
In	5E+13	-	-	-	-
Ta	5E+14	-	-	-	-
W	2E+14	-	-	-	-

\* Assuming Ca level is below 1E15 at/cm

- Elemental composition
- No/minimal information about chemical state
- Depth profile
- Lateral analysis + 3D
- Stability of layers
- Diffusion
- Dopants and contamination

# Basic applications - limitations





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# Quantitative analysis – basic equation

$$I(A) = I_p Y(A) a(A) c(A) \eta$$

$I(A)$  secondary ion current

$I_p$  primary ion current

$Y(A)$  partial sputter yield

$a(A)$  ionization probability

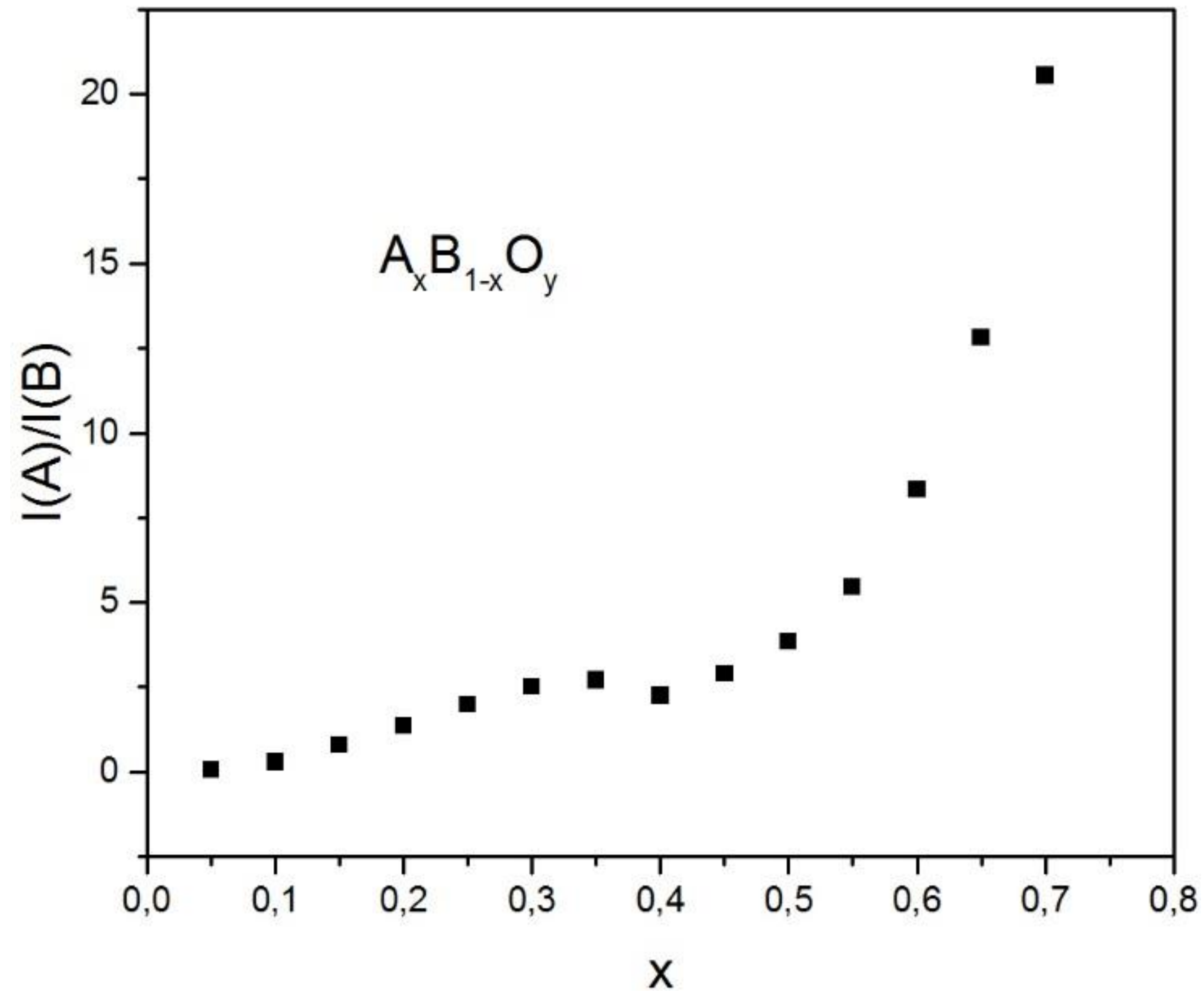
$c(A)$  concentration

$\eta$  transmission and detection coefficient

## Challenges

- Matrix effect
- High sensitivity on conditions

# Quantitative analysis – elemental composition

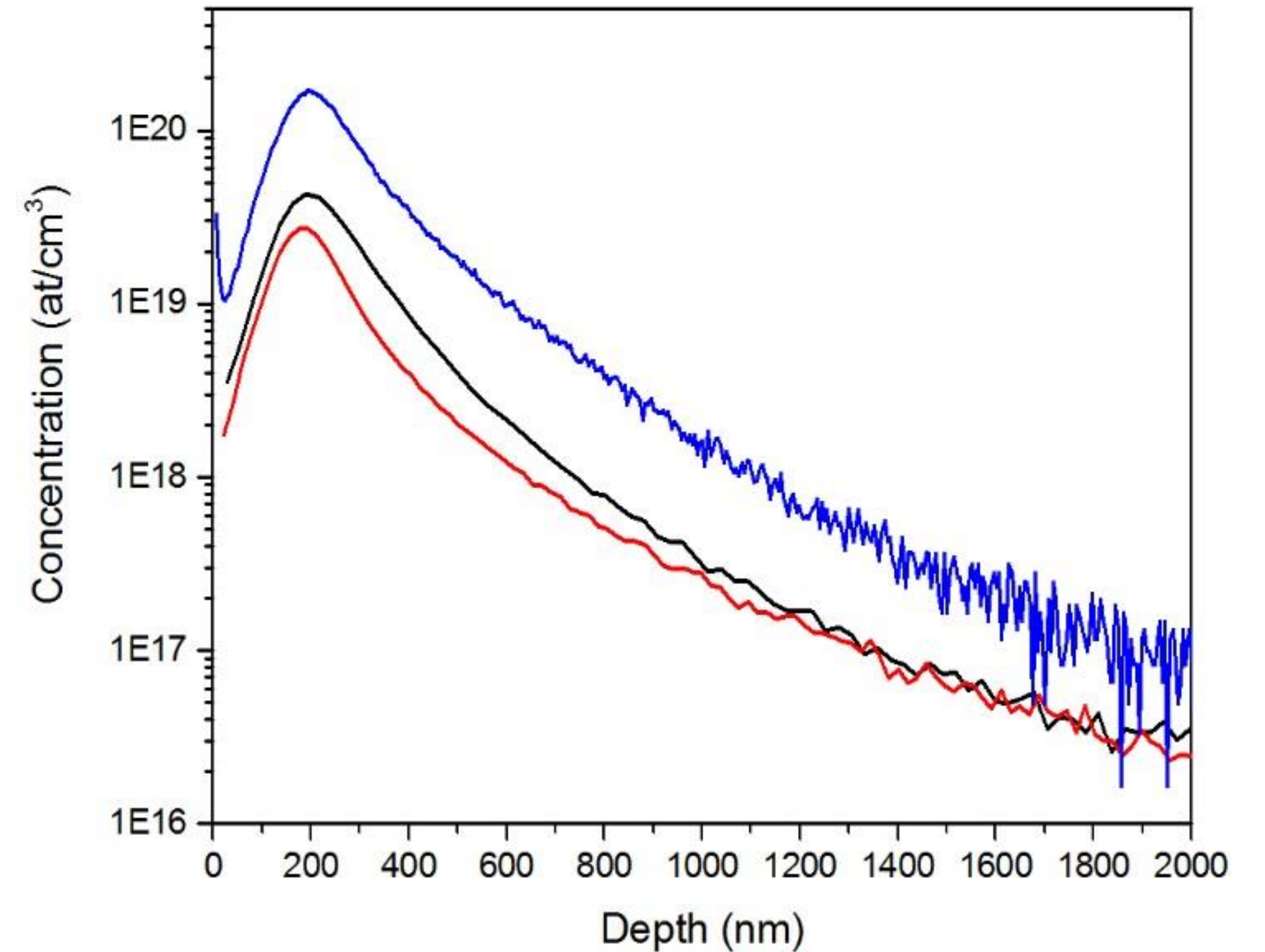
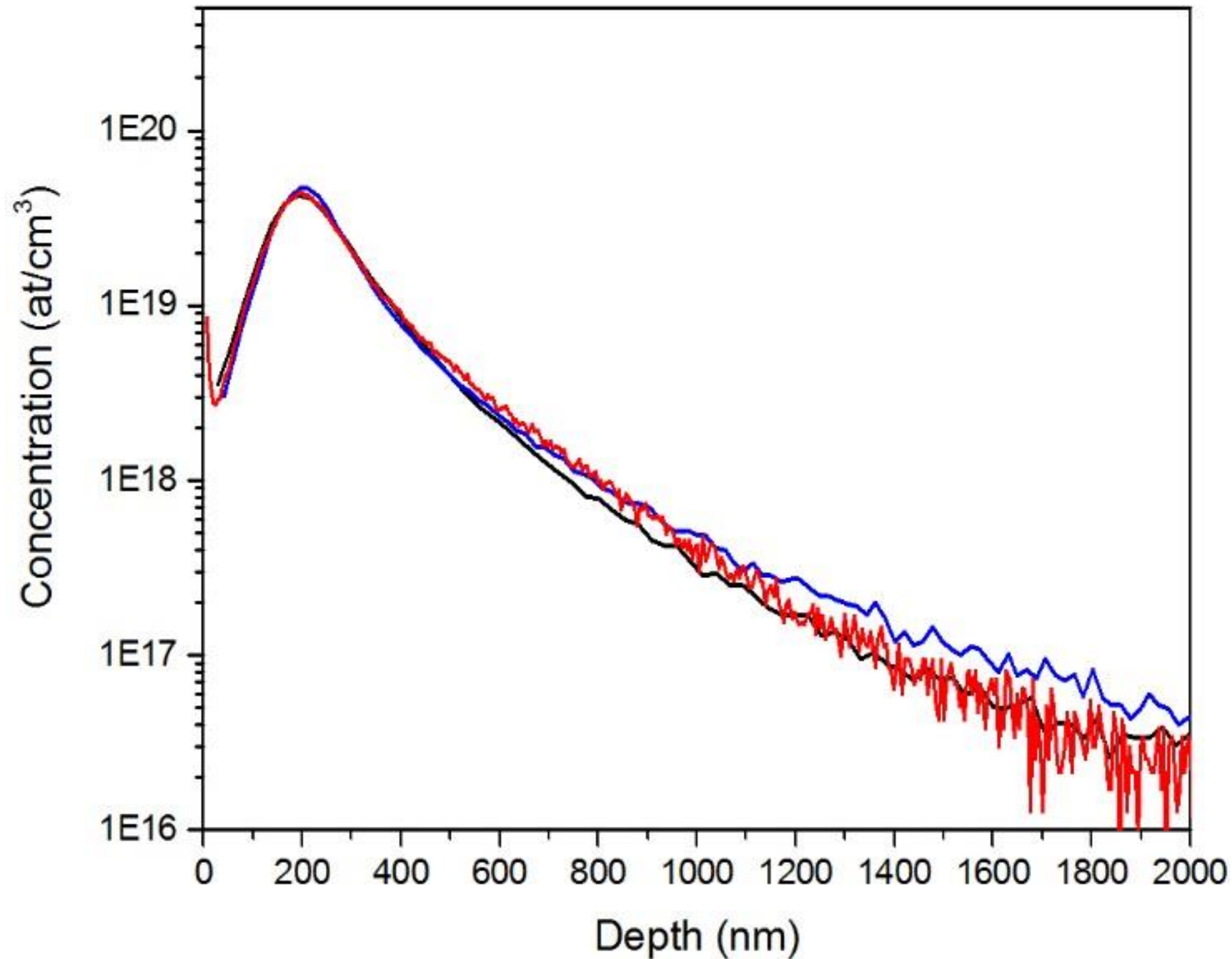


- Simple samples
- Complicated procedure
- Possible errors
- Identification: other techniques
- Depth profiles: good choice



# Quantitative analysis – Dopants and contamination

Very precise measurements:  $C(A) = RSF_A I(A) / I(M)$   
RSF based on reference samples



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# Ultra Low Impact Energy SIMS (ULIE SIMS)

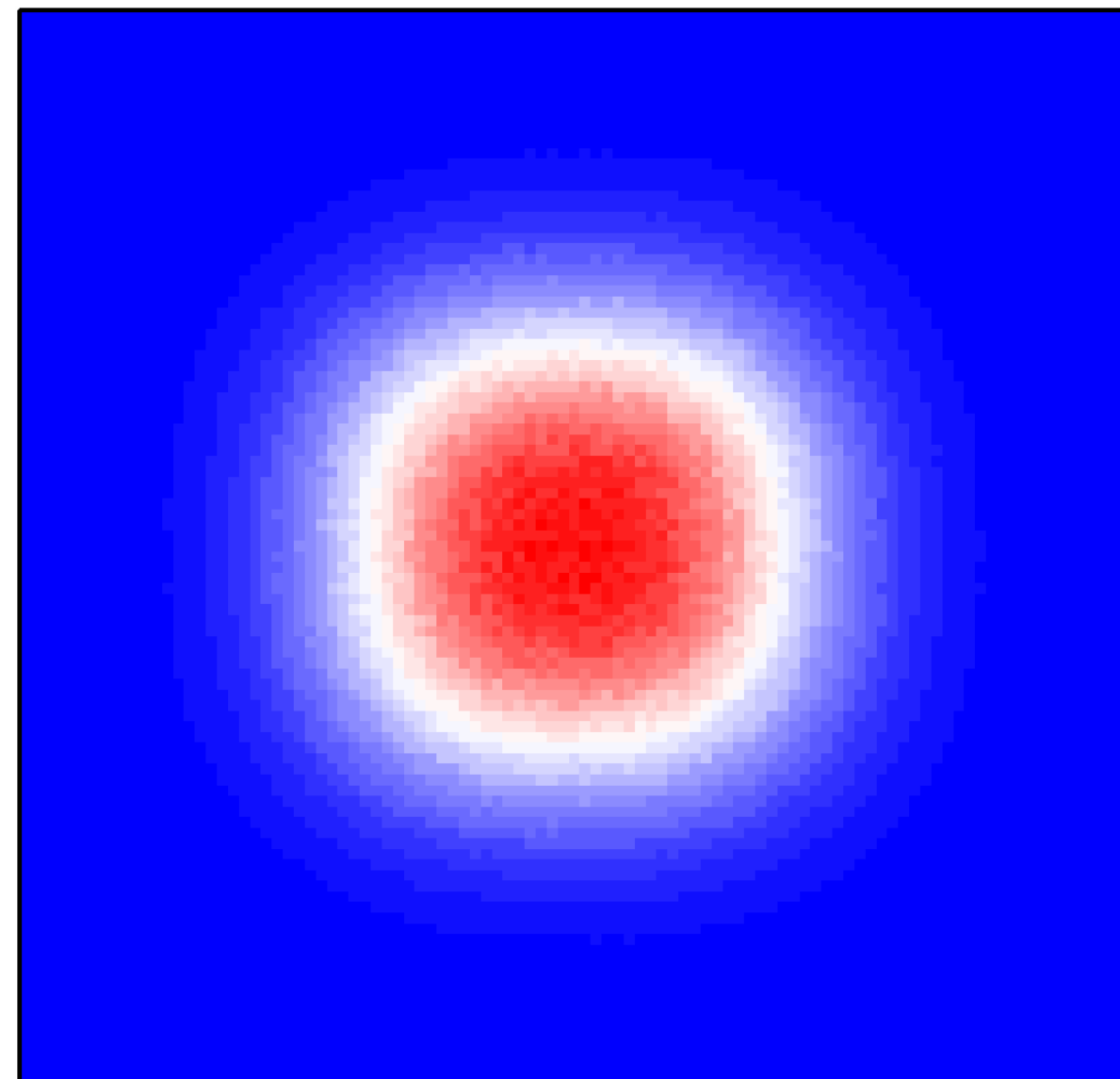
## EXLIE (EXtreme Low Impact Energy) technology

- RF Plasma for oxygen column – down to 60 eV
- Floating voltage for cesium column – down to 90 eV

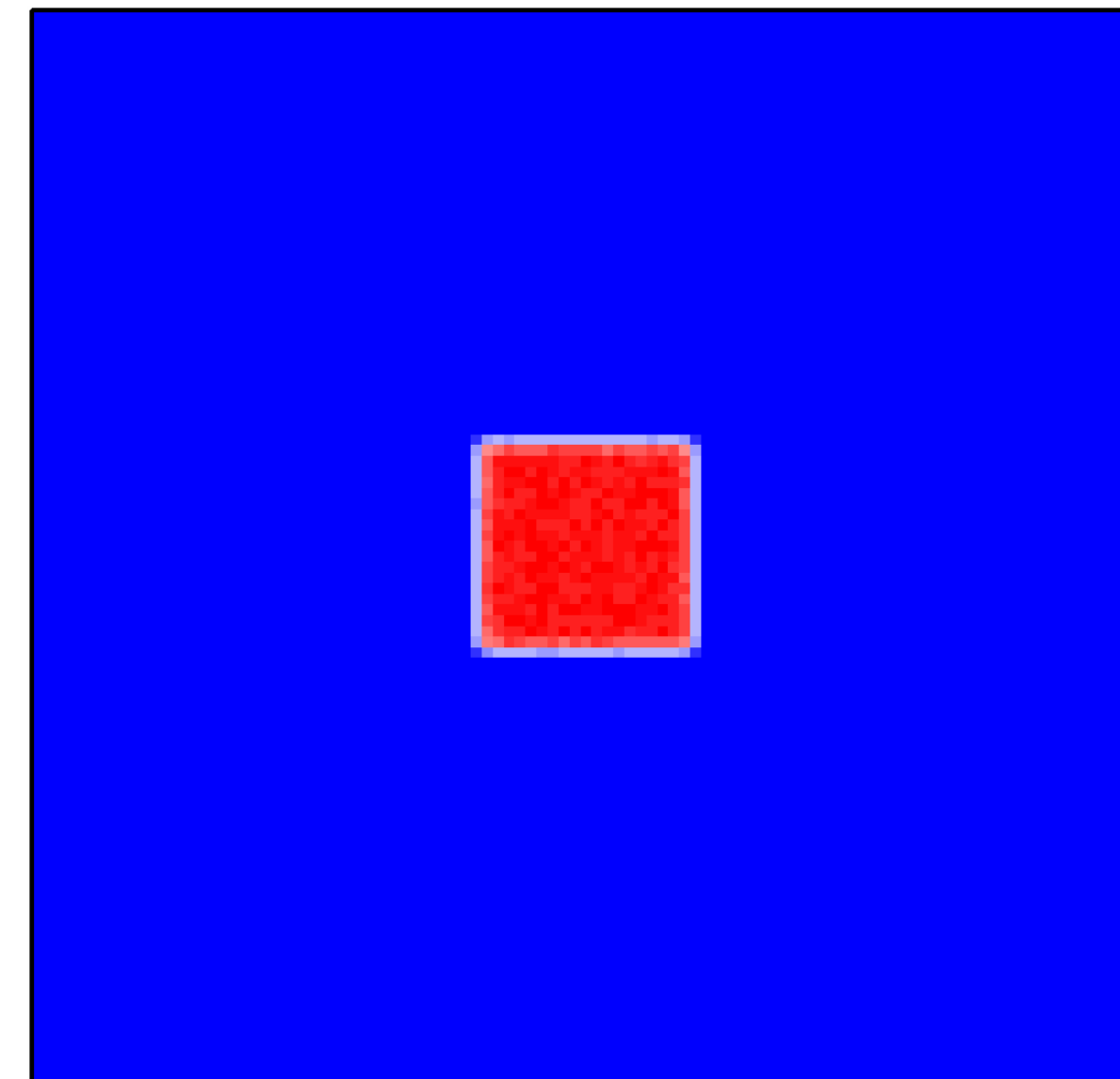
## Beam shape

**15 instruments!!!**

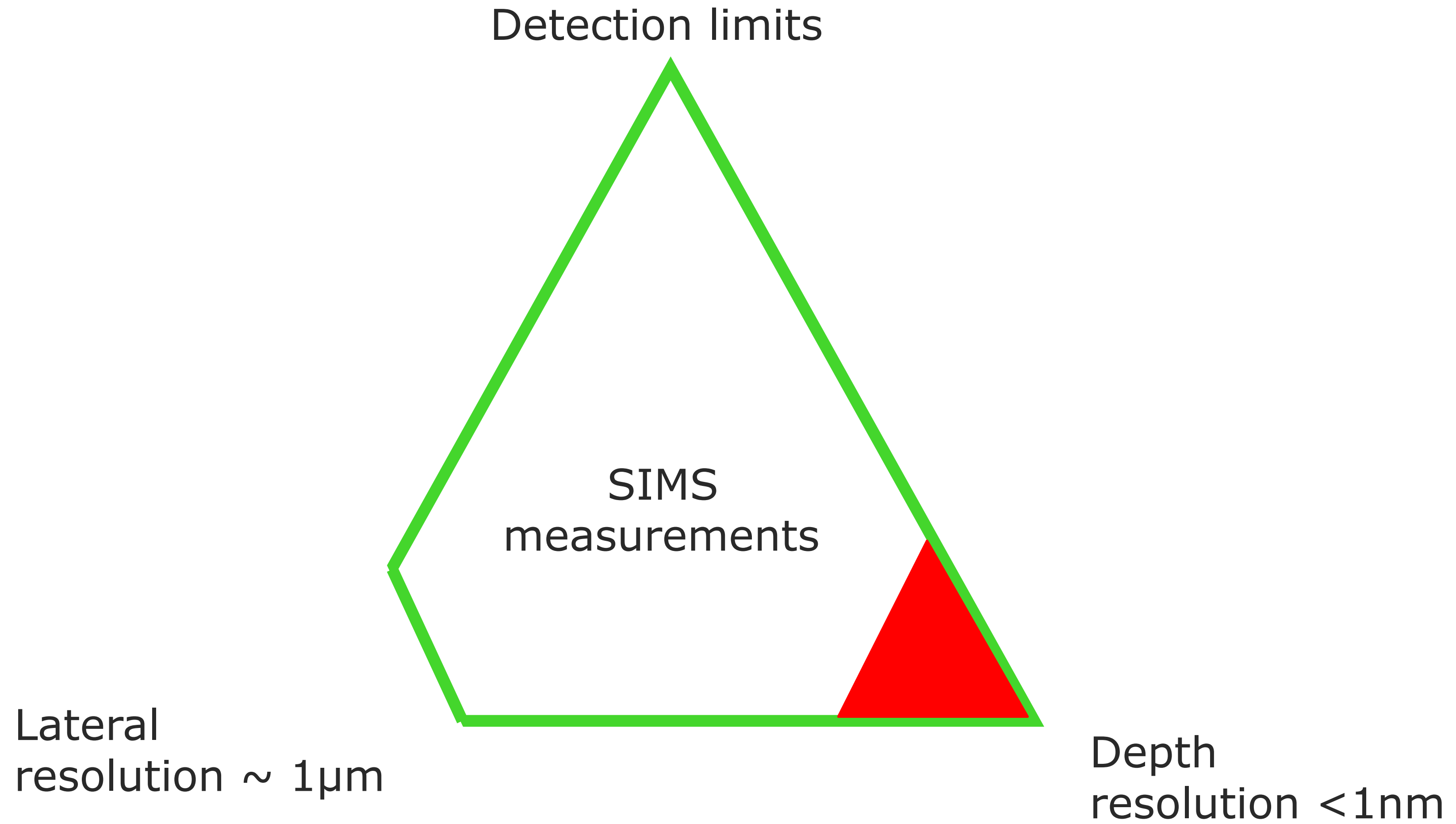
Typical Gaussian-shaped beam



Projected on square stencil



# CAMECA IMS SC Ultra - limitations



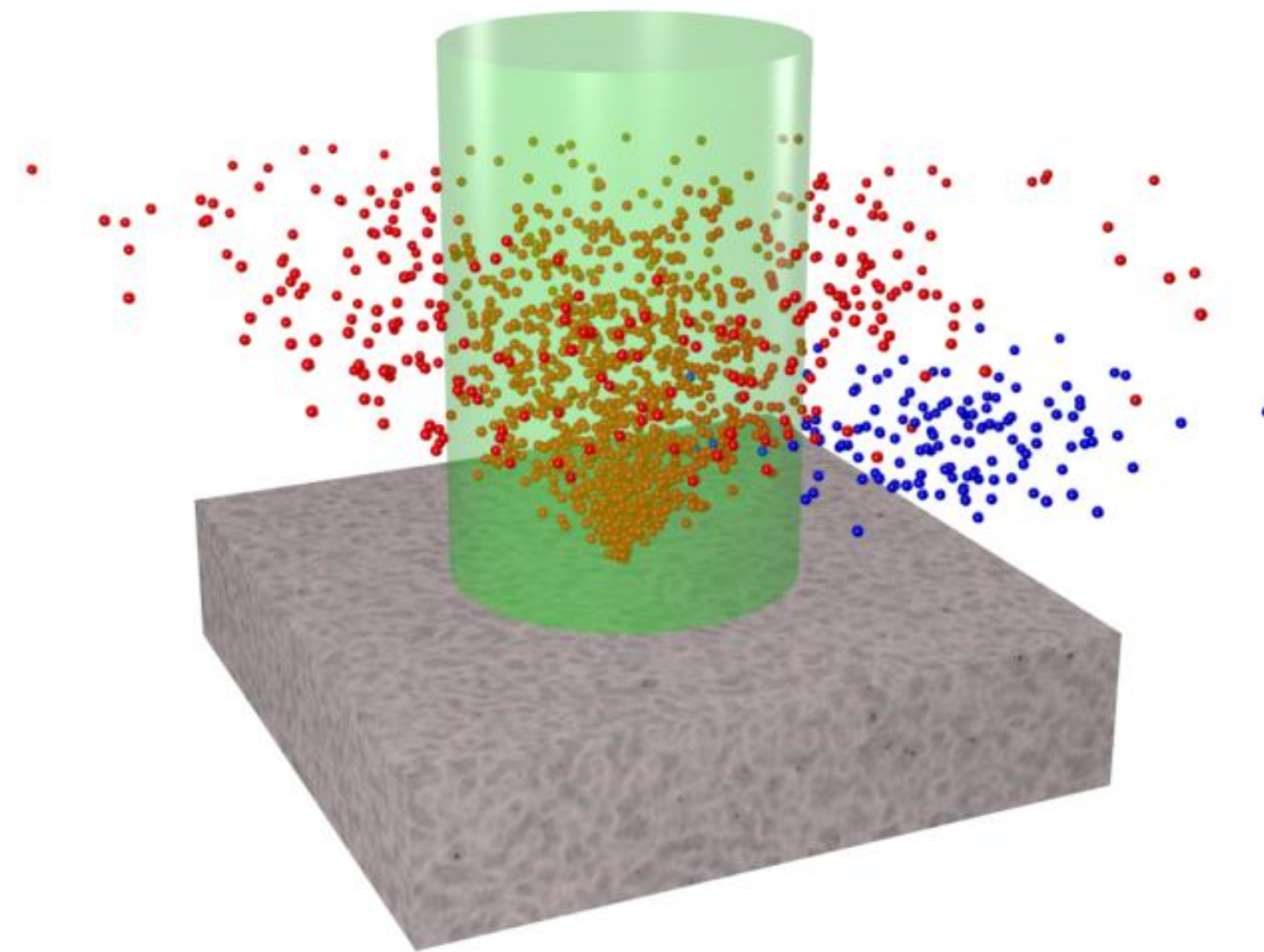


# CAMECA IMS SC Ultra – dedicated procedures

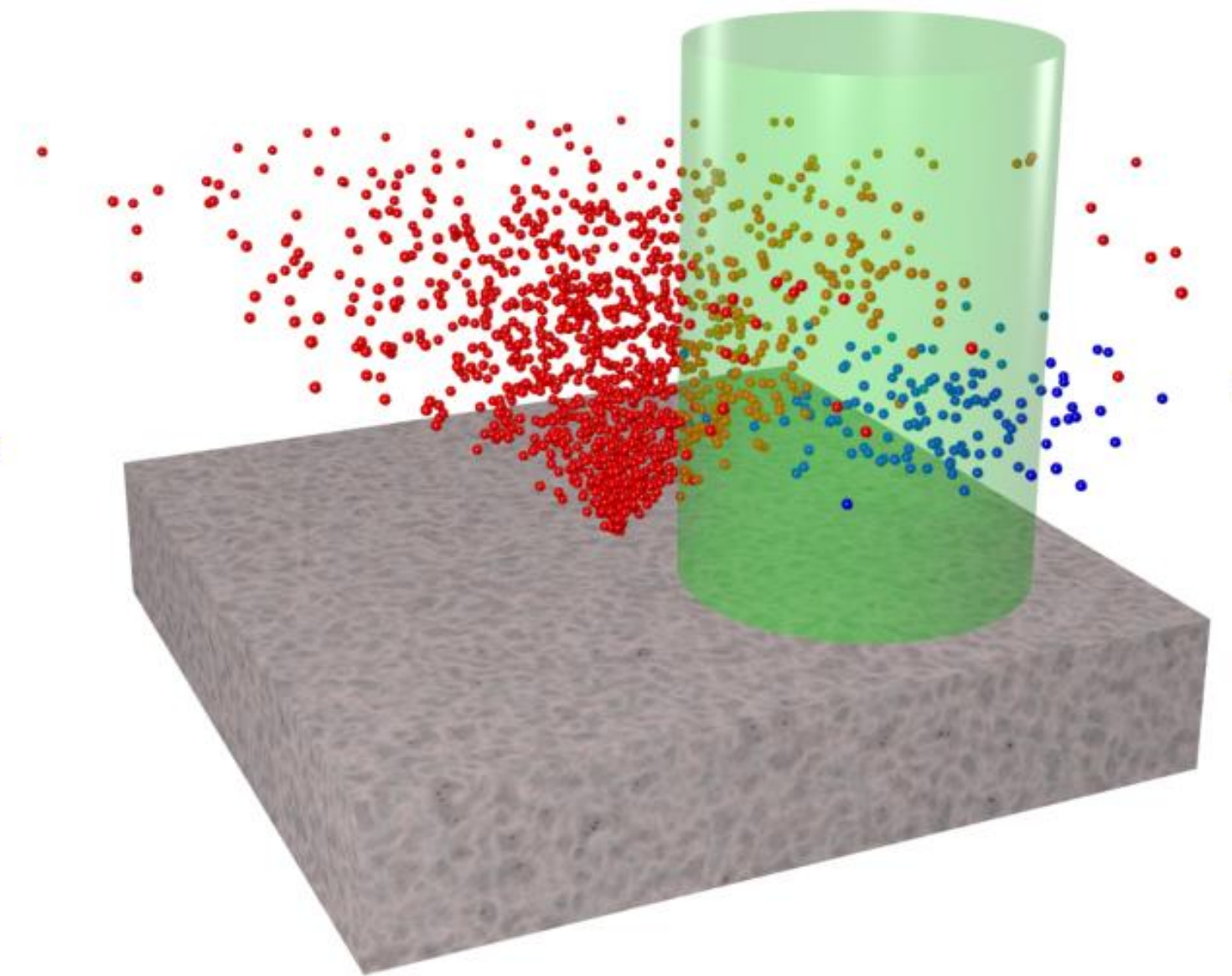
## Type of procedures

- Standard/universal
- Dedicated

Standard



Dedicated





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**1. Principles of SIMS**

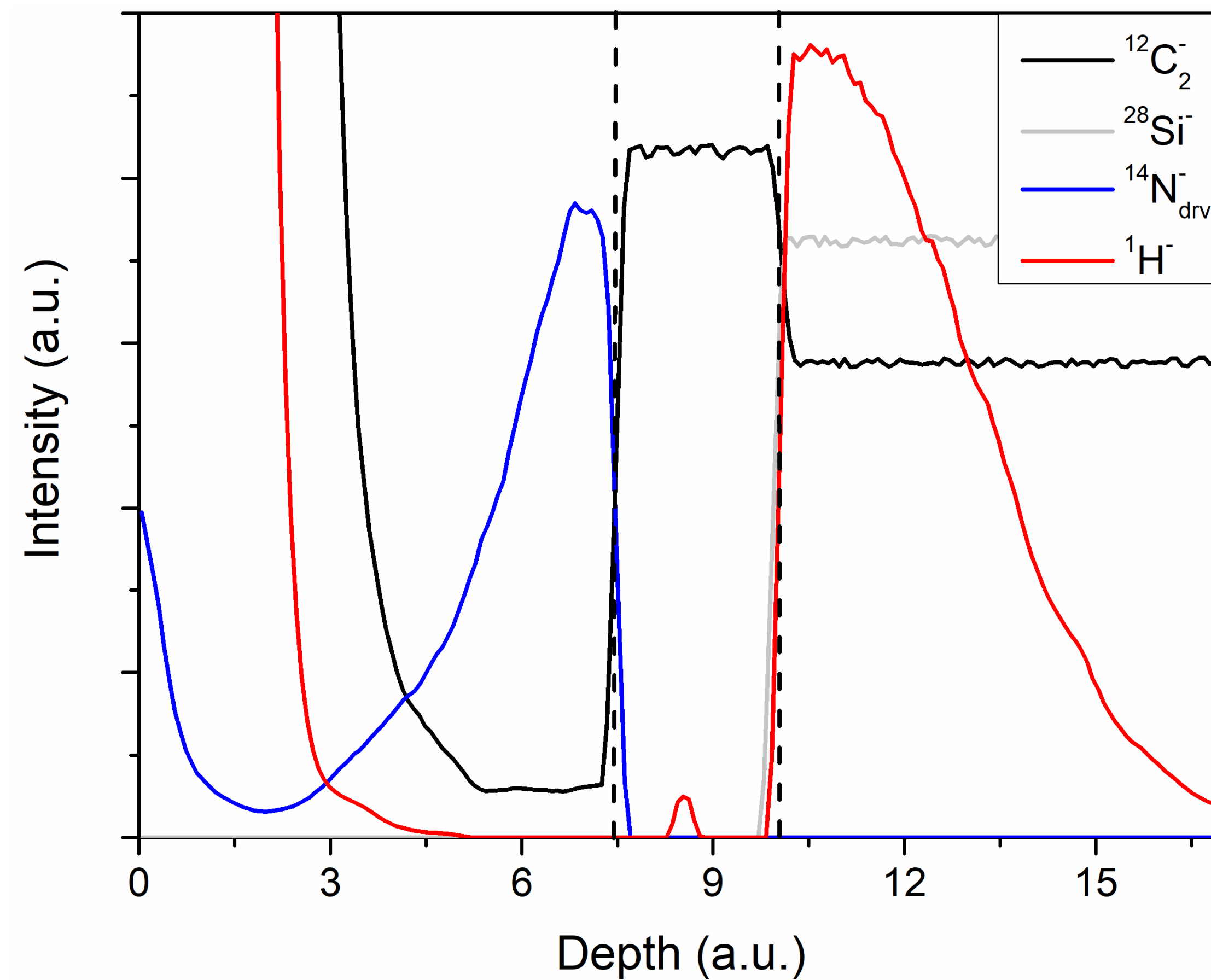
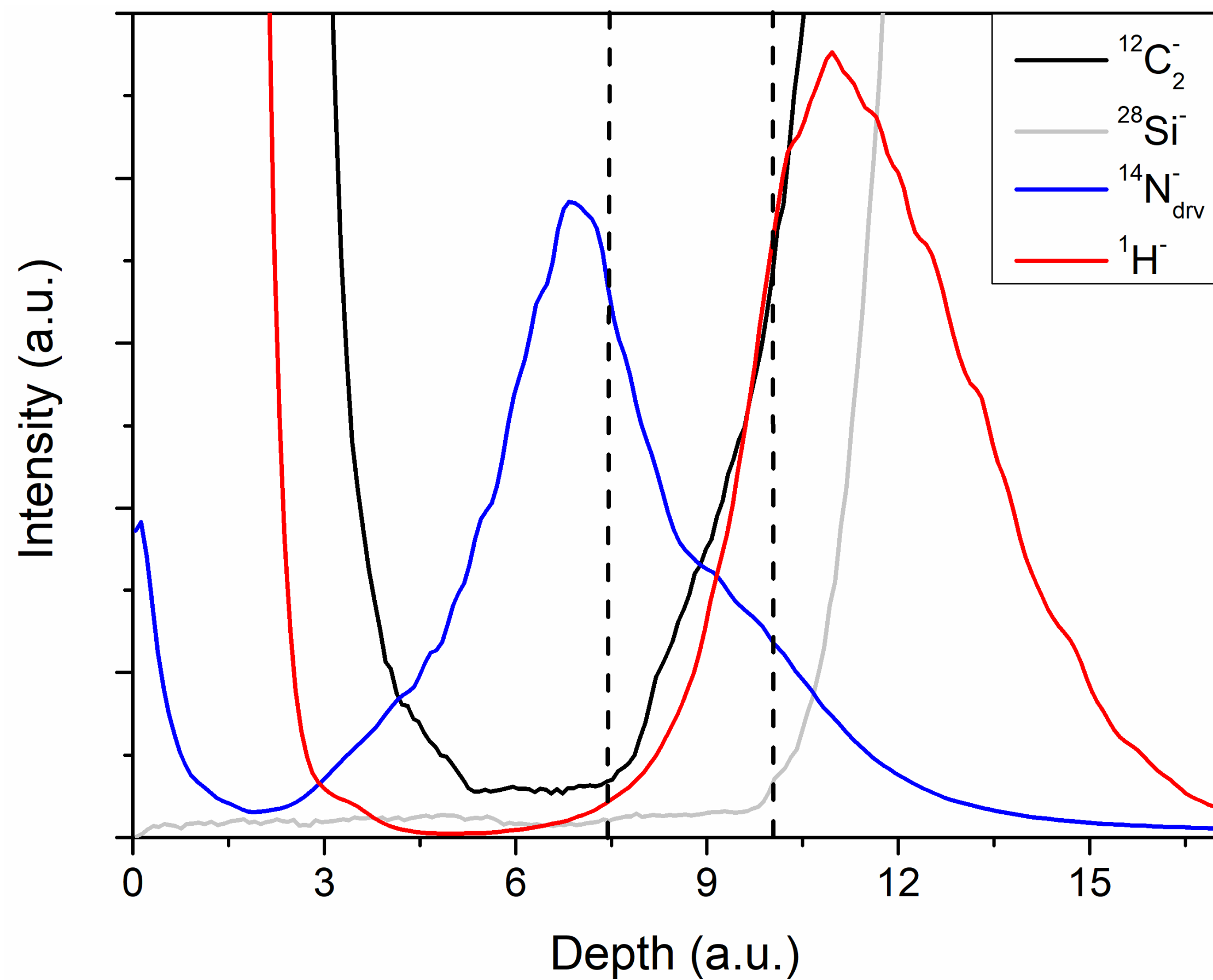
**2. Basic applications**

**3. Quantitative analysis**

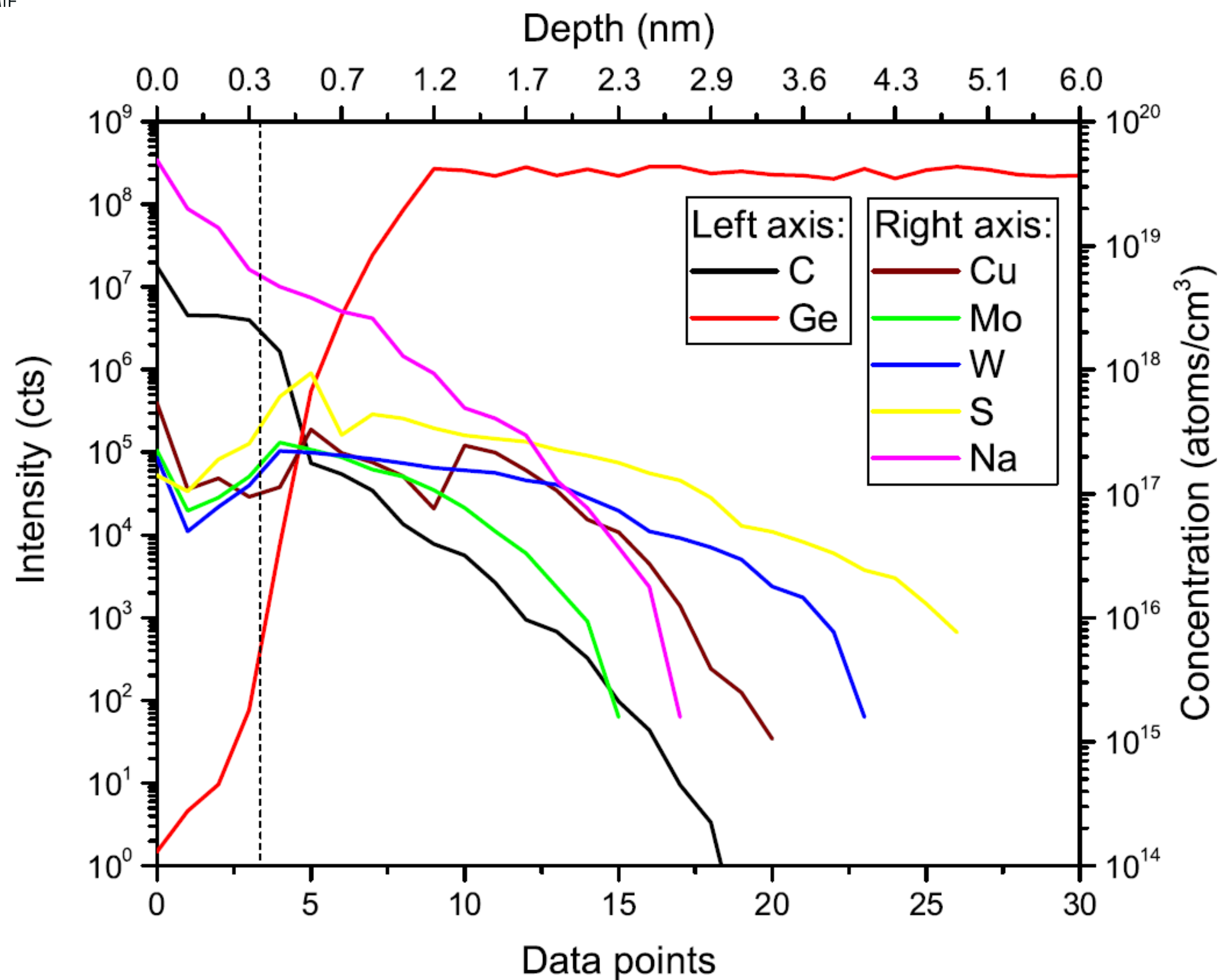
**4. CAMECA SC Ultra**

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# How clean is Graphene?



## Remarks

- 250 eV impact energy
- 45° incident angle
- Detection
- Localization?

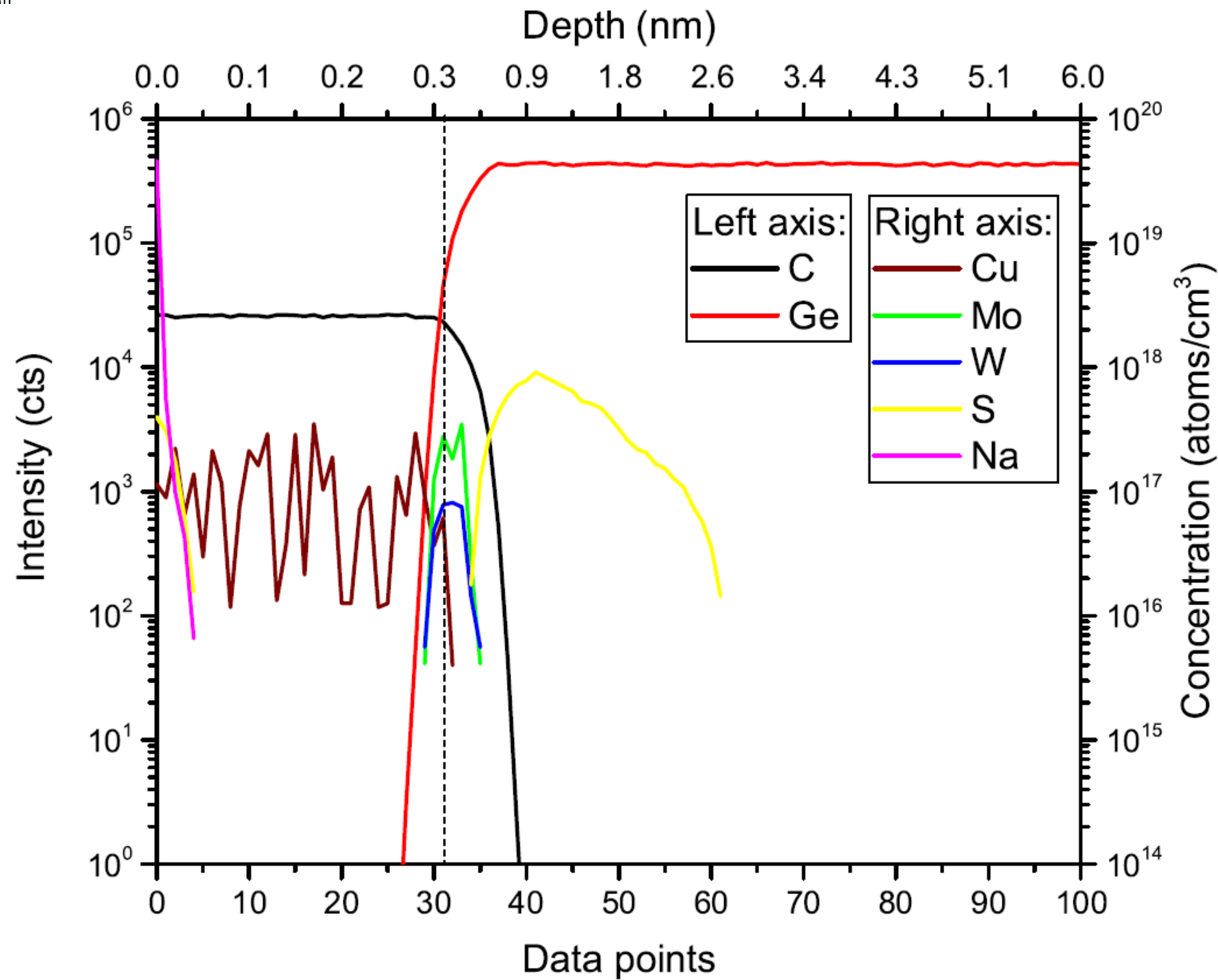
## PROBLEMS AND POTENTIAL SOLUTIONS

Problem	Potential solution	Resulting problems	Potential solution	Conclusion
Transition layer	Lower beam density	Signals intensity reduction	Higher integration time	Still a few data points per graphene
Ion mixing	Lower impact energy	Signals intensity reduction	Higher integration time	Still a few data points per graphene
Preferential sputtering	Higher impact energy	Bigger ion mixing	?	Not feasible

## REALISTIC SOLUTION – HIGH INCIDENT ANGEL

Angle	Data points	Transition layer	Ion mixing	Preferential sputtering	Acquisition time	Detection limits (ppm)
45°	4 for graphene	Severe	Severe	Severe	5 minutes	0.2 – 1.5
75°	30 for graphene	Negligible	Negligible	Negligible	3 hours	0.8 – 2.9

# Enhanced procedure?

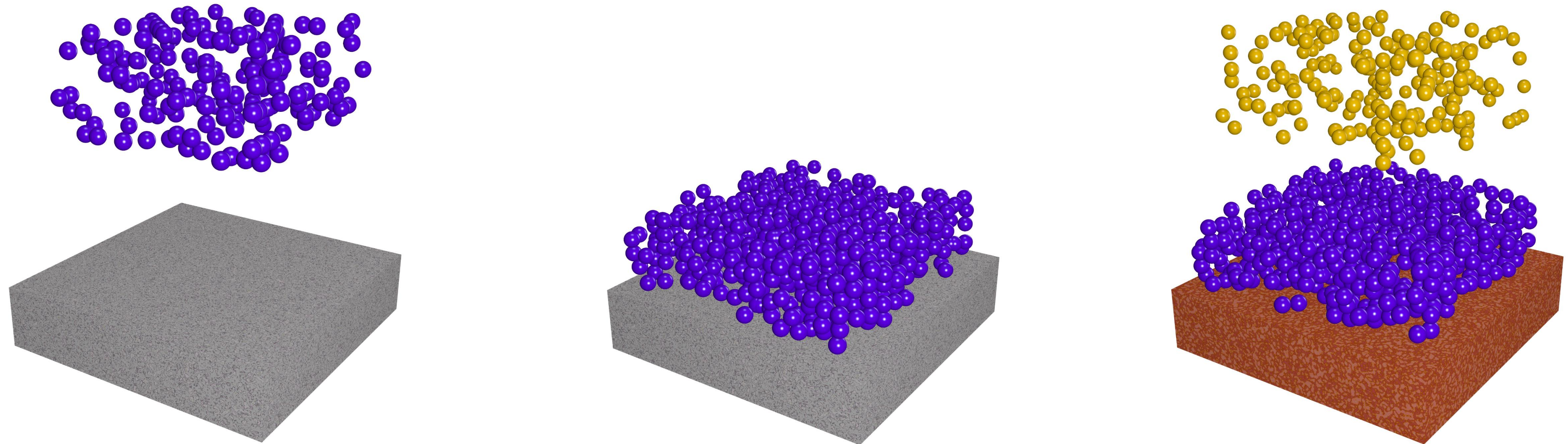


## Remarks

- 250 eV impact energy
- 75° incident angle
- Detection
- Localization!

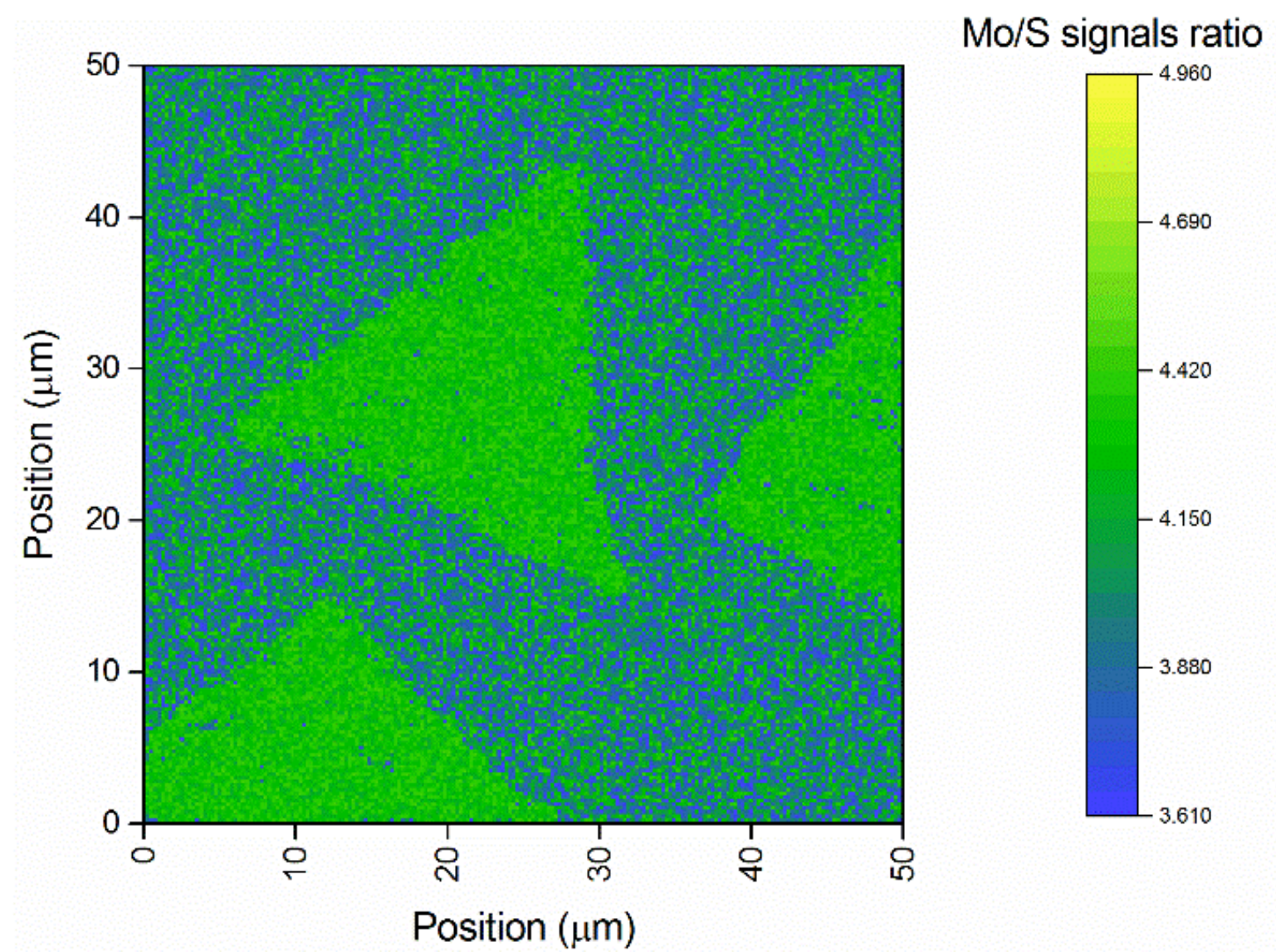


# Molybdenum disulfide

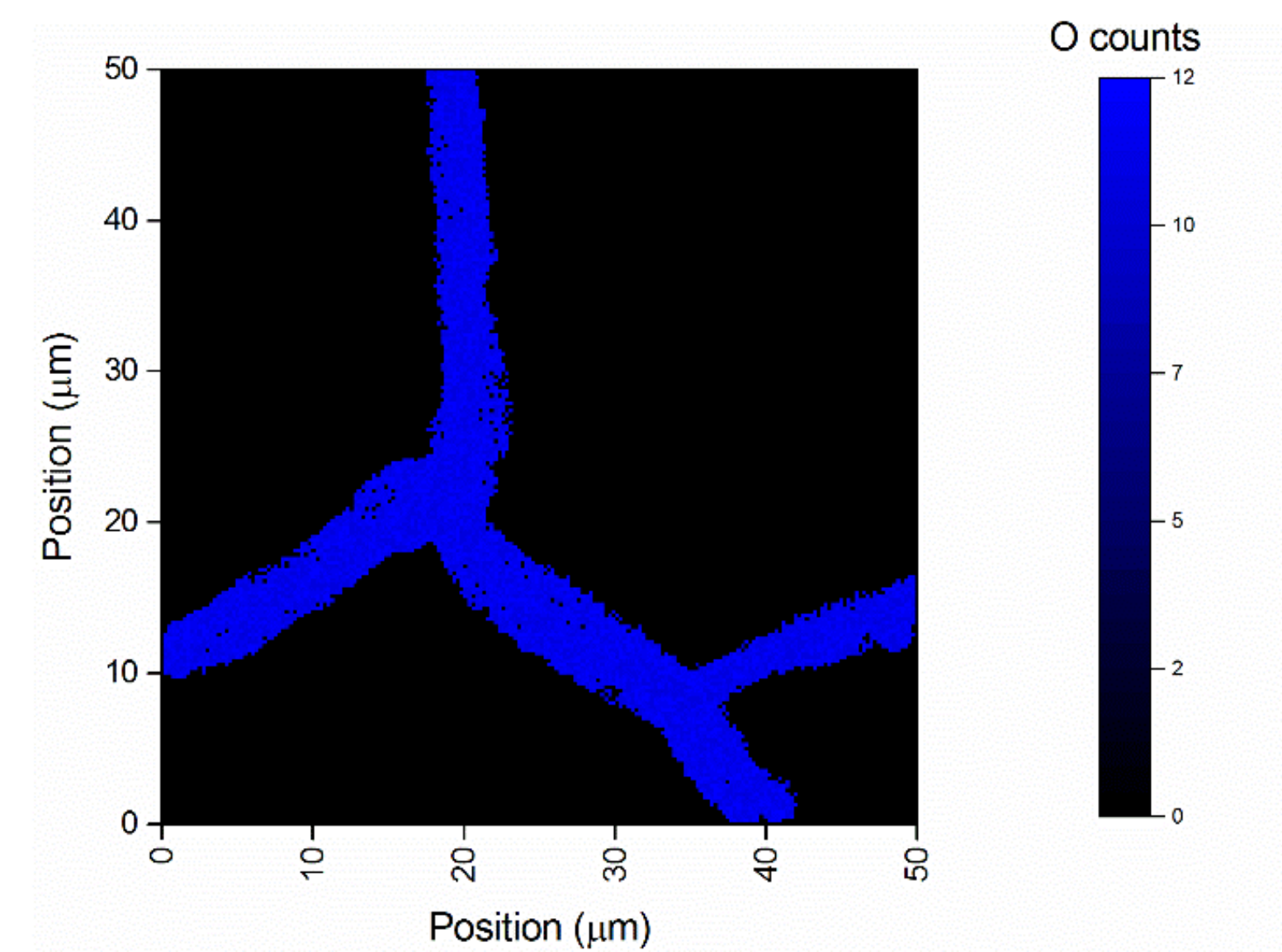
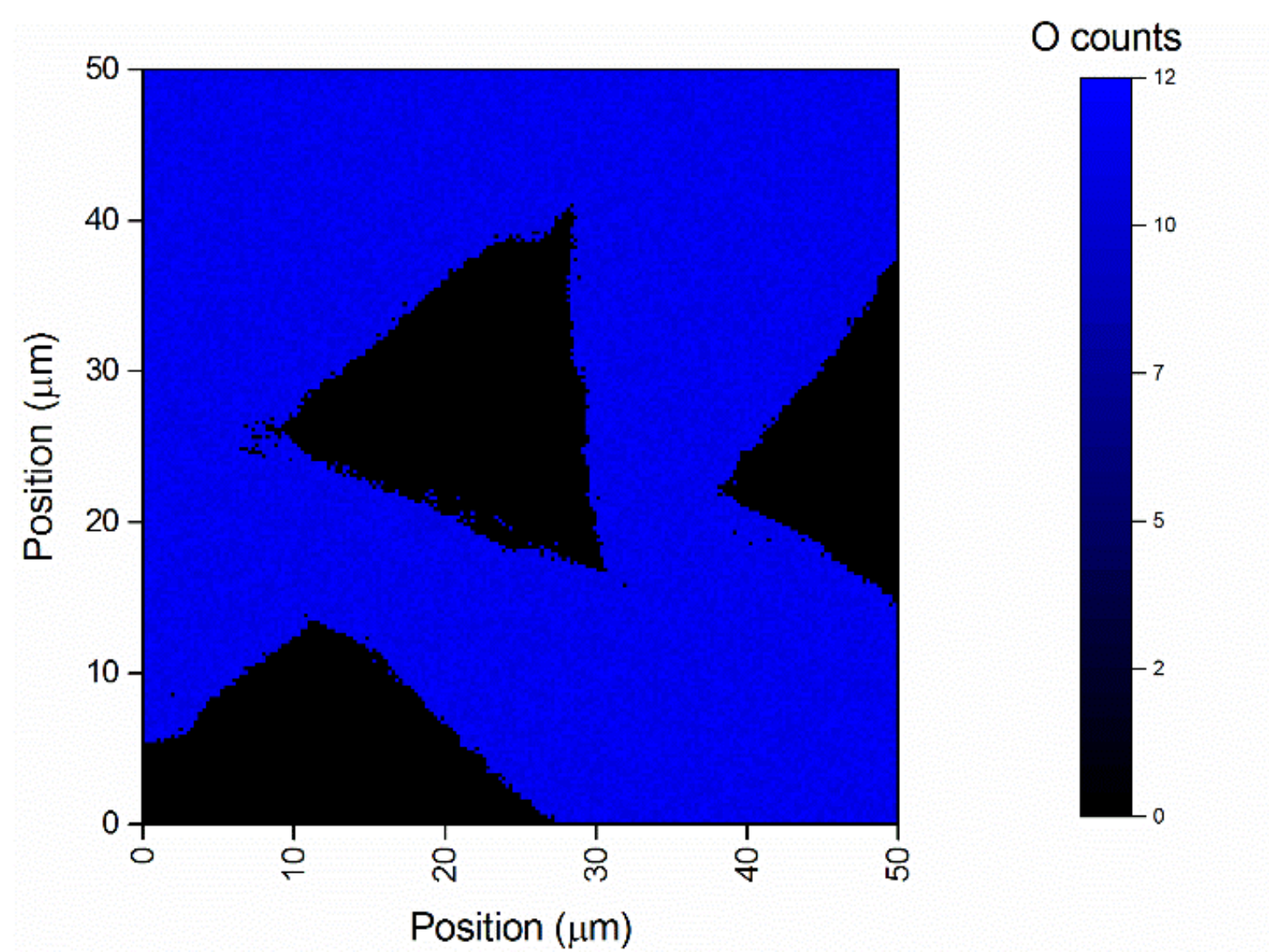
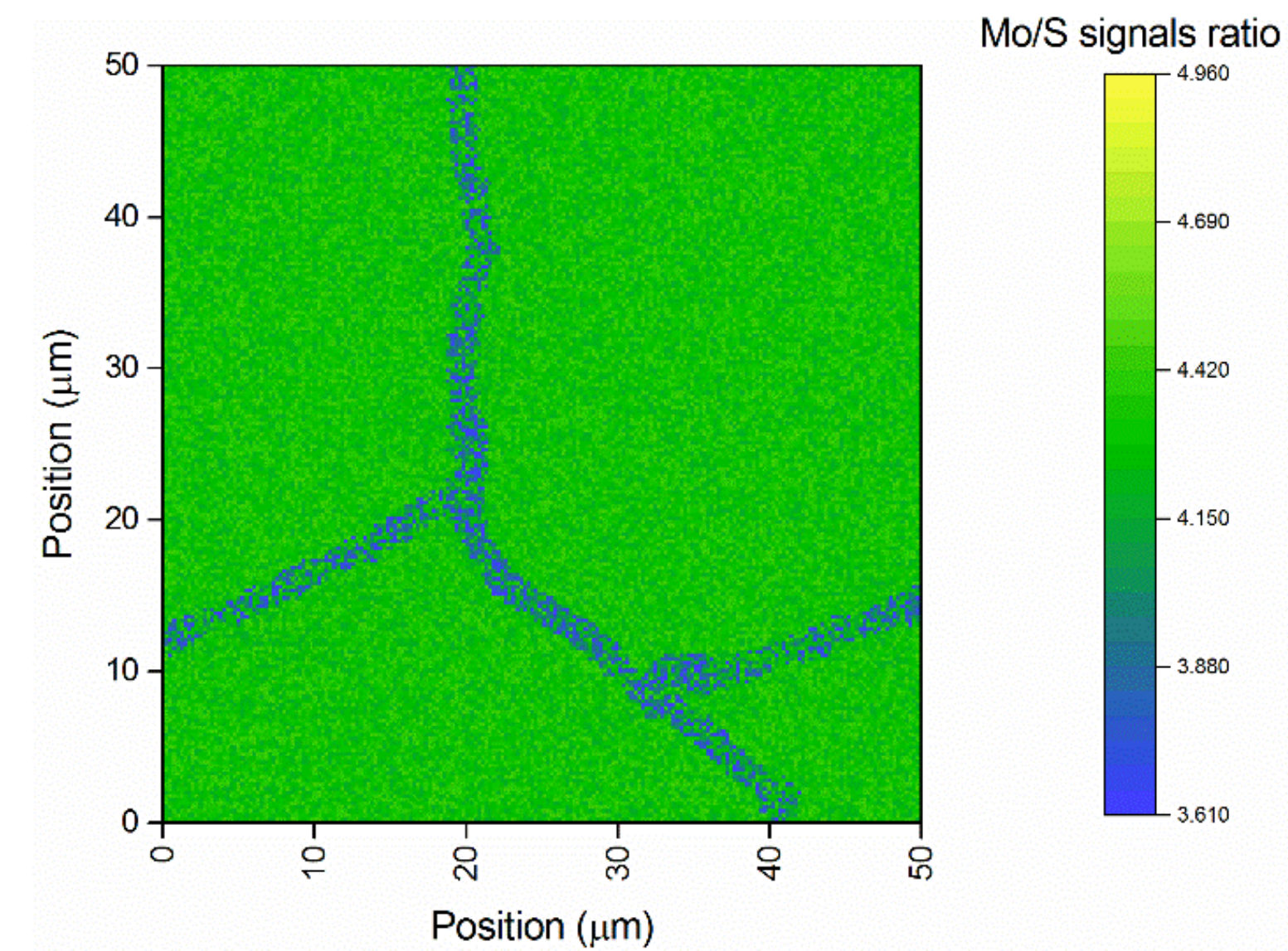




$\text{SiO}_2$

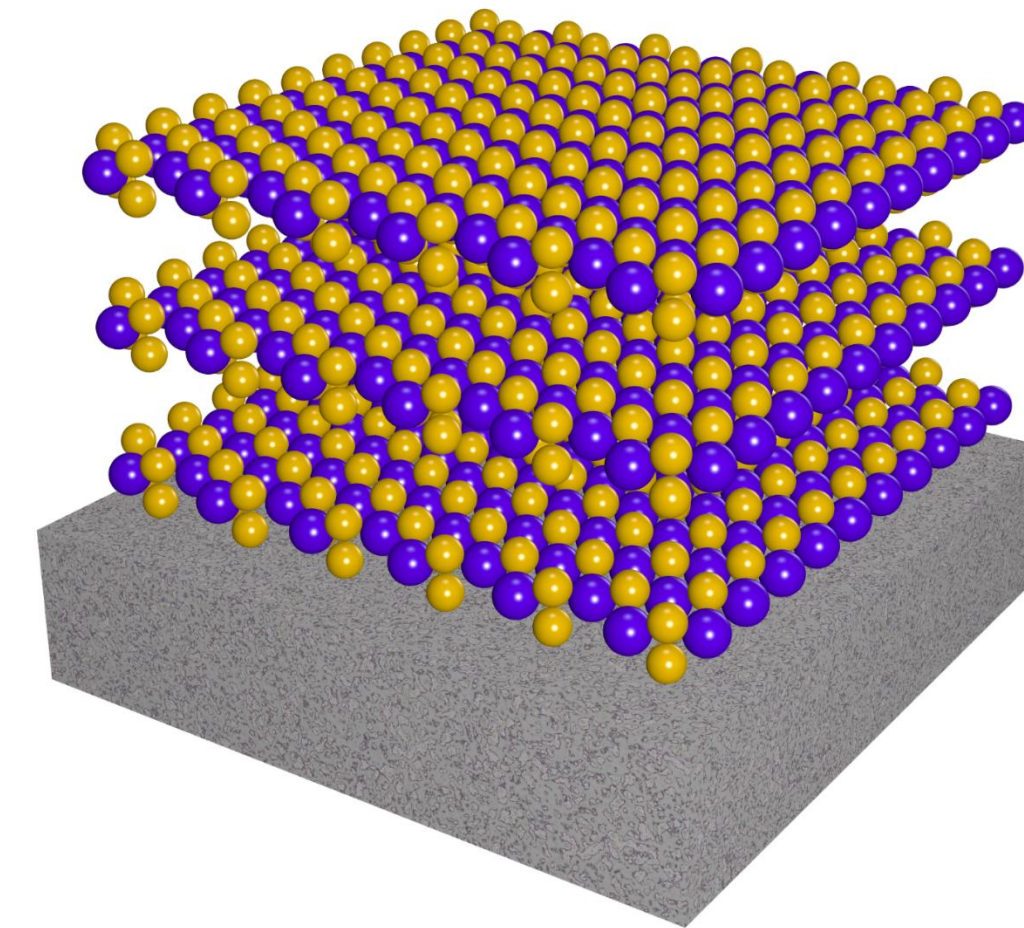
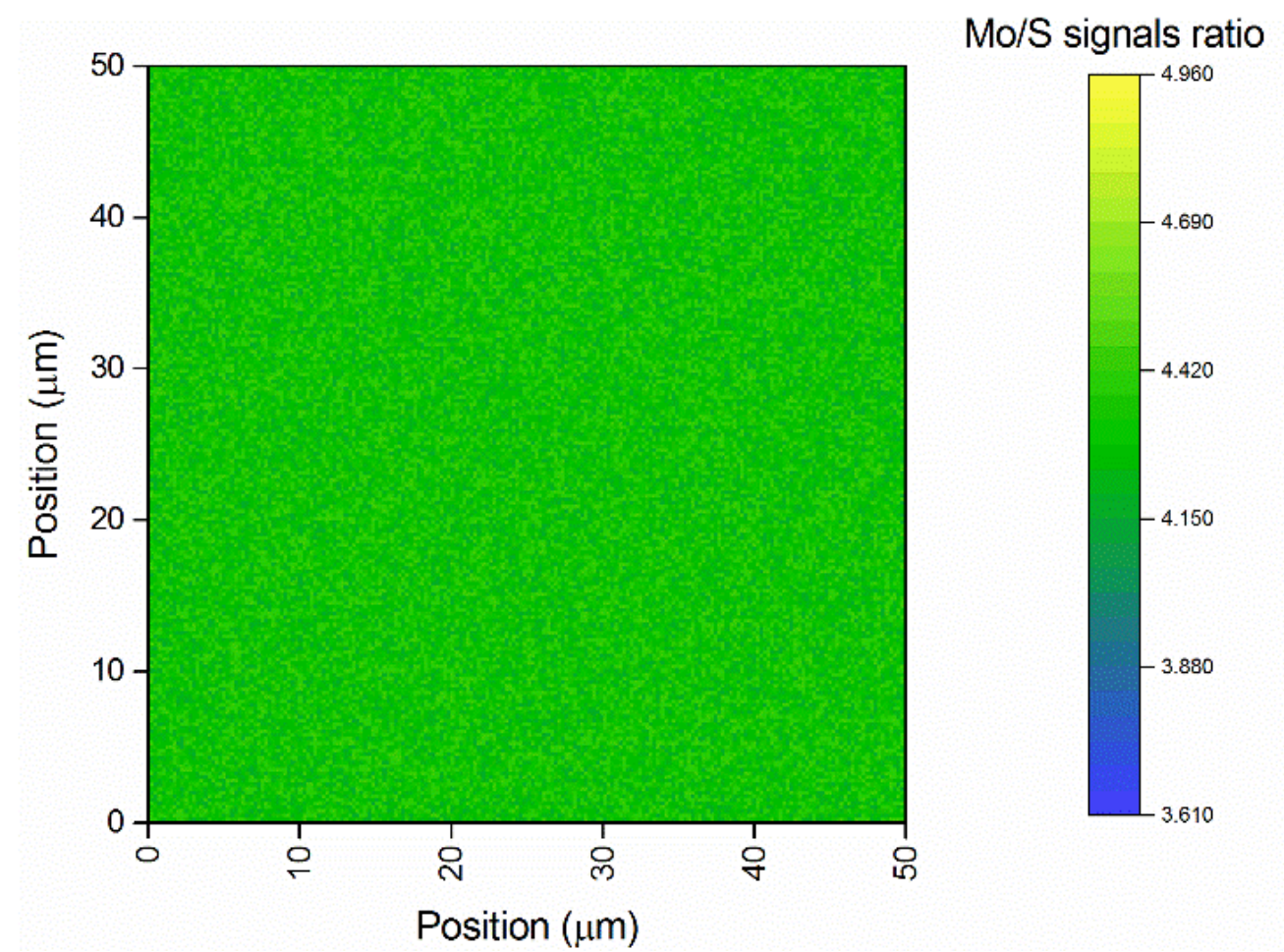
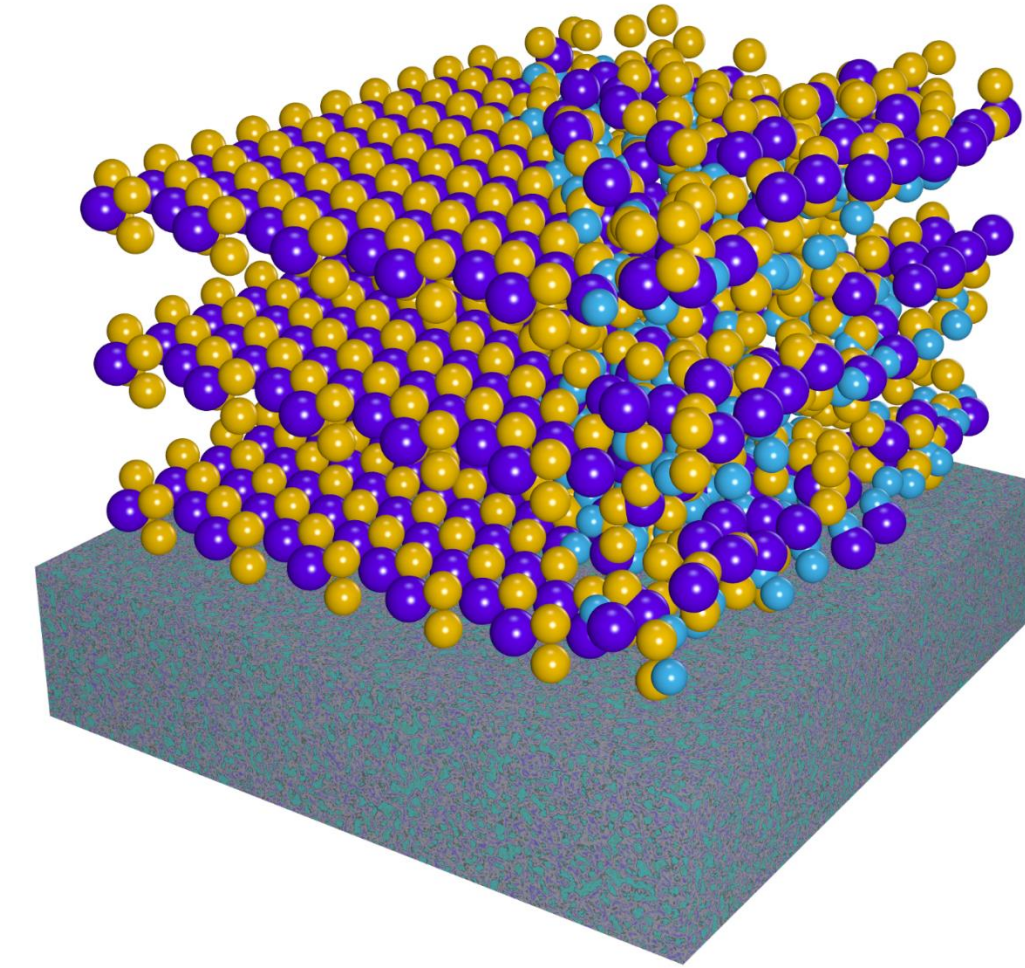
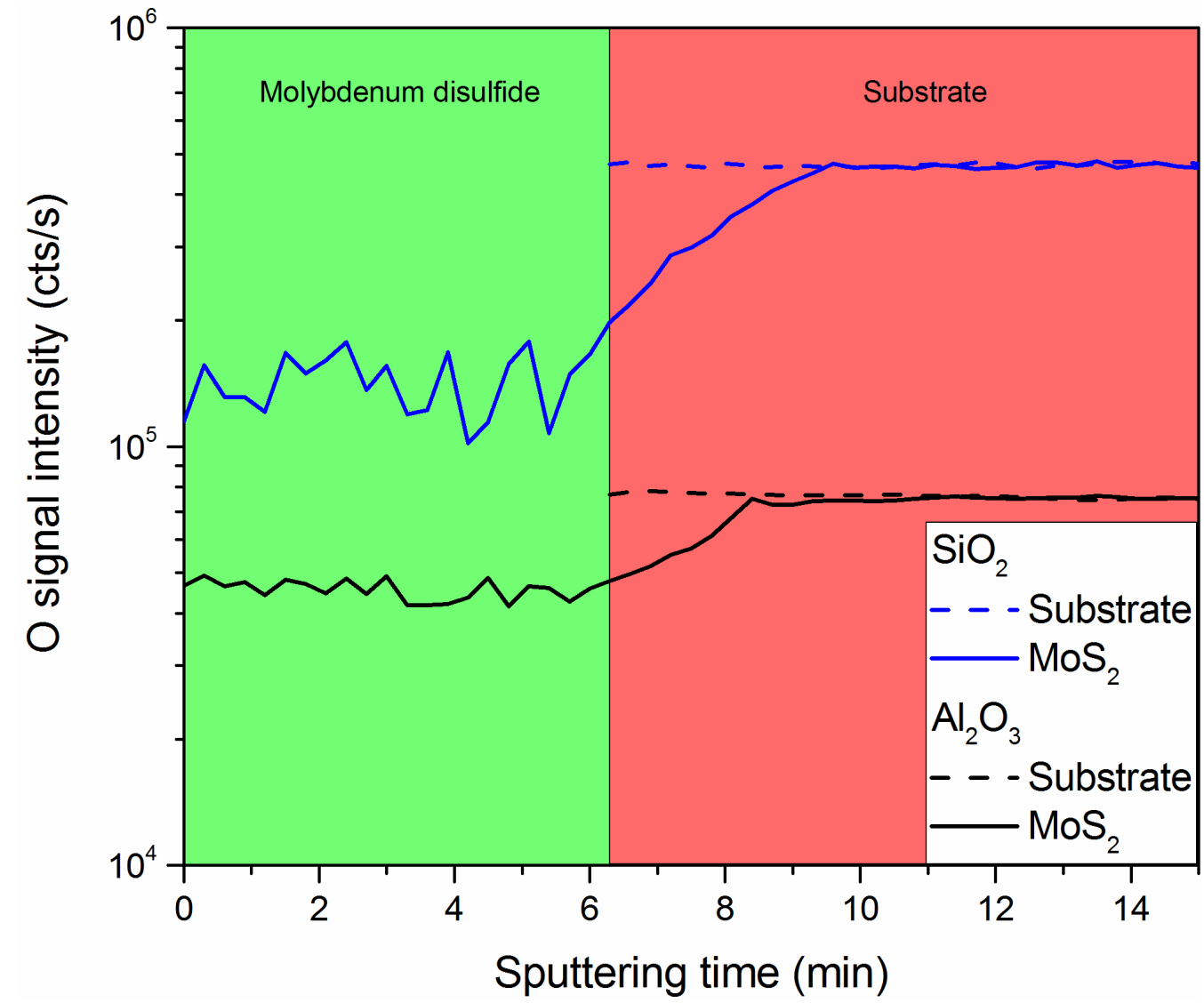


$\text{Al}_2\text{O}_3$

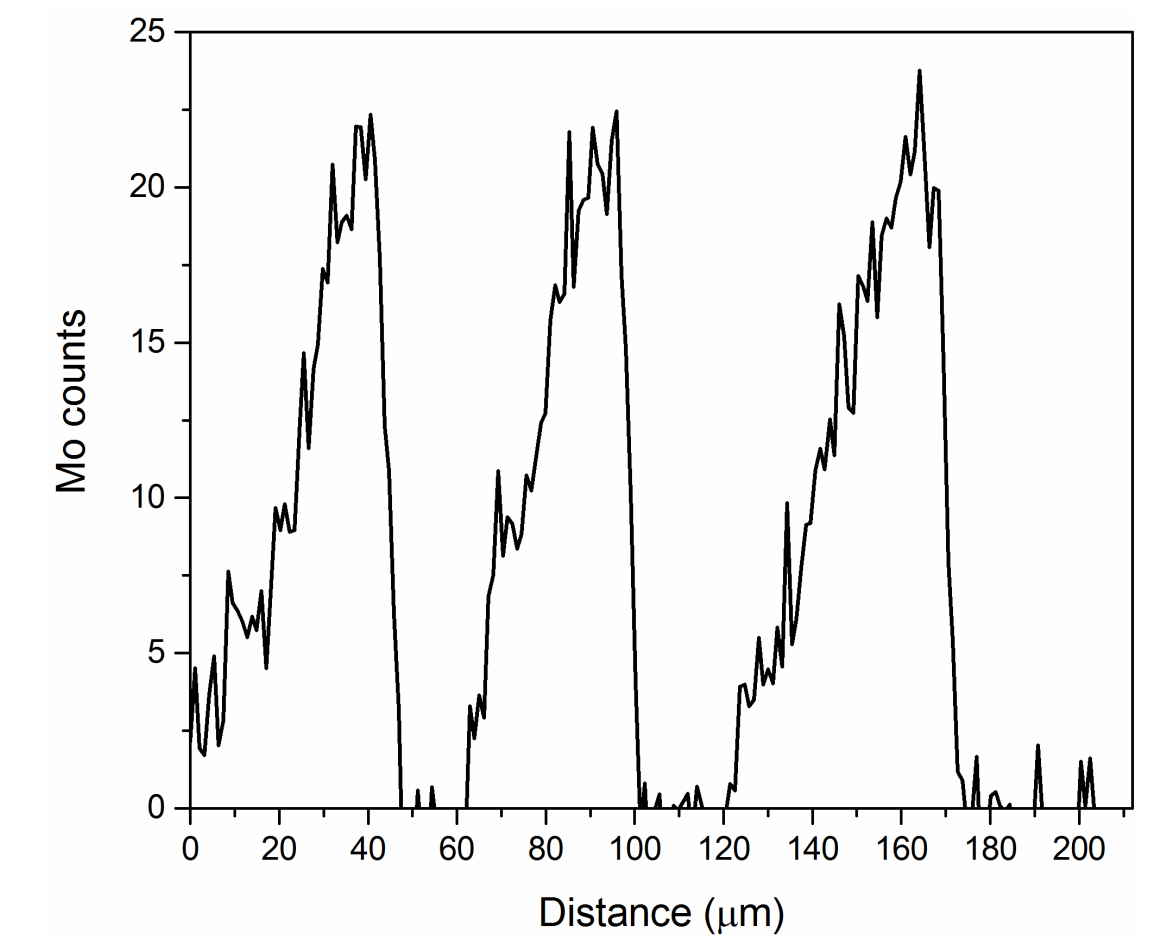
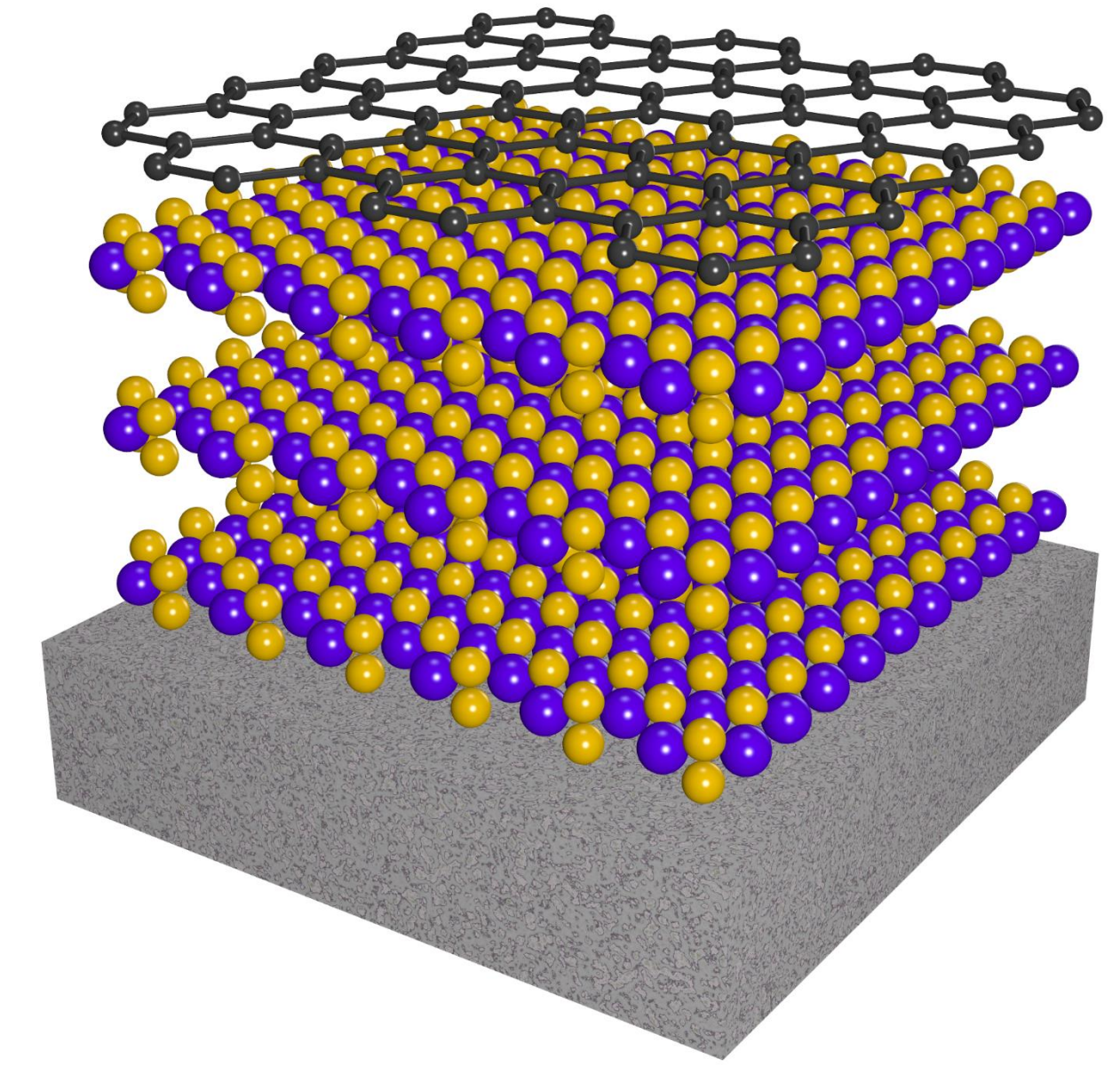
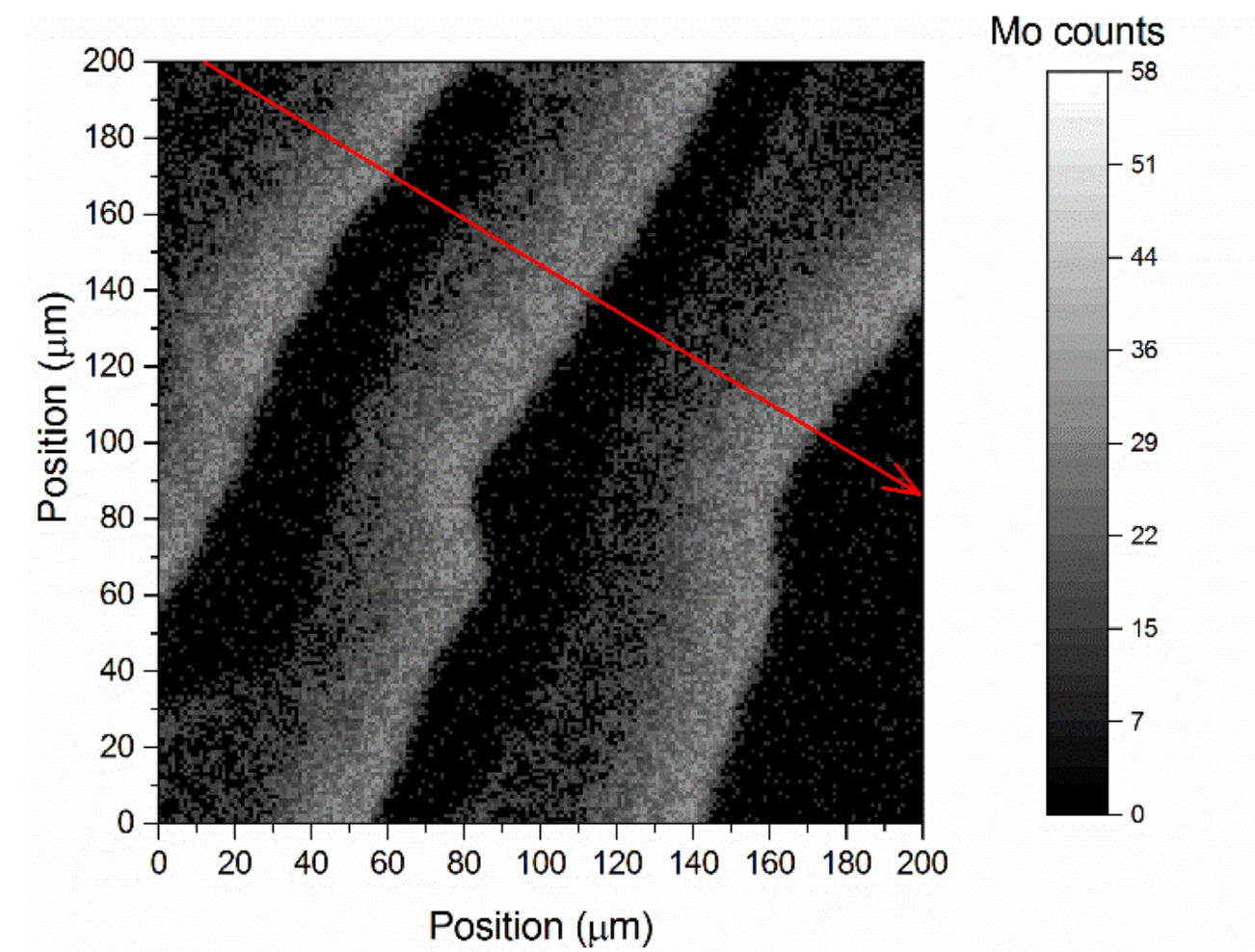
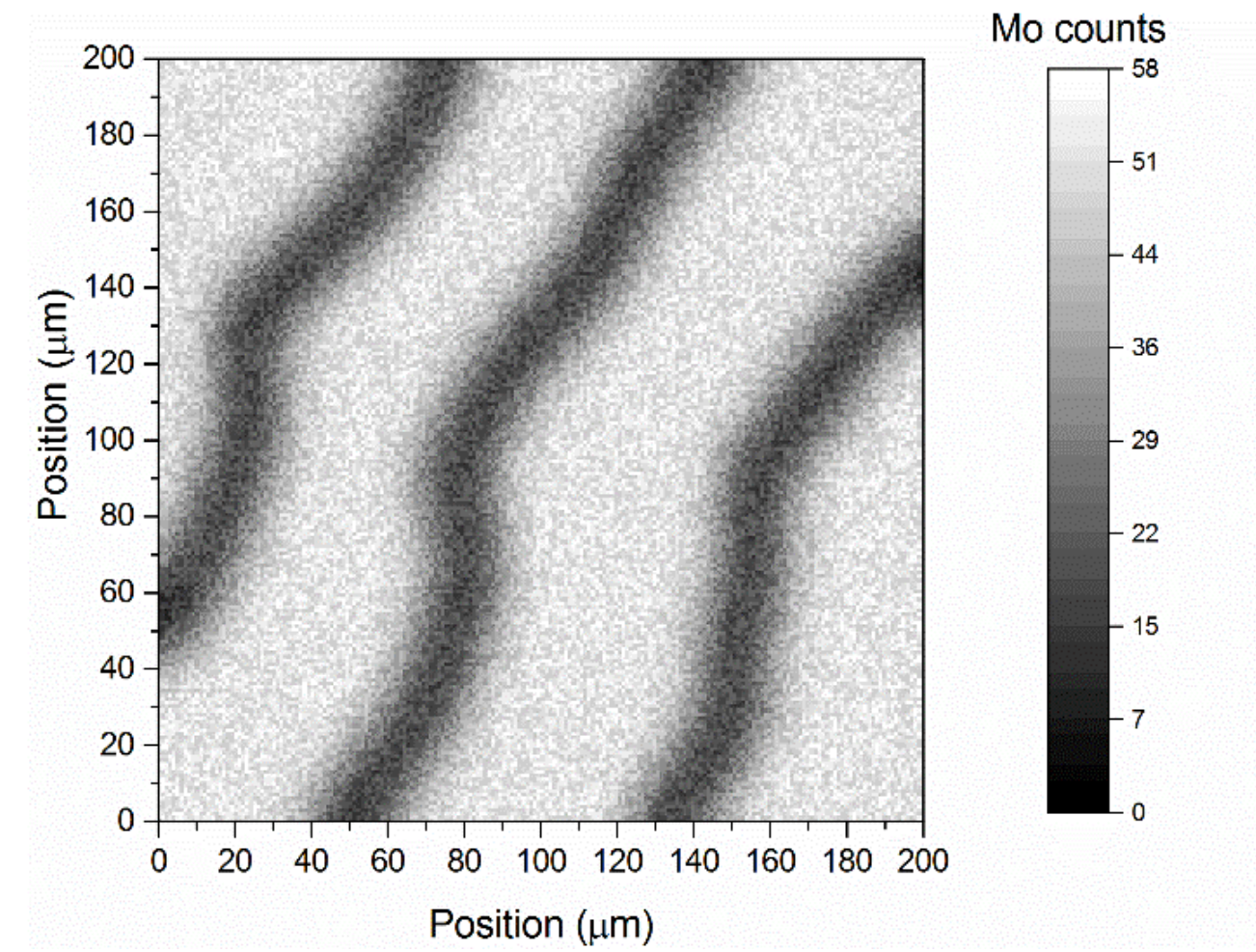
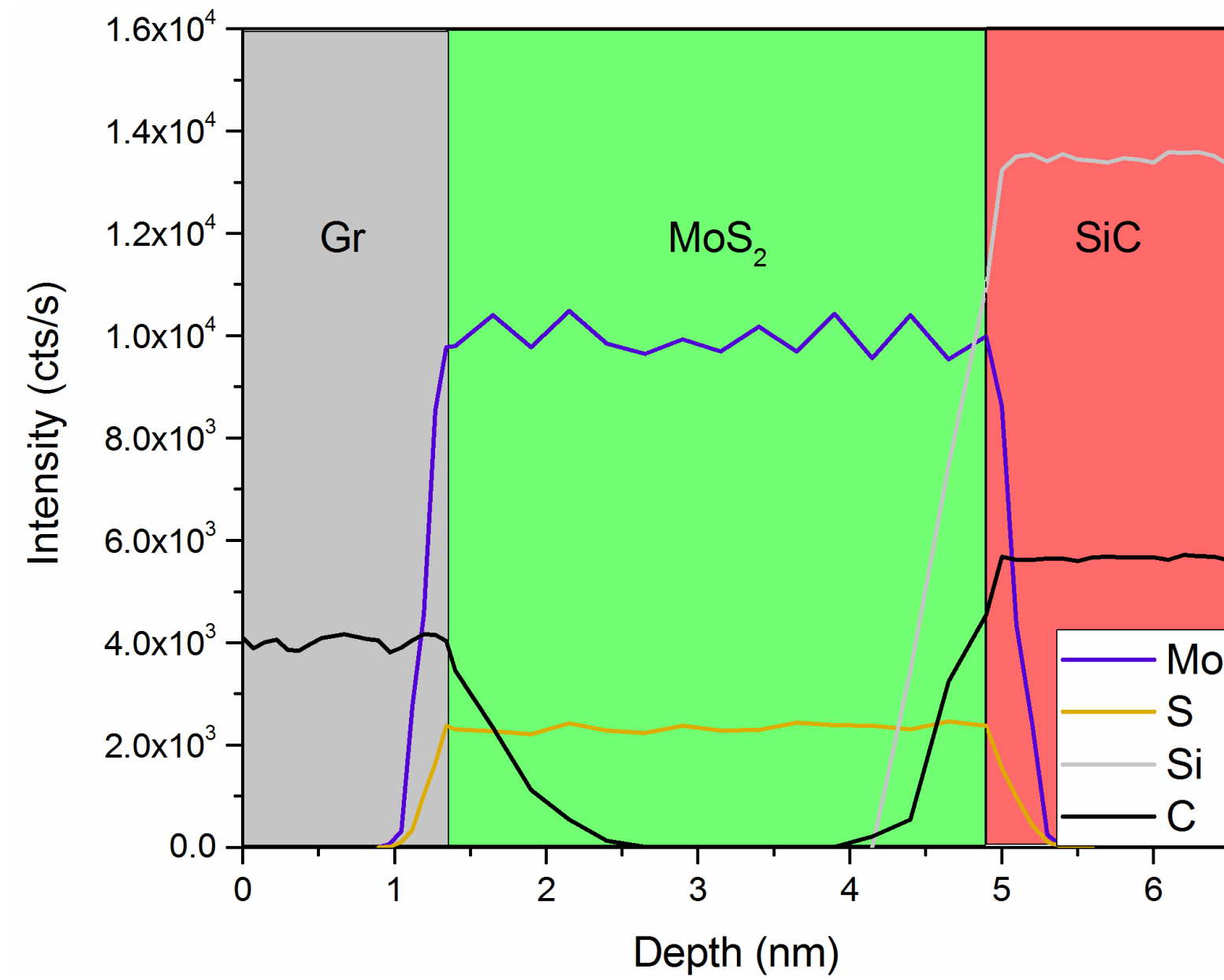




# Substrate type / procedure optimization

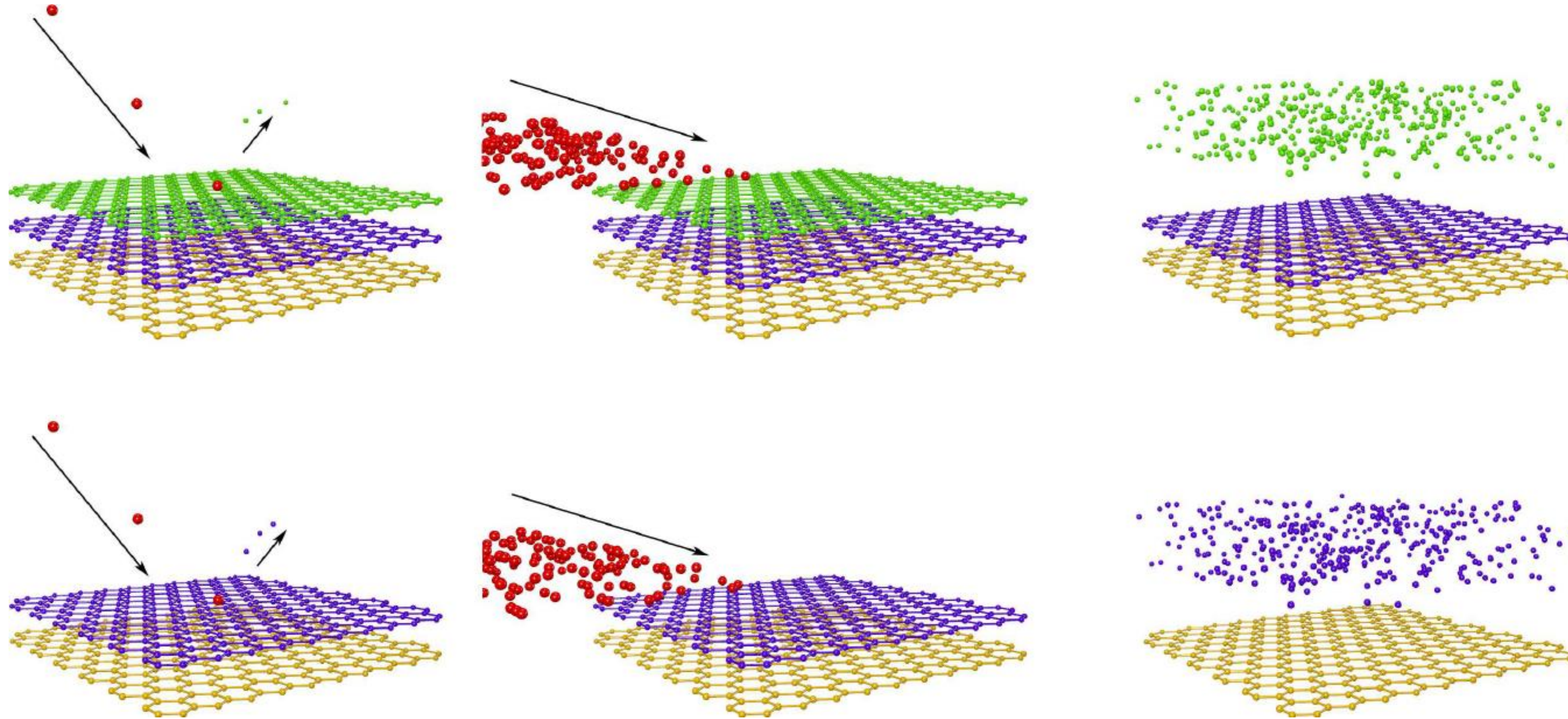








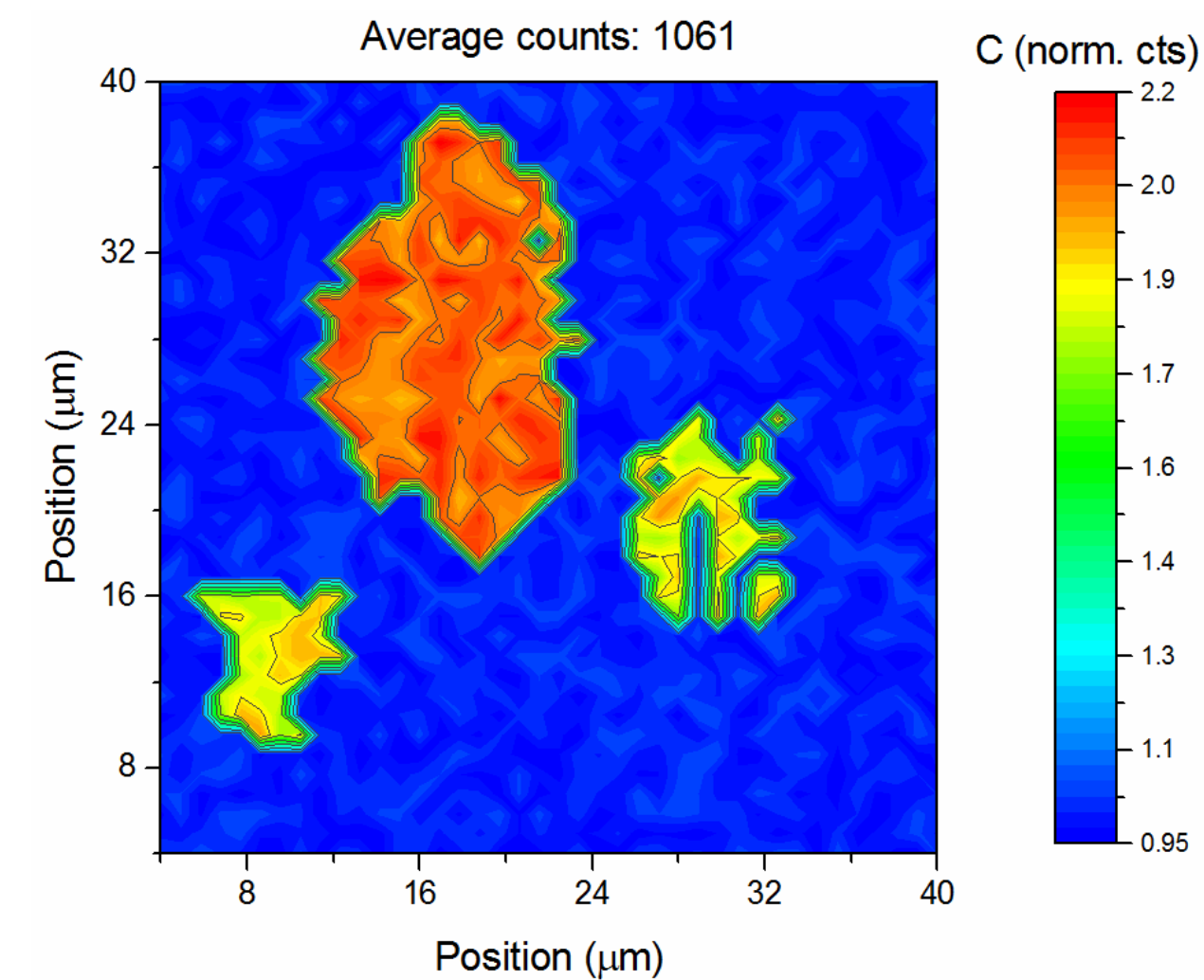
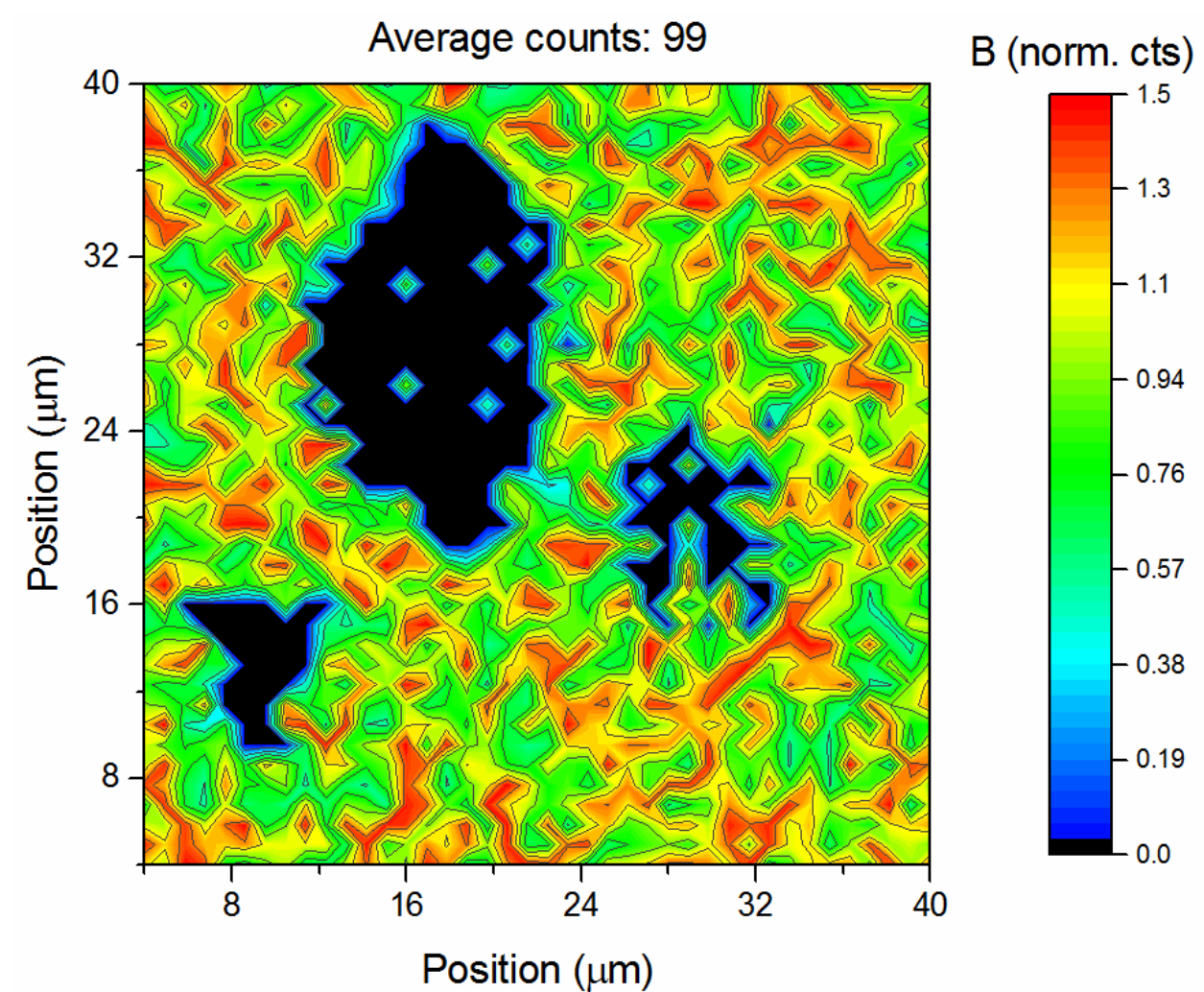
# Hexagonal boron nitride



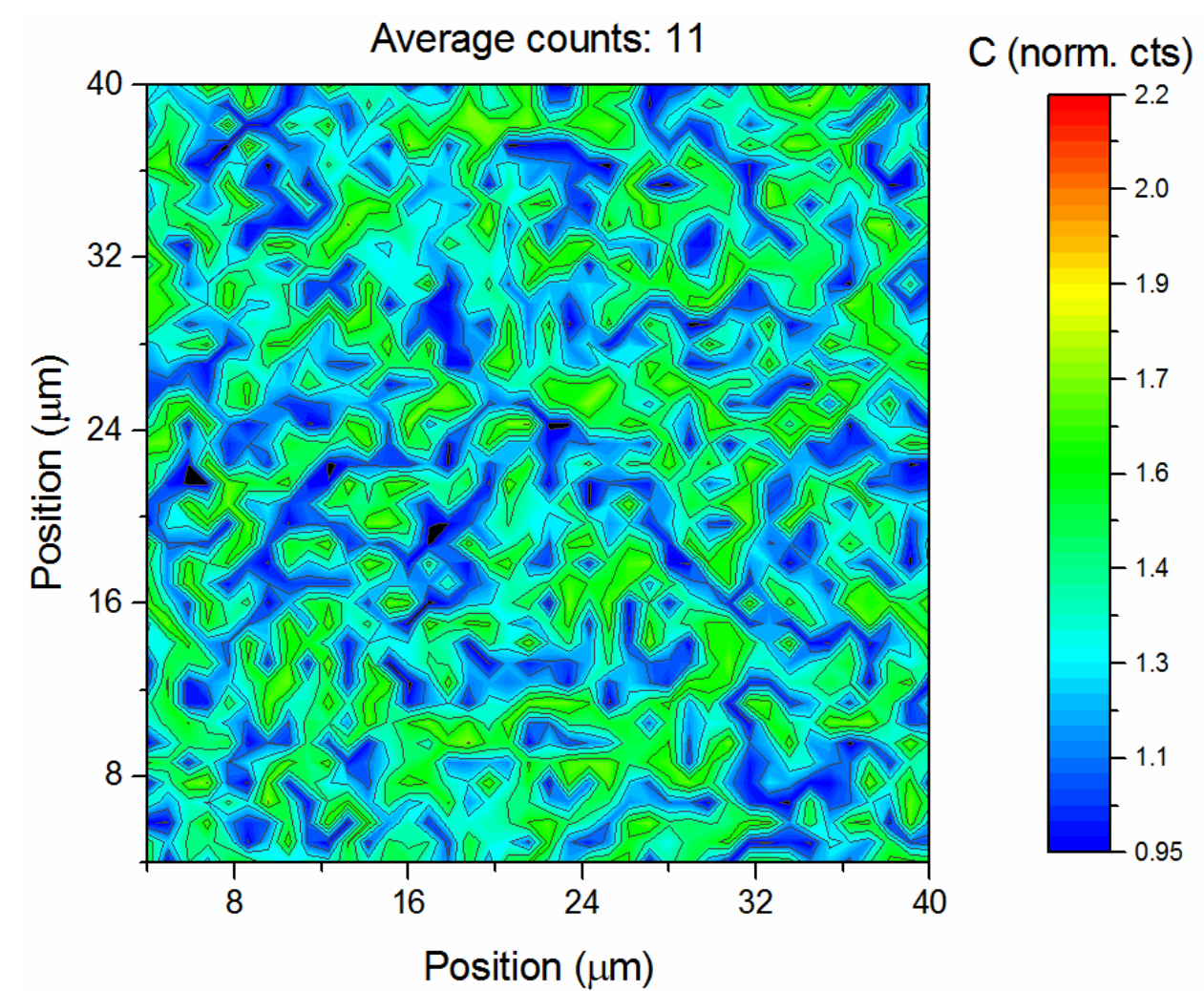
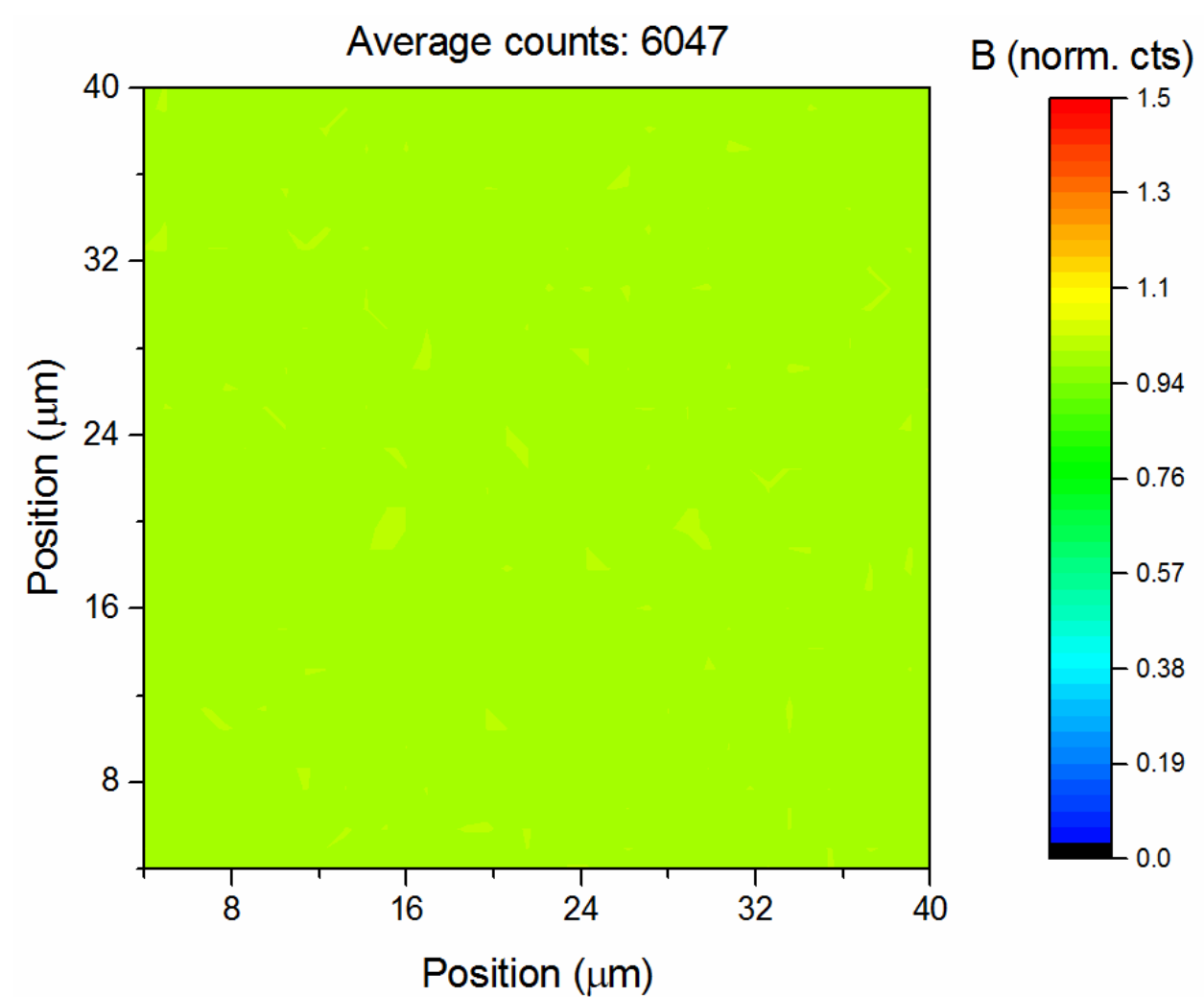


# Different carrier gas

Ar



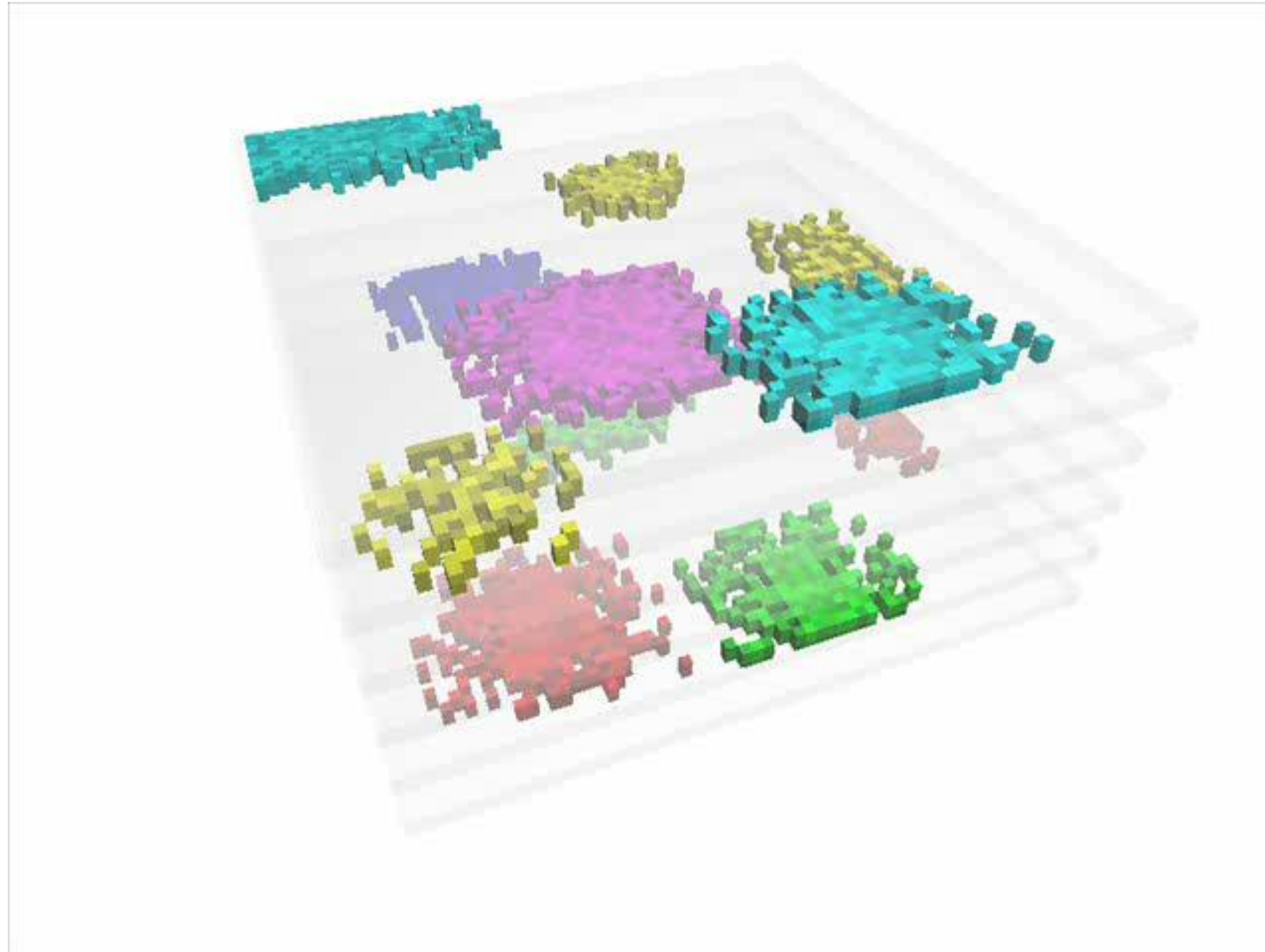
H<sub>2</sub>



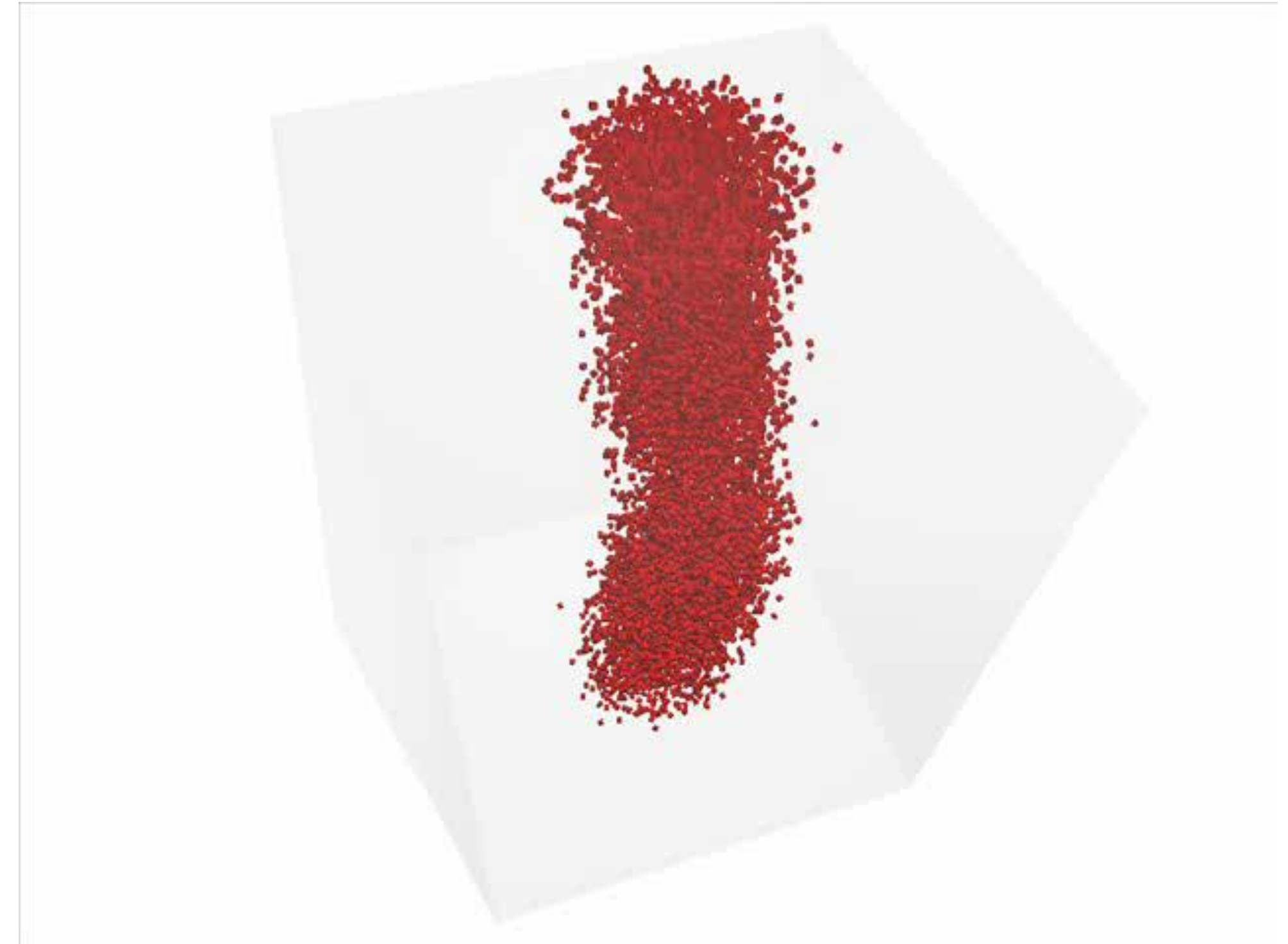


# Different reactor pressure

High

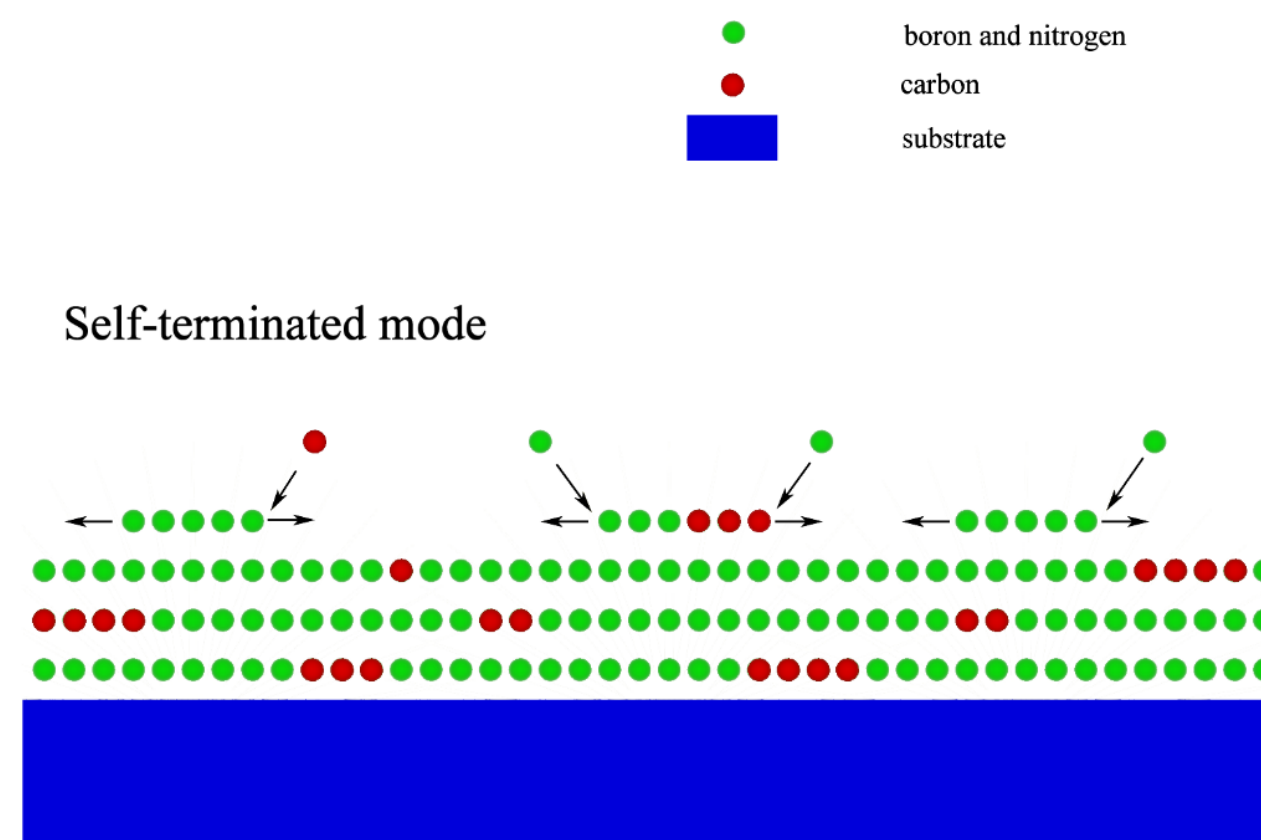
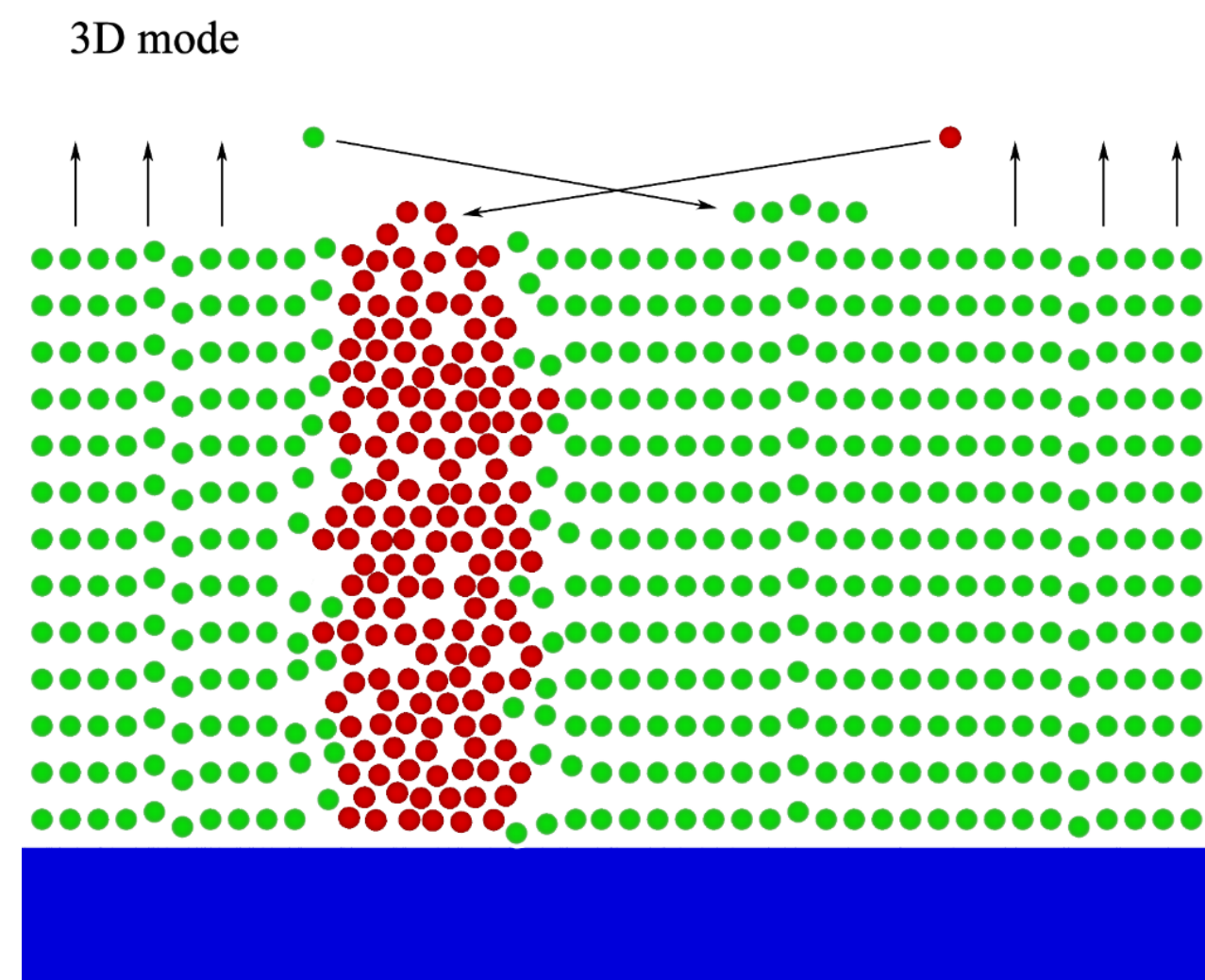


Low



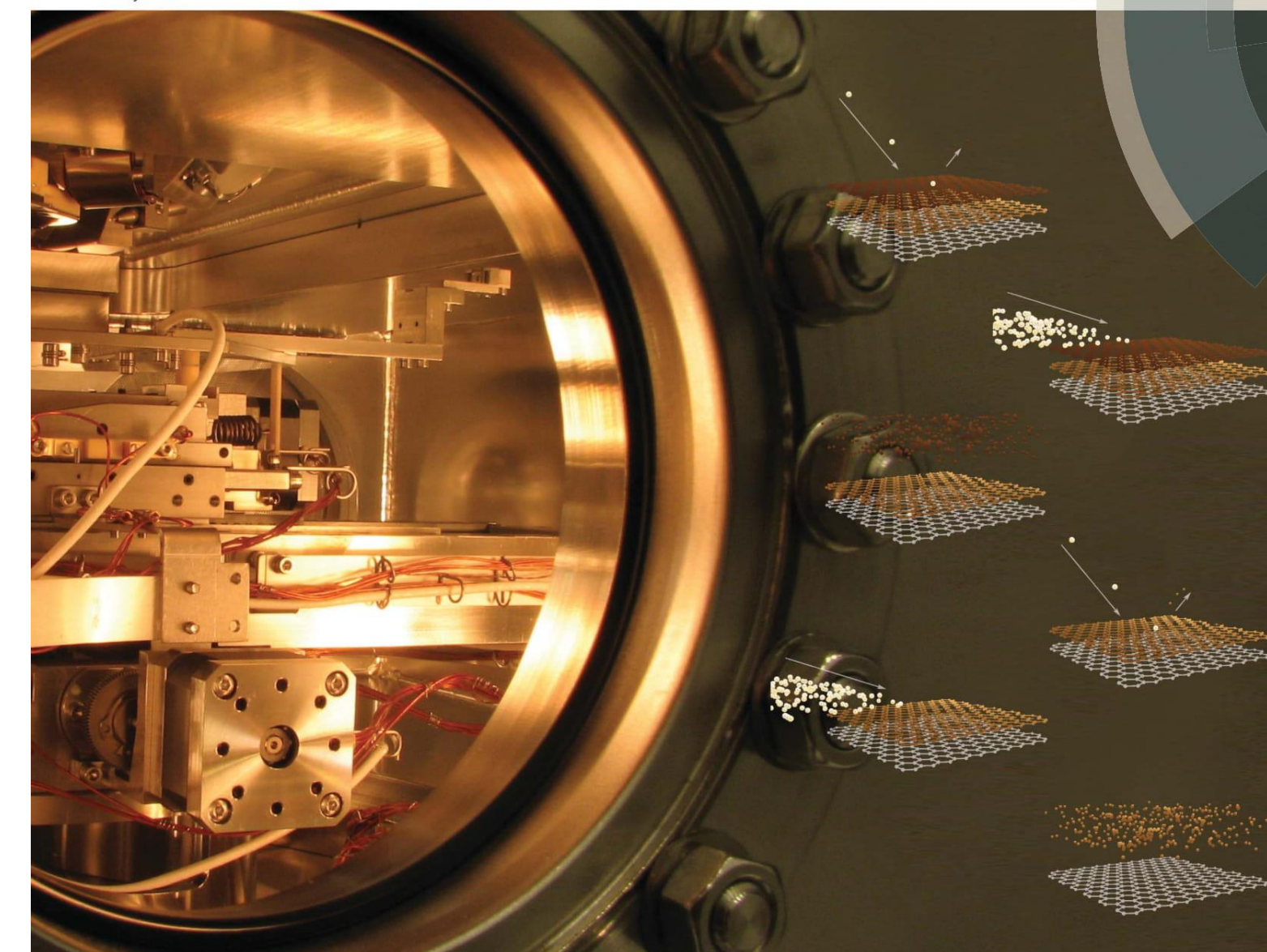


# hBN - summary



## JAAS

Journal of Analytical Atomic Spectrometry  
rsc.li/jaas



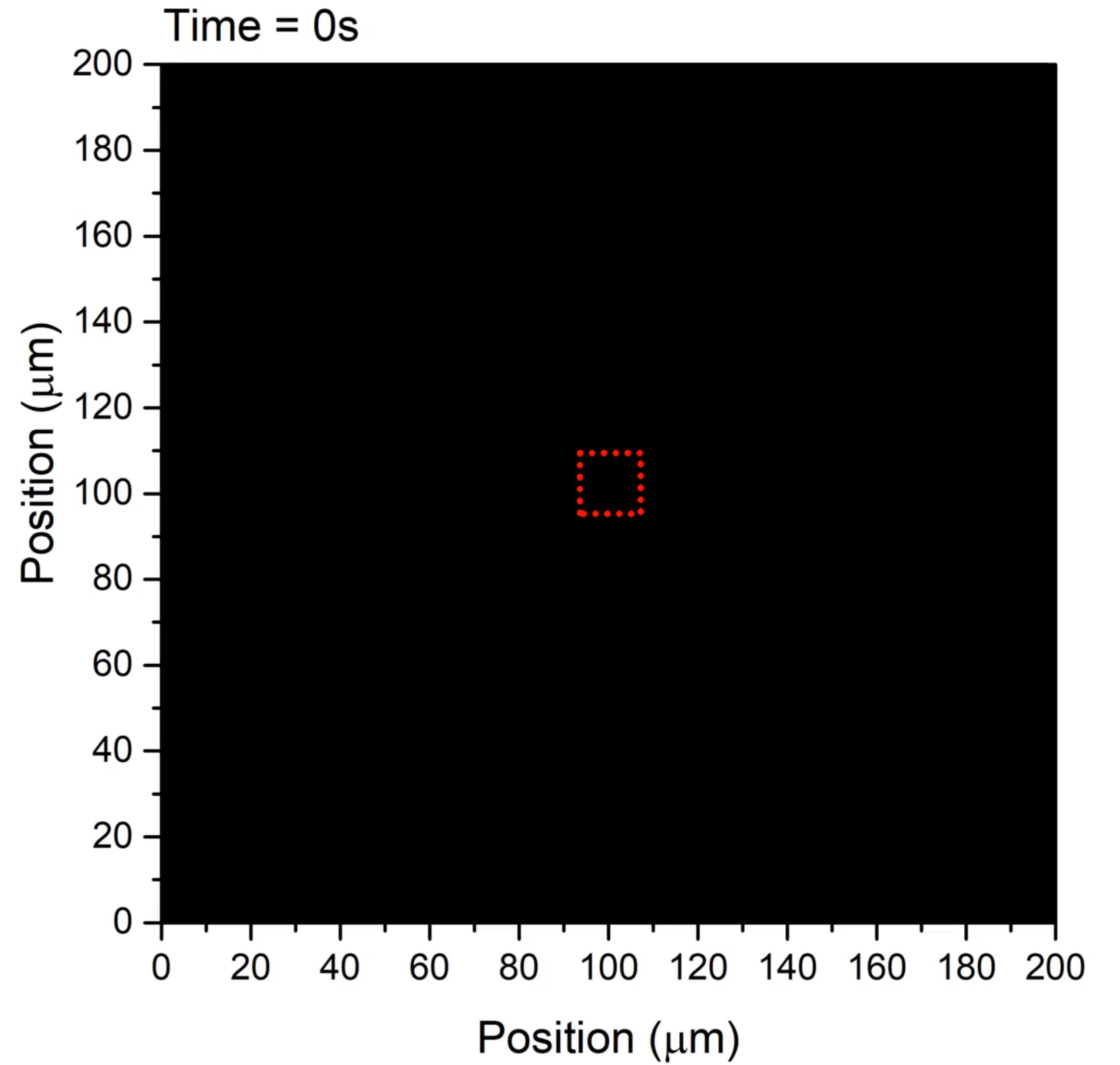
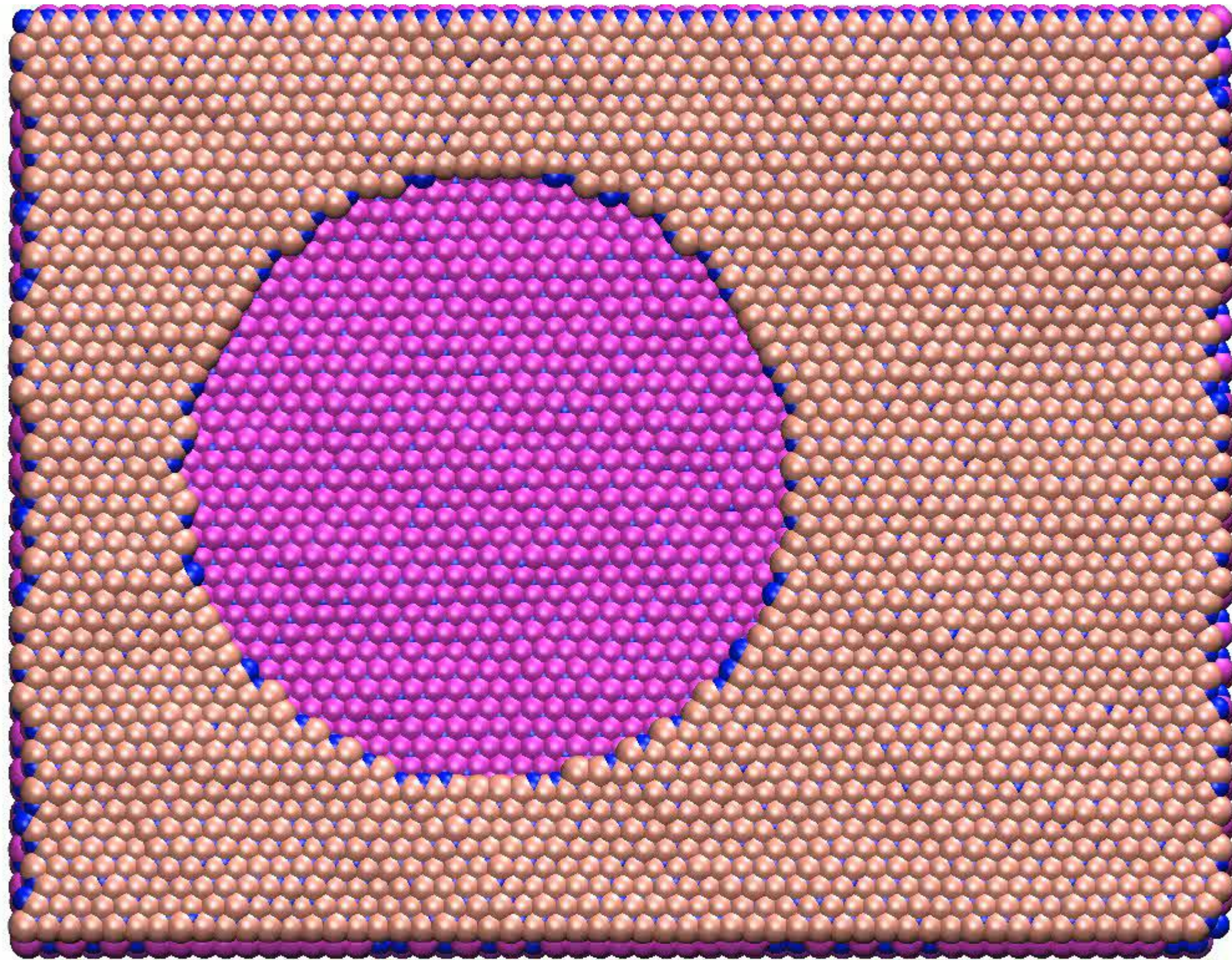
ISSN 0267-9477



PAPER  
Pawel Piotr Michatowski *et al.*  
Secondary ion mass spectrometry investigation of carbon grain formation in boron nitride epitaxial layers with atomic depth resolution

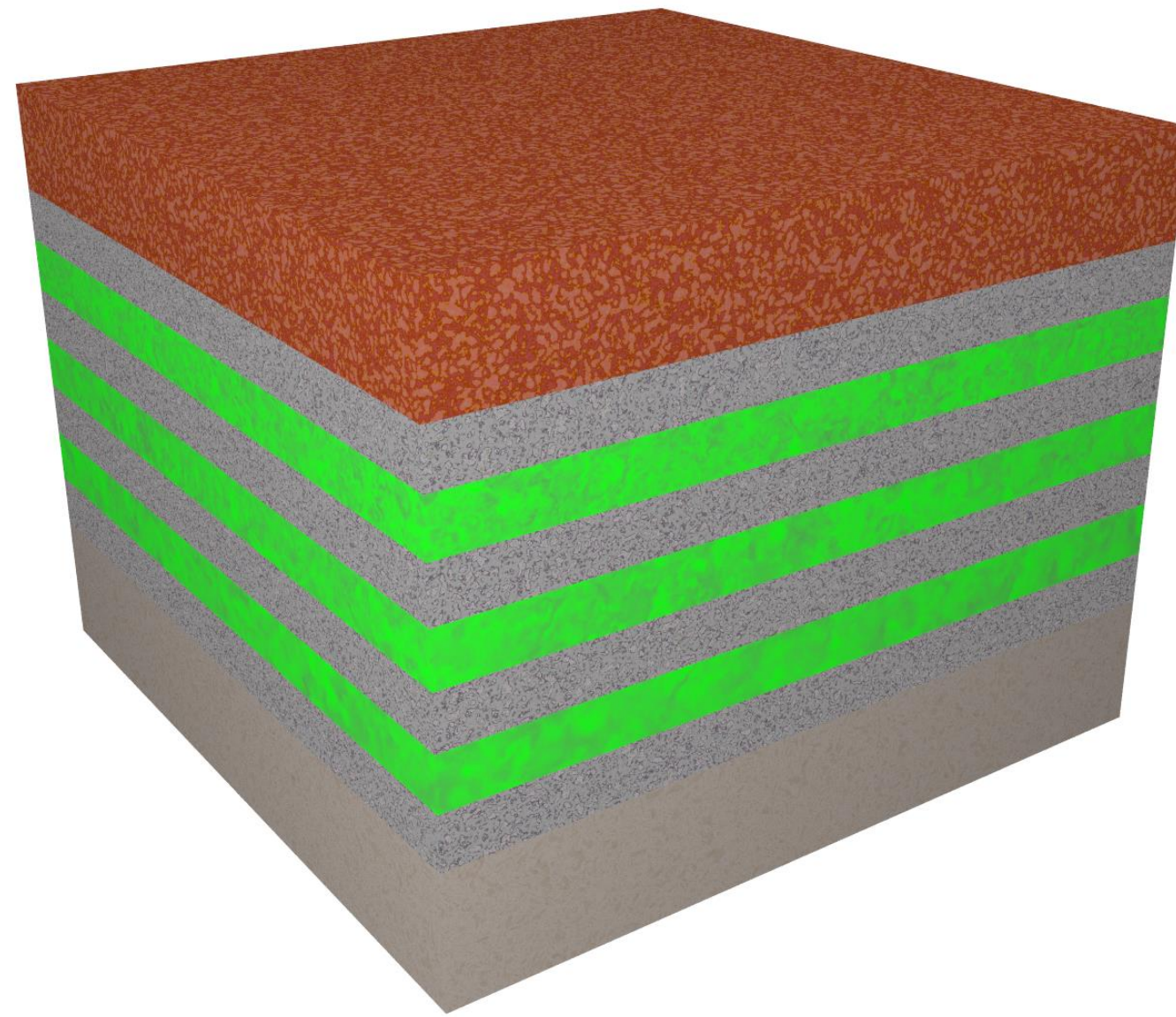


# How does it work?





# InGaN QWs

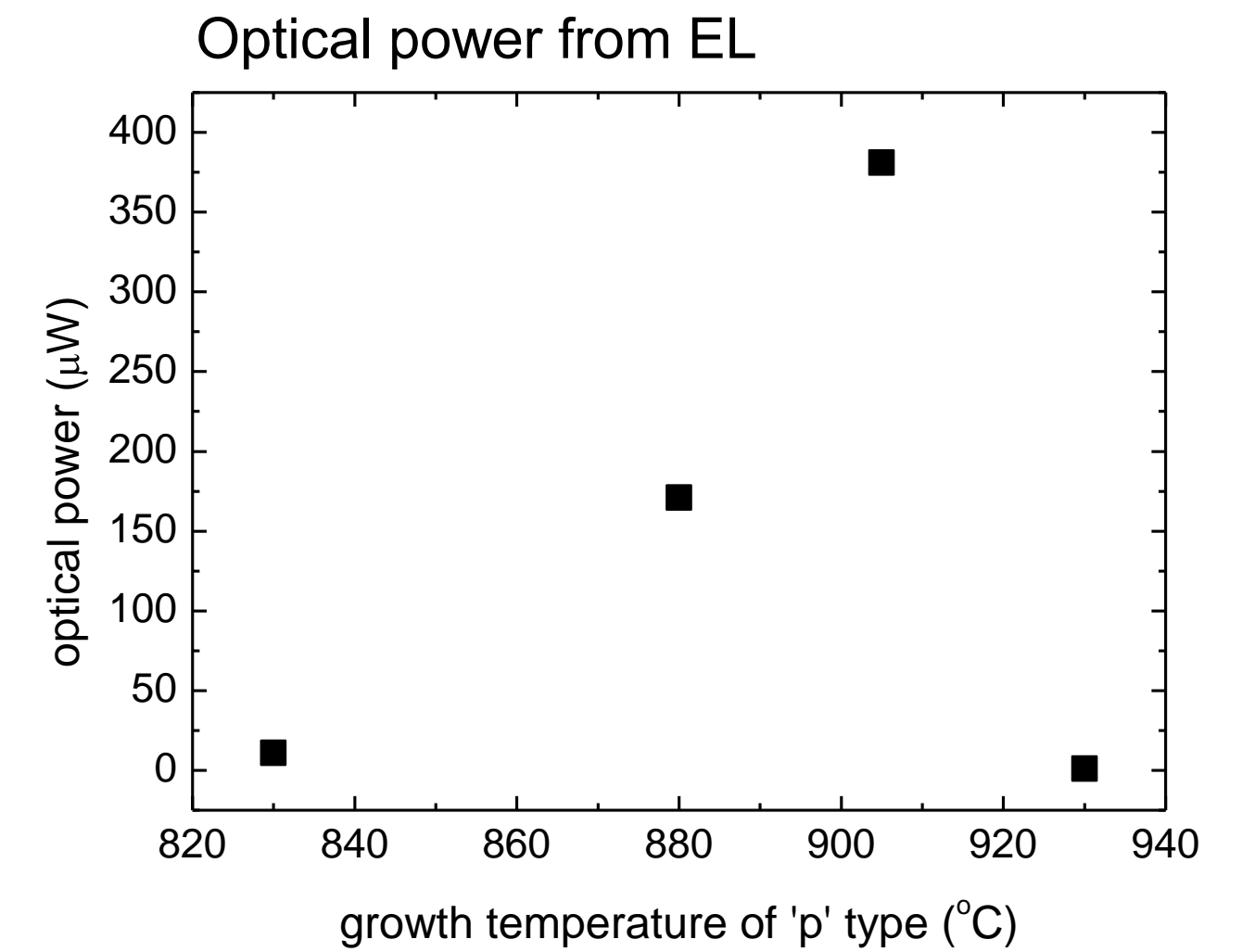
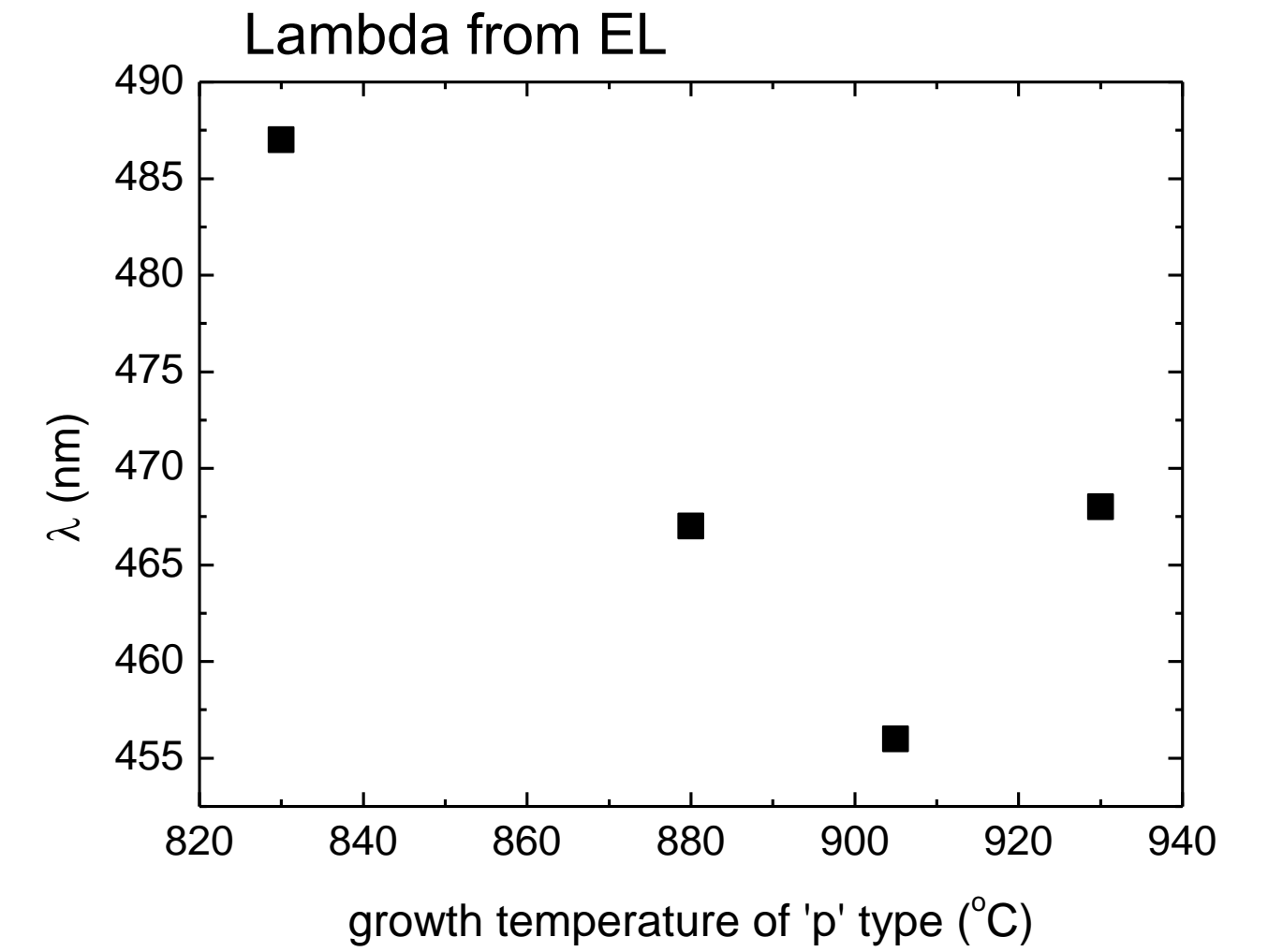


p-type GaN

QW InGaN (In 18%) 2.5nm  
QB InGaN (In 0.5%) 7nm

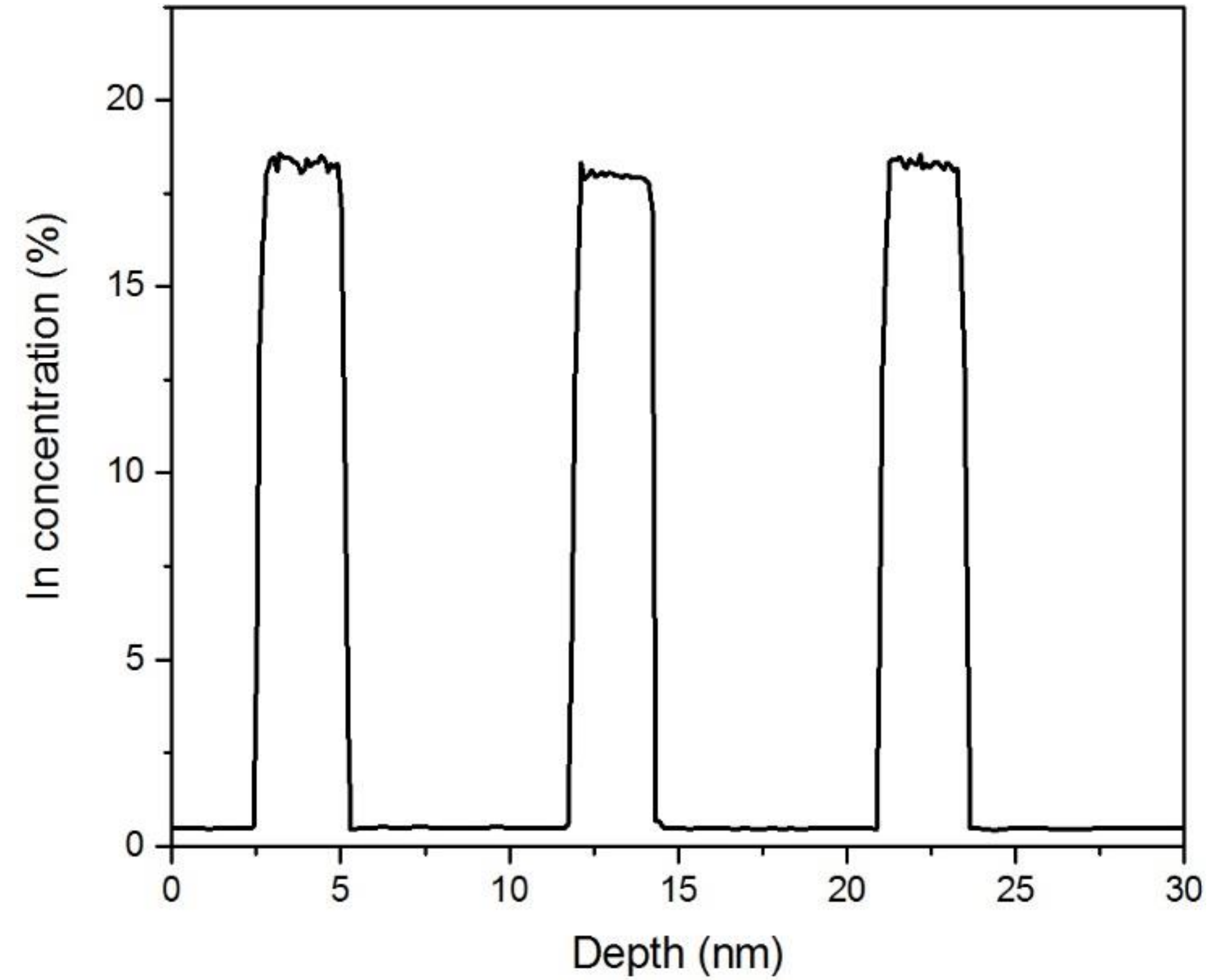
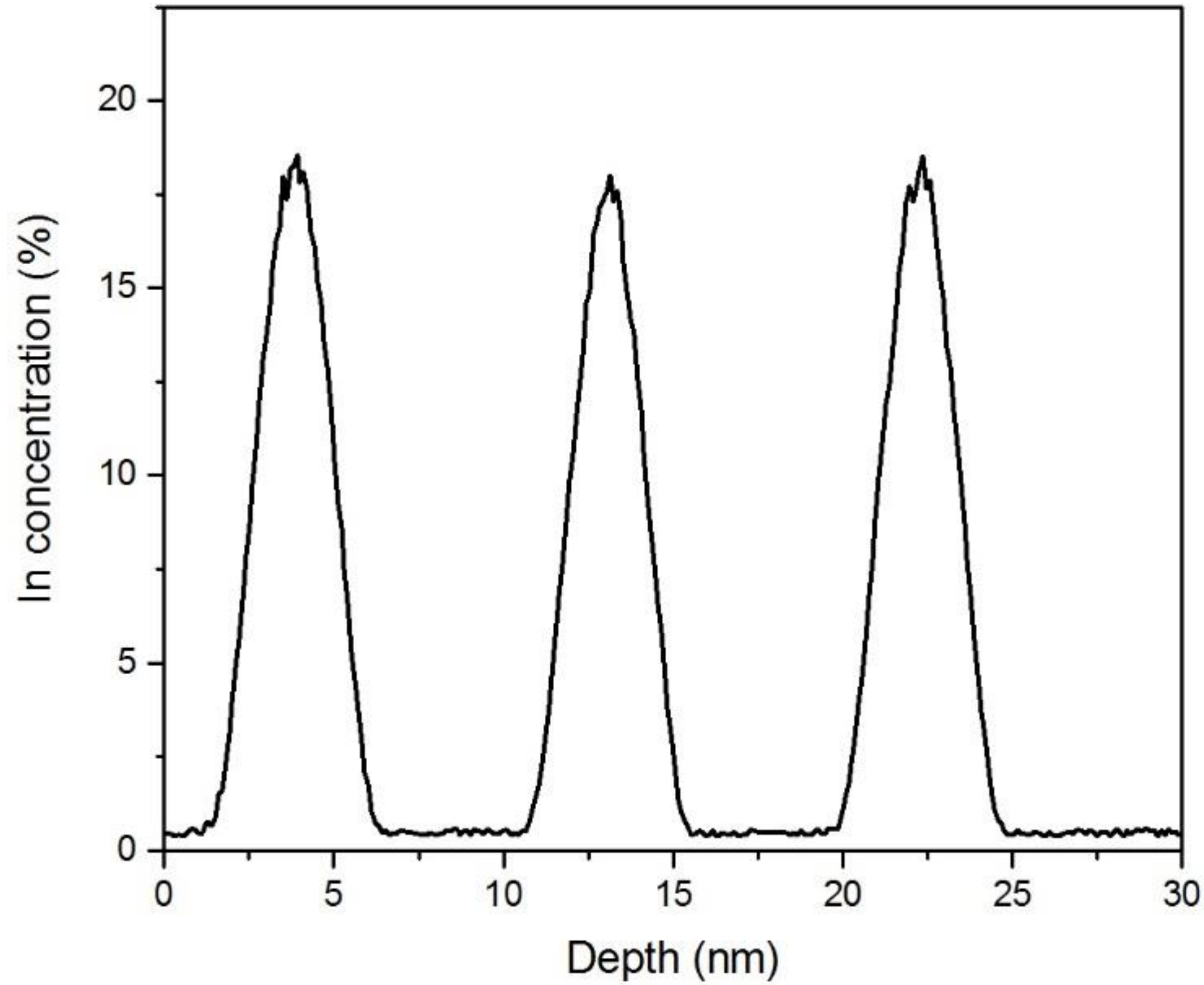
n-type GaN

Lattice mismatch  
Growth temperature differences



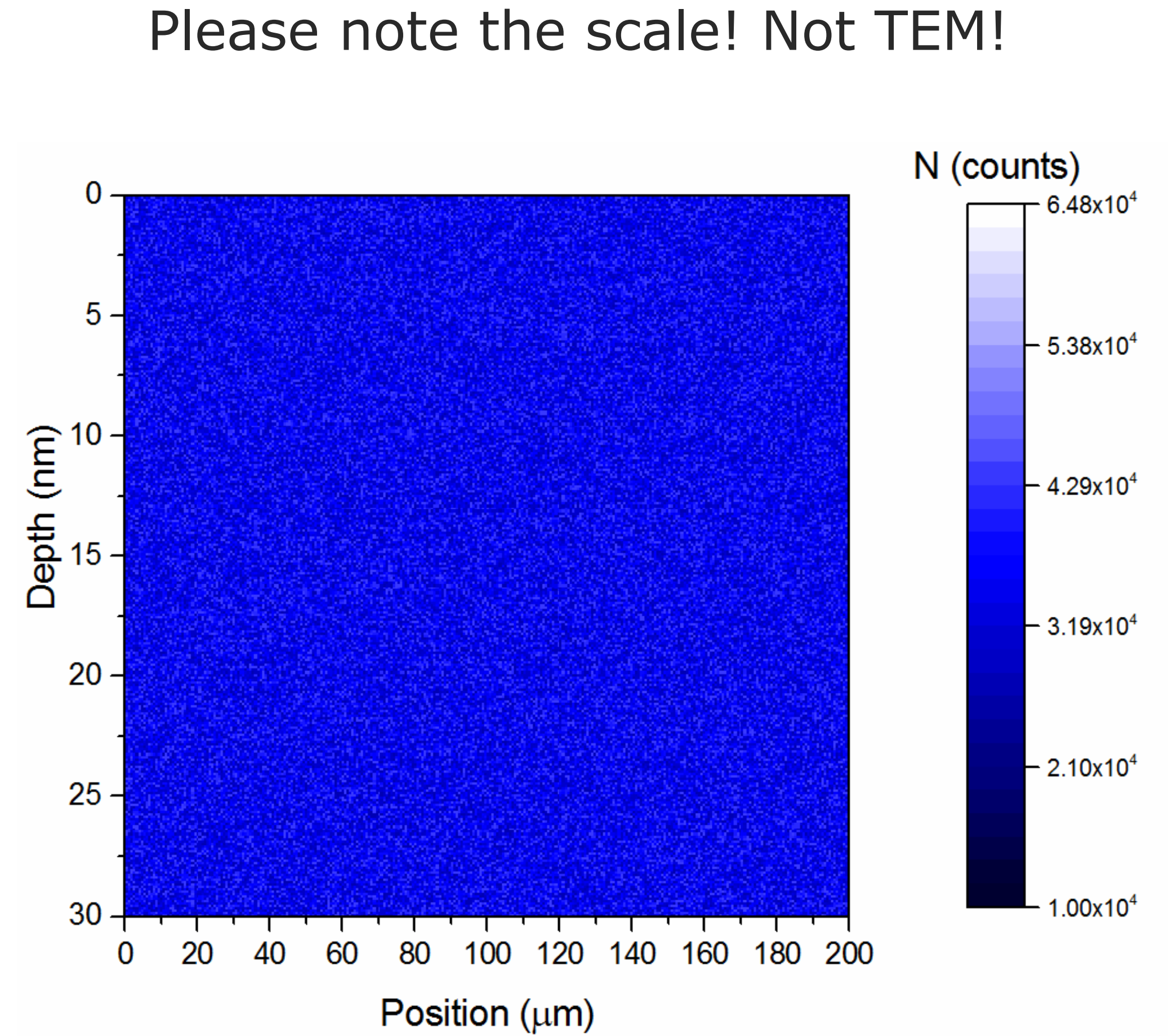
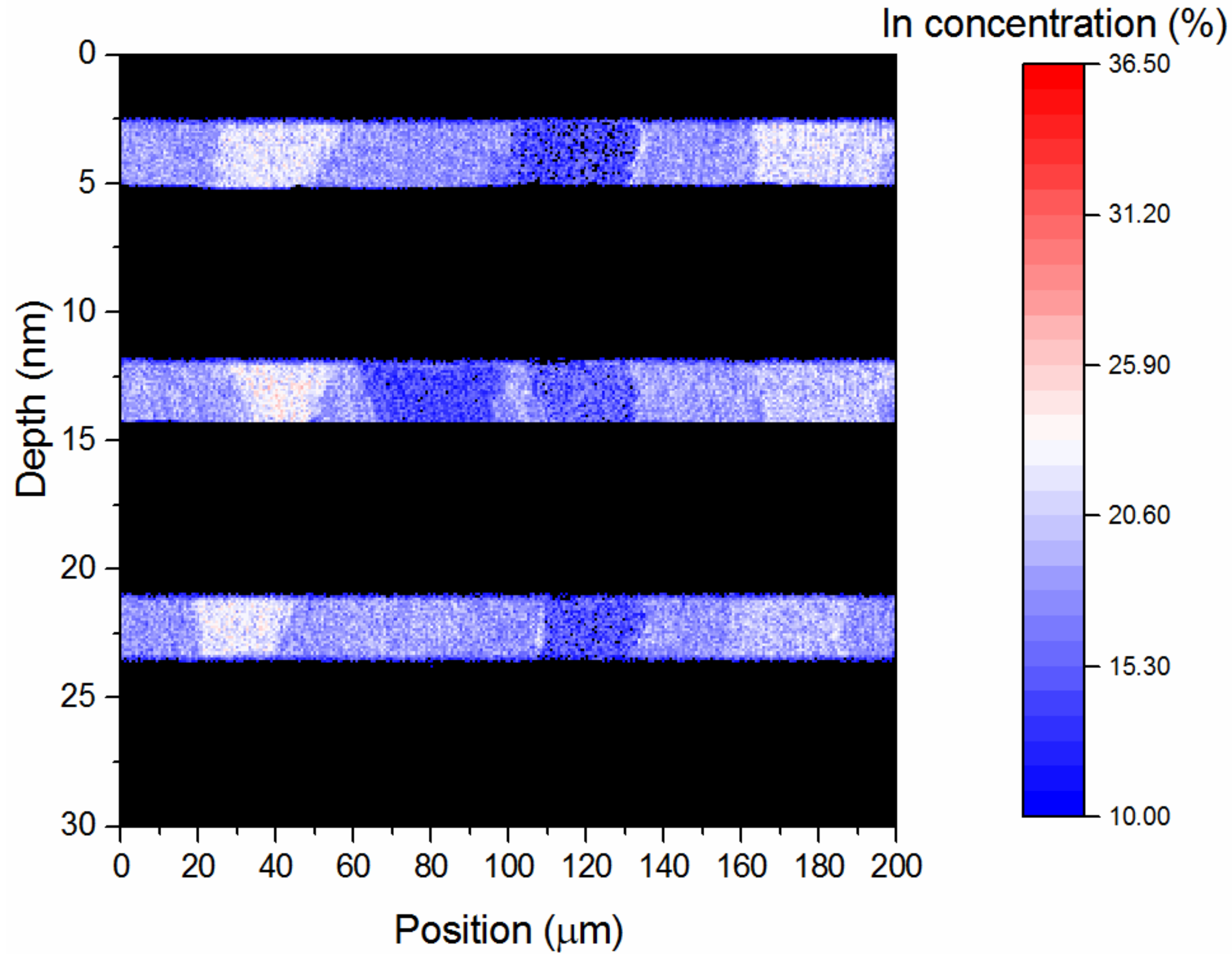


# Standard SIMS vs ULIE-SIMS





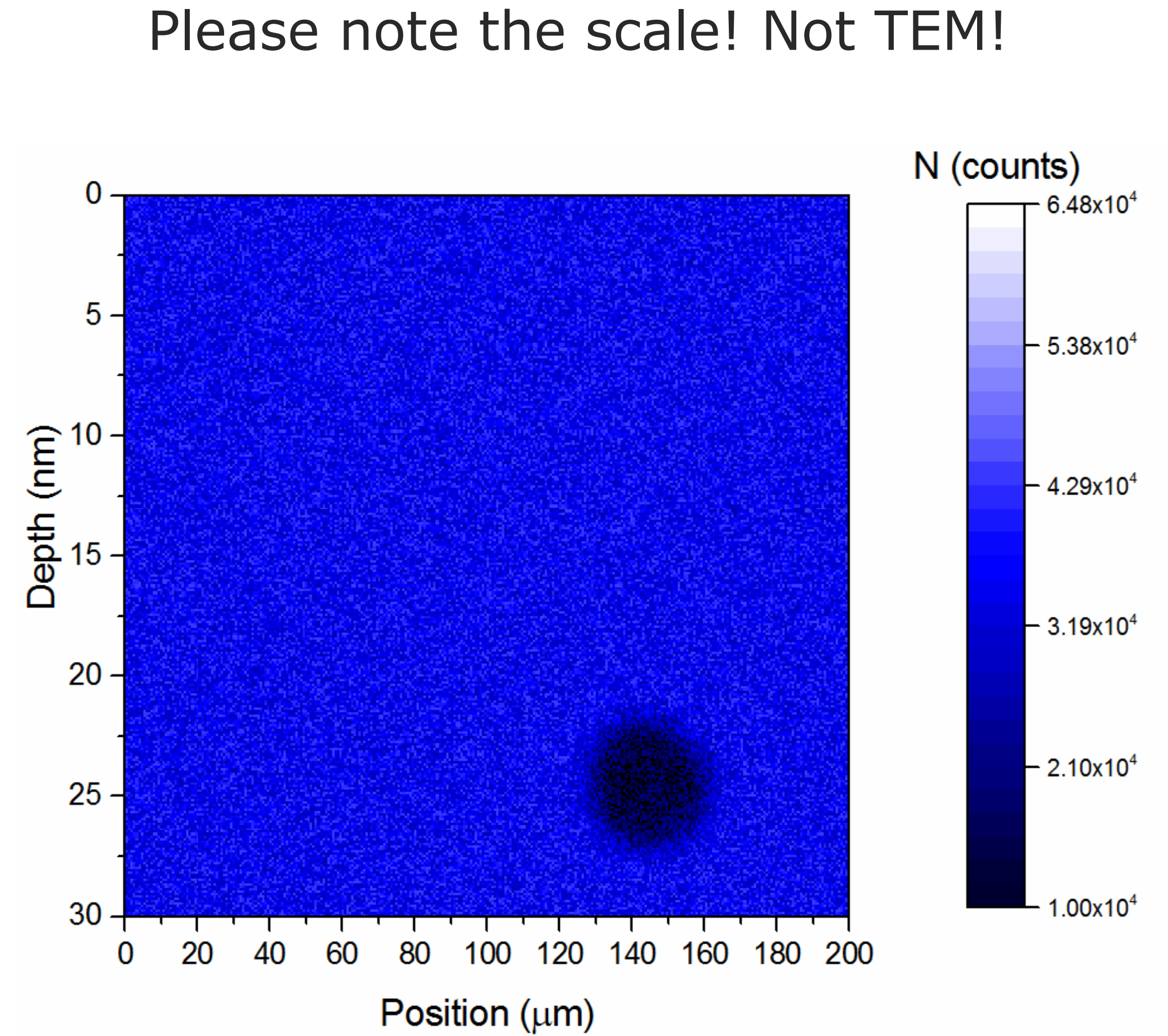
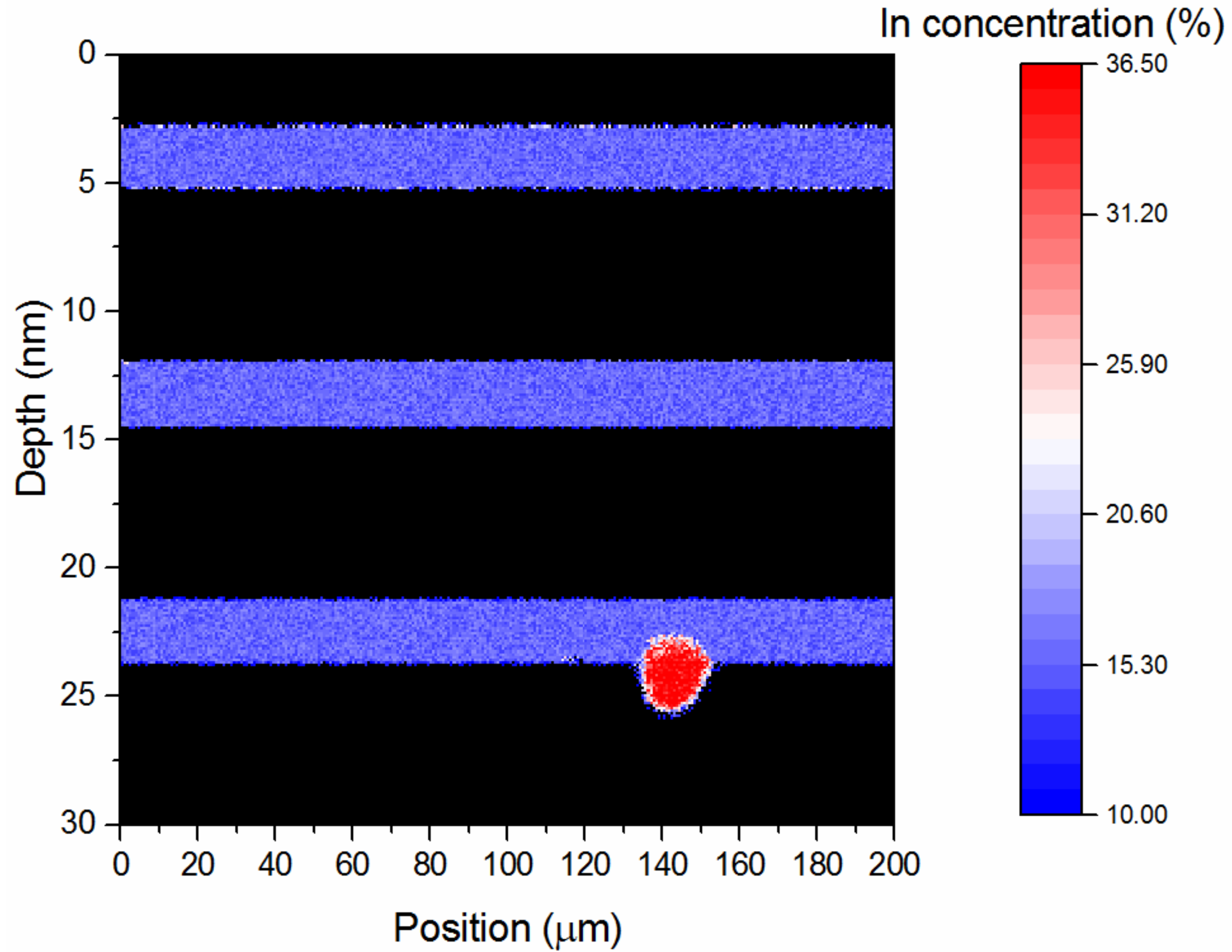
# Growth temperature 830°C







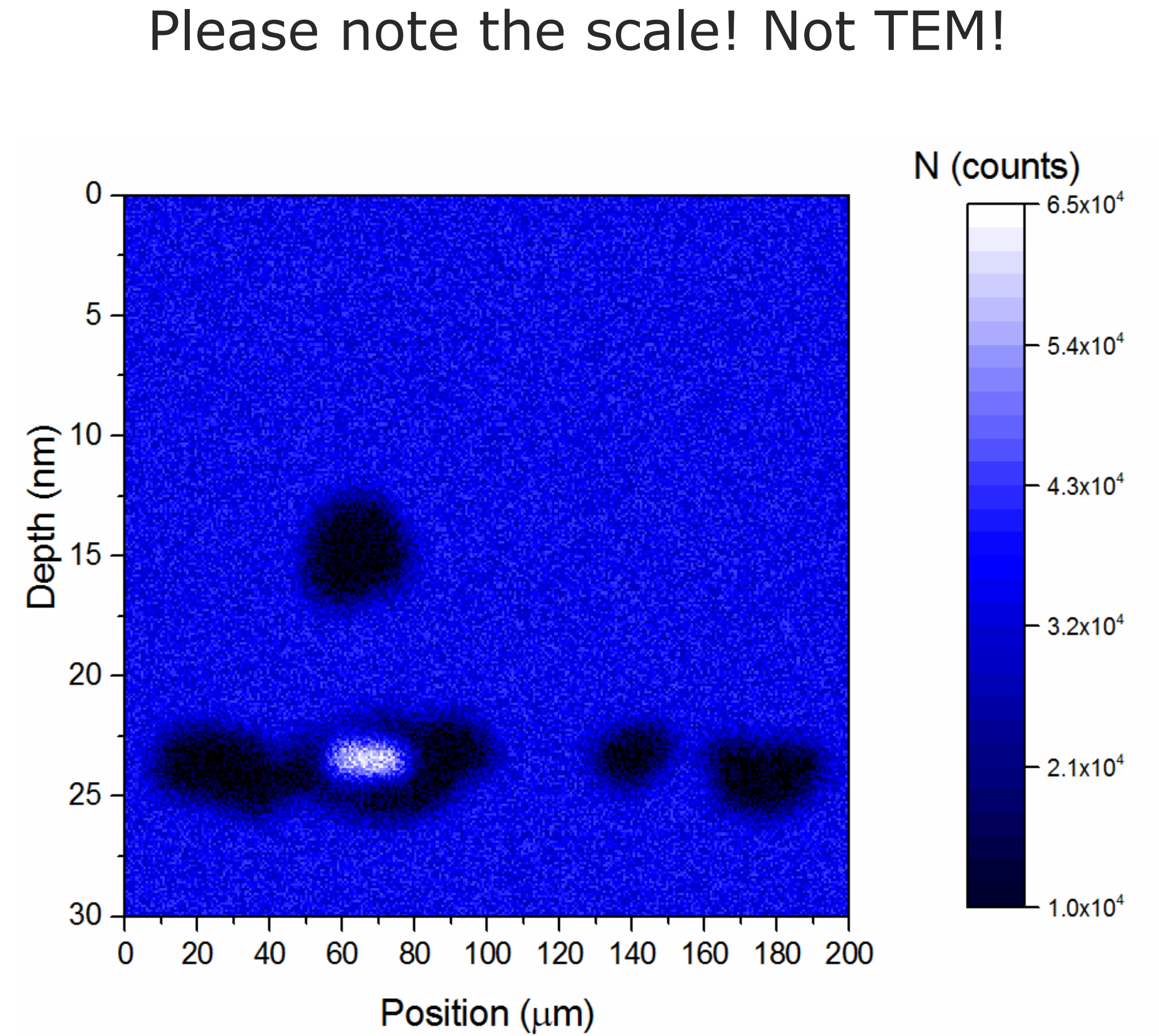
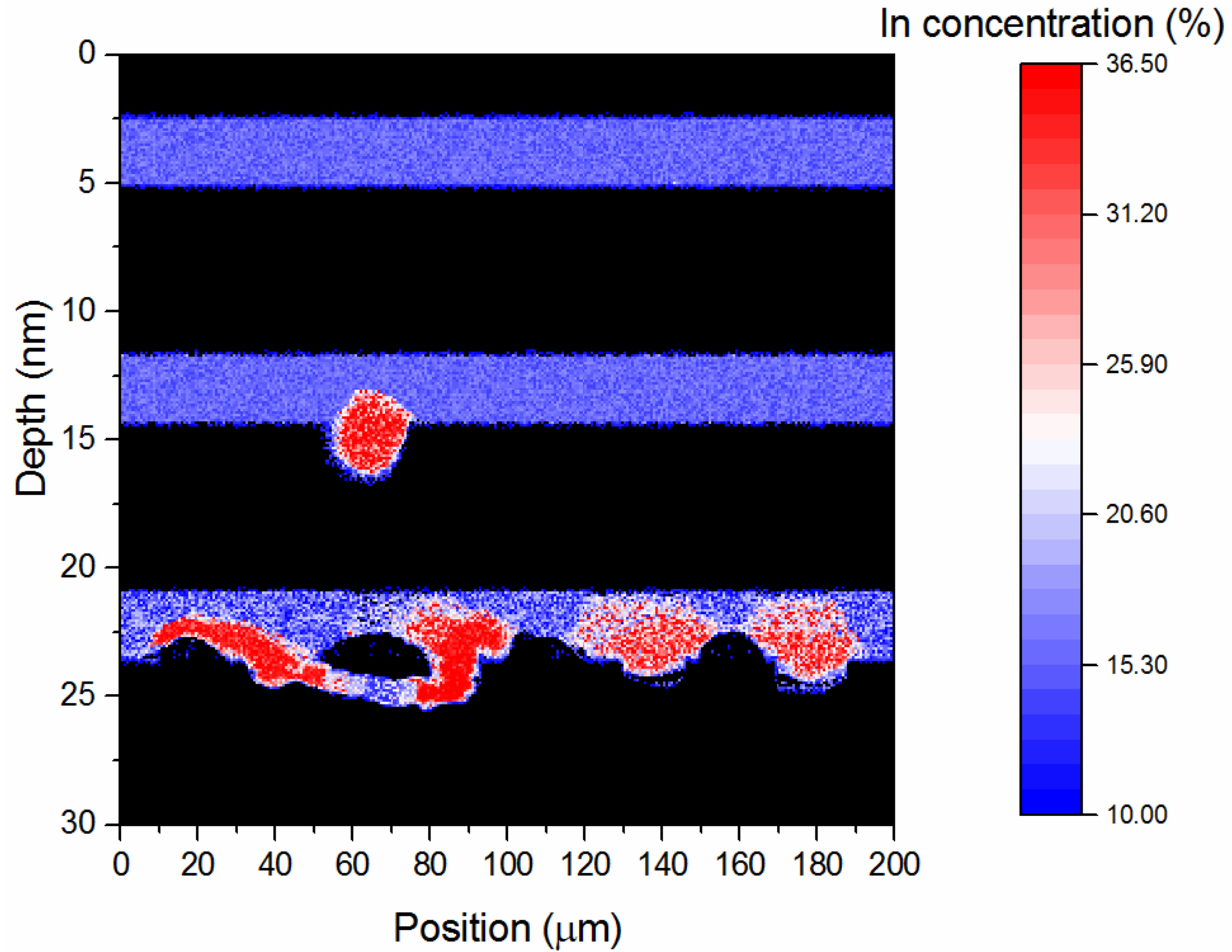
# Growth temperature 905°C





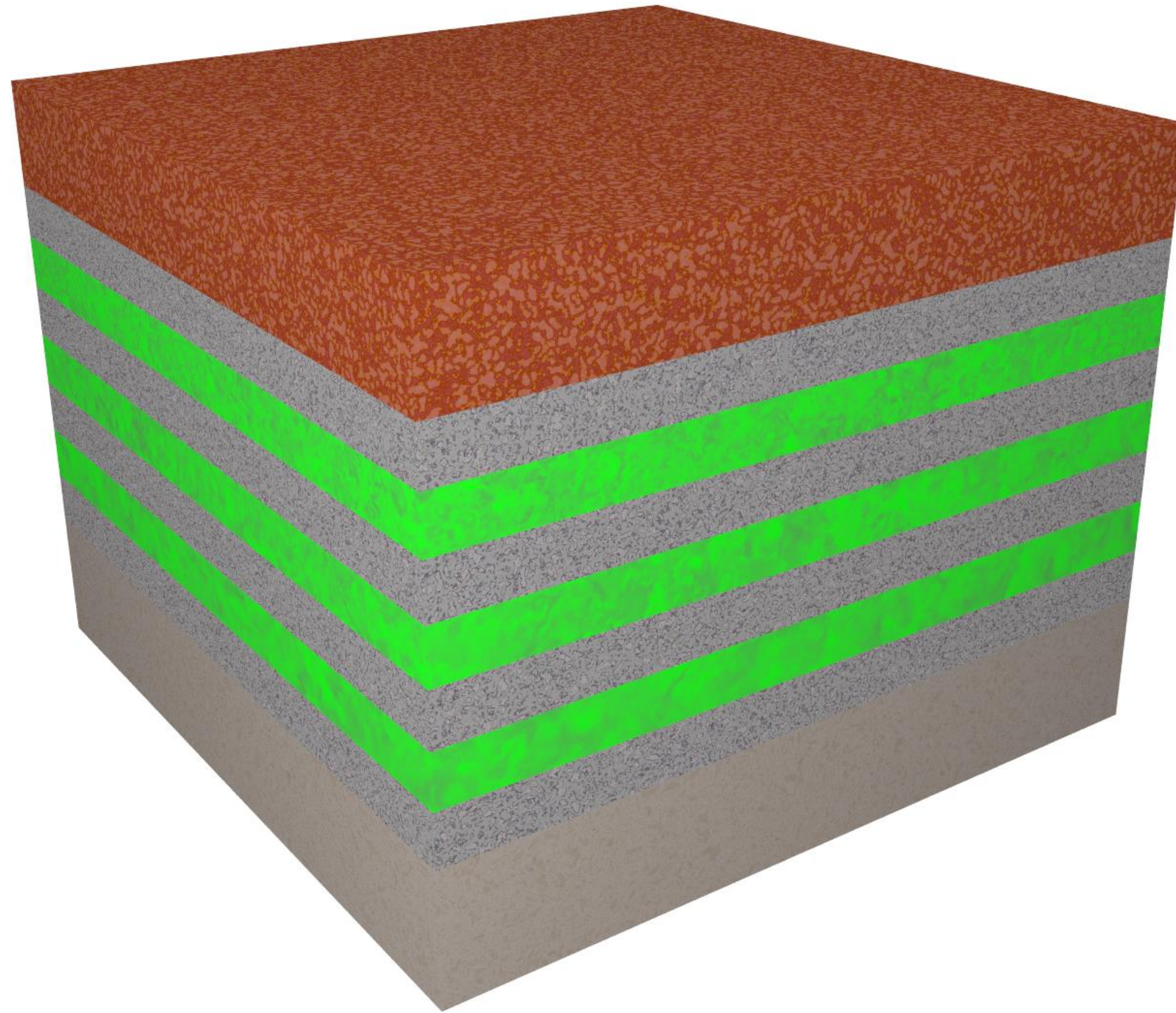


# Growth temperature 930°C





## InGaN QWs – summary

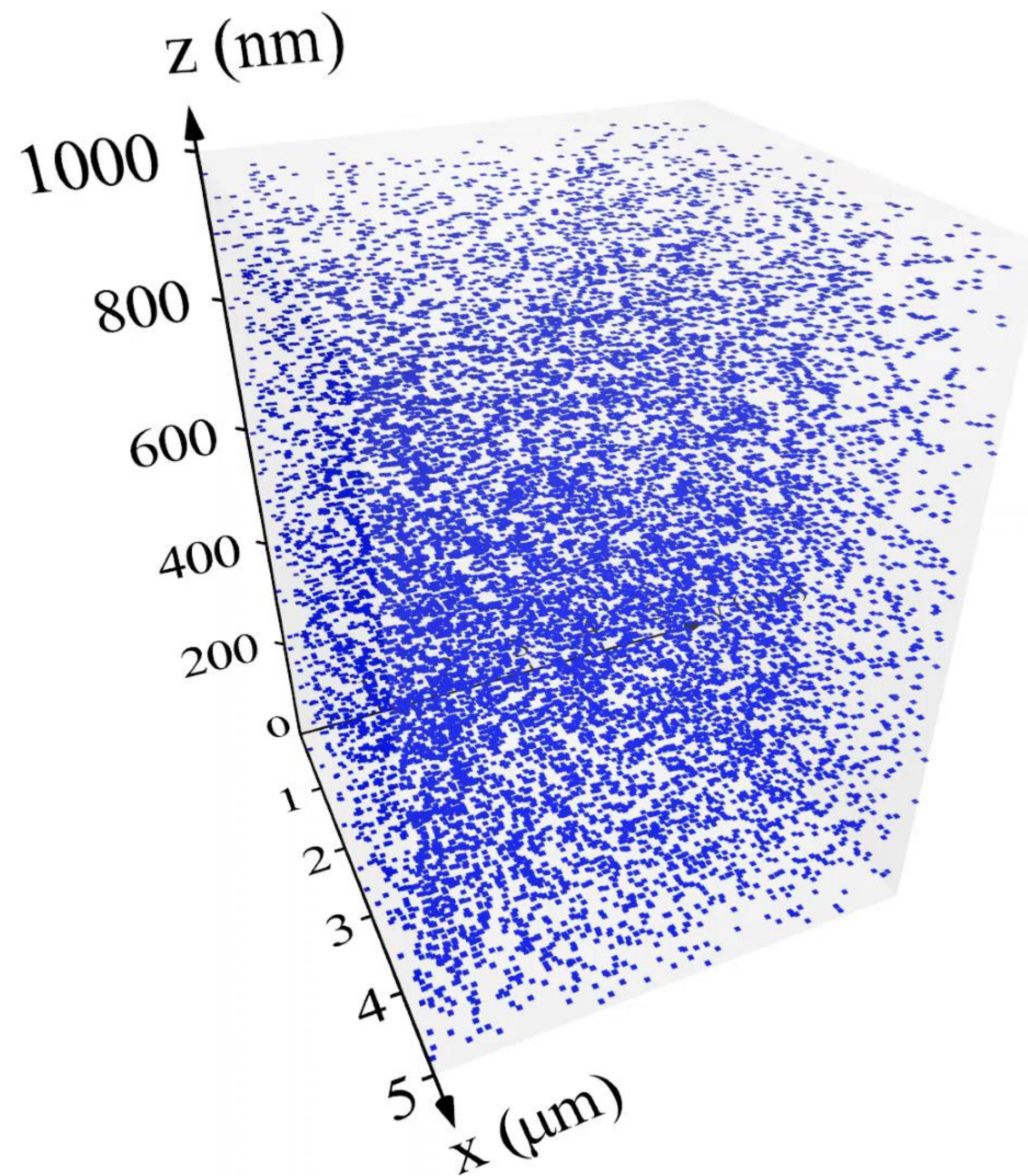


- Microscopic fluctuations
- Metallic indium precipitation
- Nitrogen bubbles
- Only one interface!
- Vacancies out-diffusion



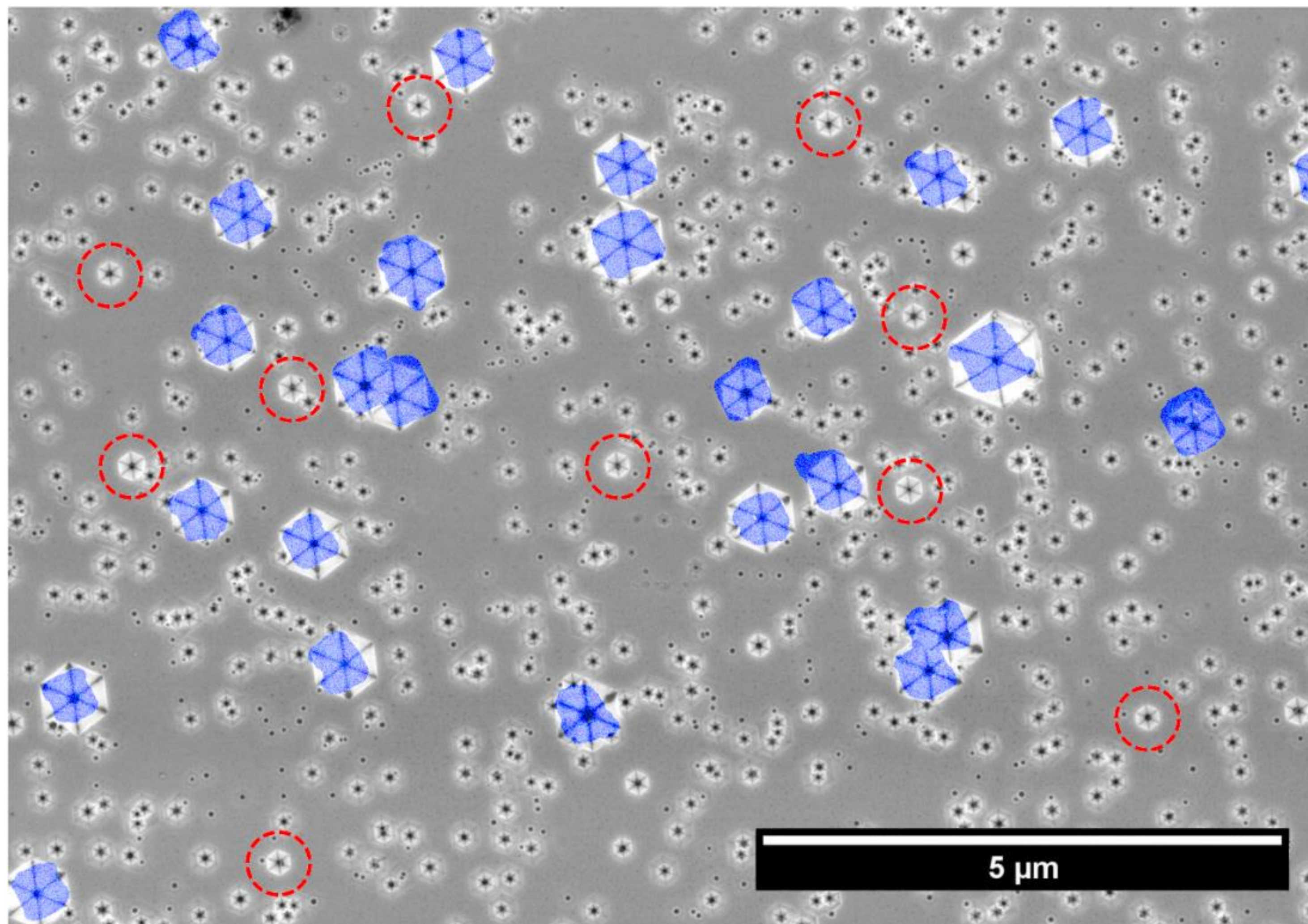
# Oxygen in GaN

- Sophisticated procedure
- Background contribution
- Random



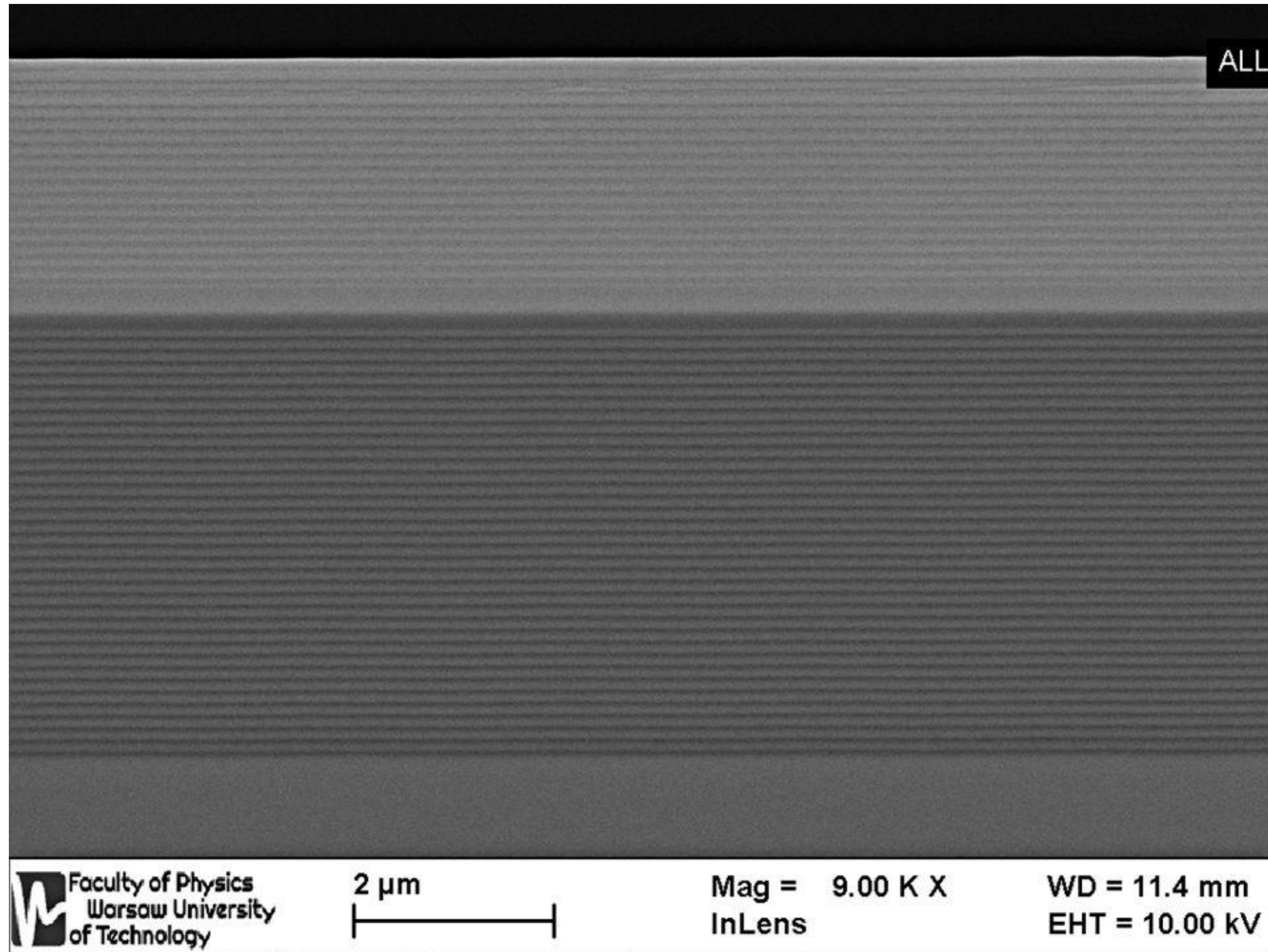


# Oxygen in GaN





# Vertical-cavity surface-emitting laser

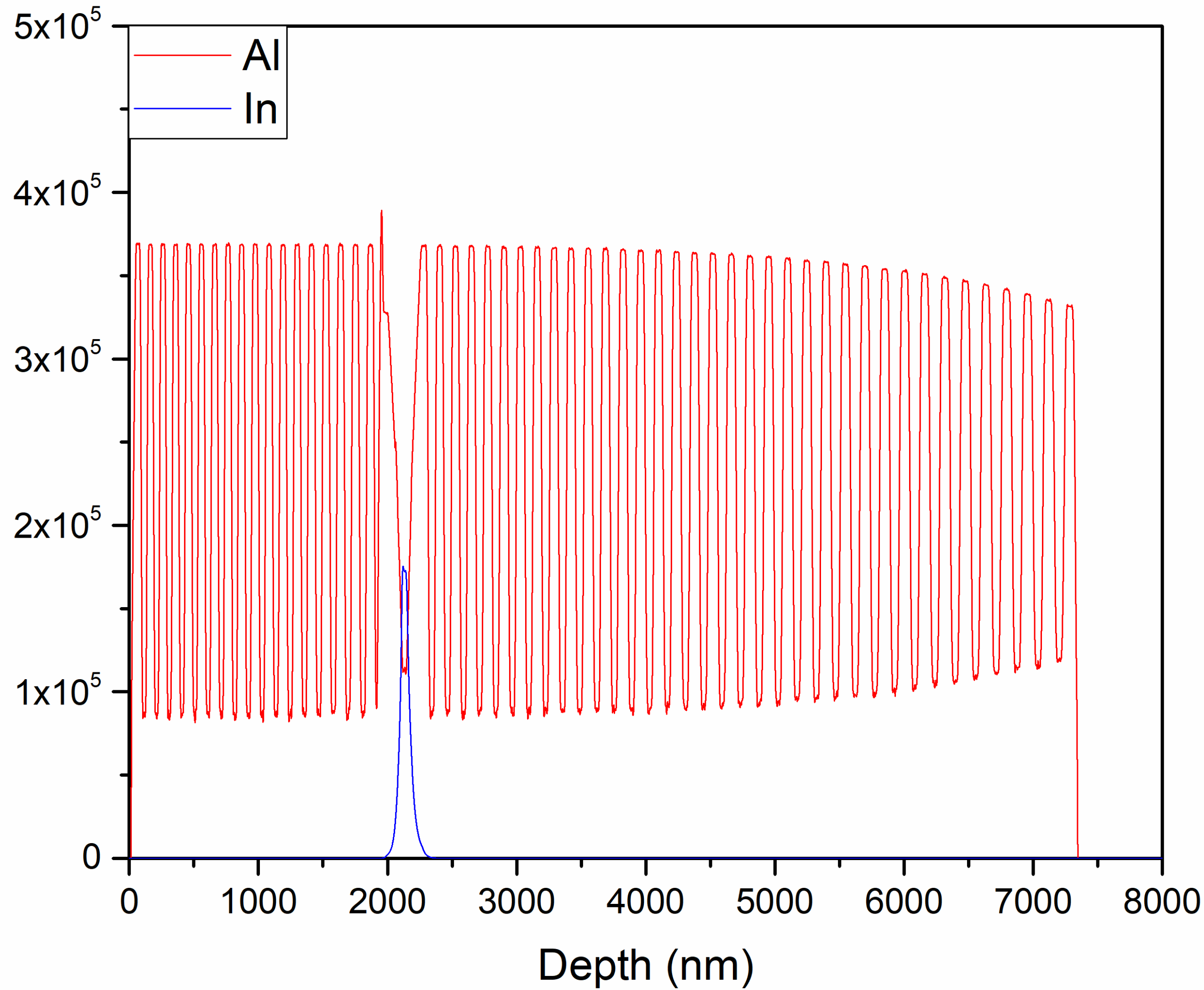


## Remarks

- Hundreds of layers
- 3 nm thick QWs
- Oxidation aperture
  
- Difficult sample for SIMS

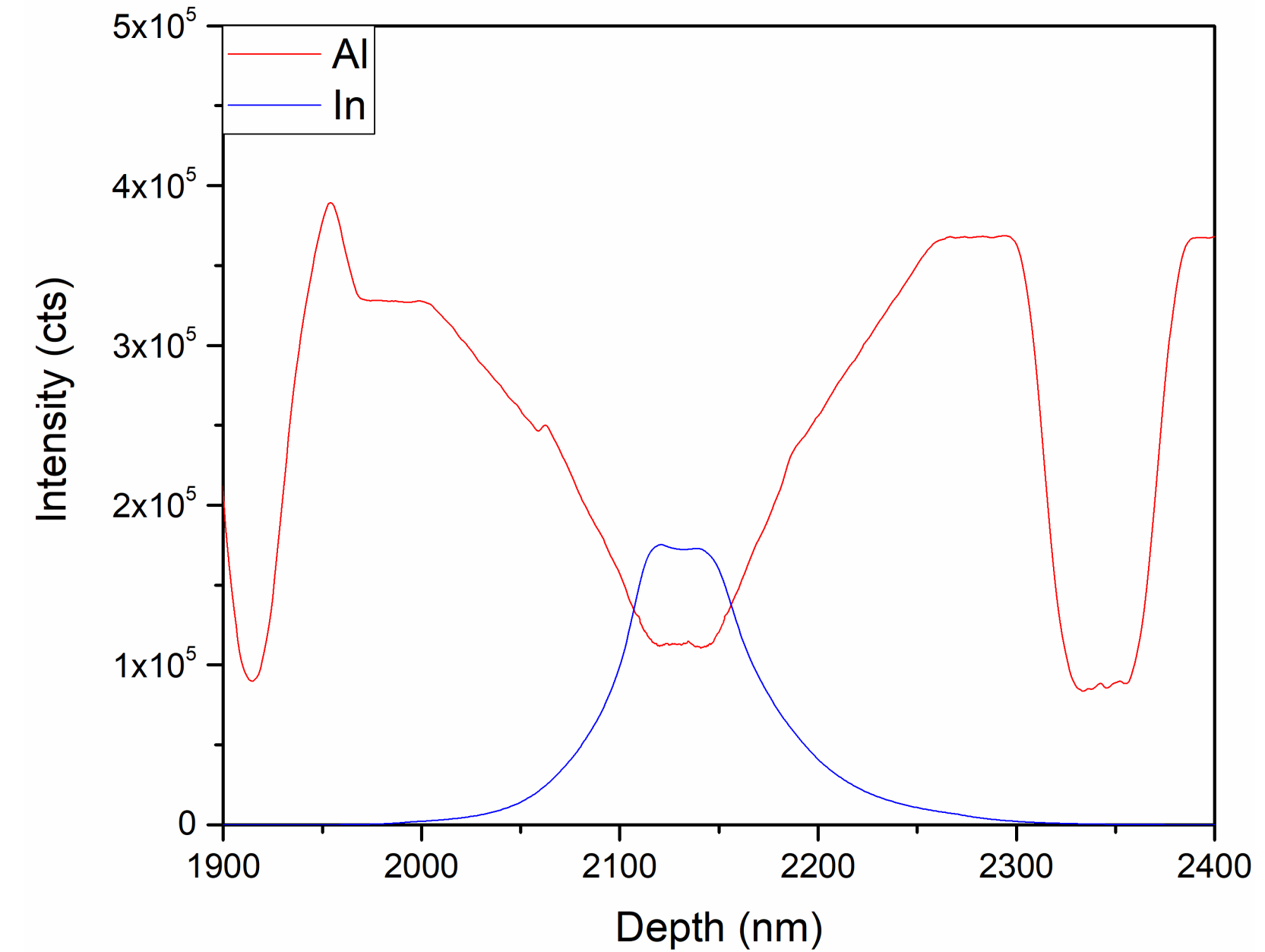


# Standard SIMS procedure



## Remarks

- Cs<sup>+</sup>, 1000 eV
- Mixing effect
- Crater roughness
- Primary beam deterioration
- Poor depth resolution







Łukasiewicz  
IMiF

# Solution

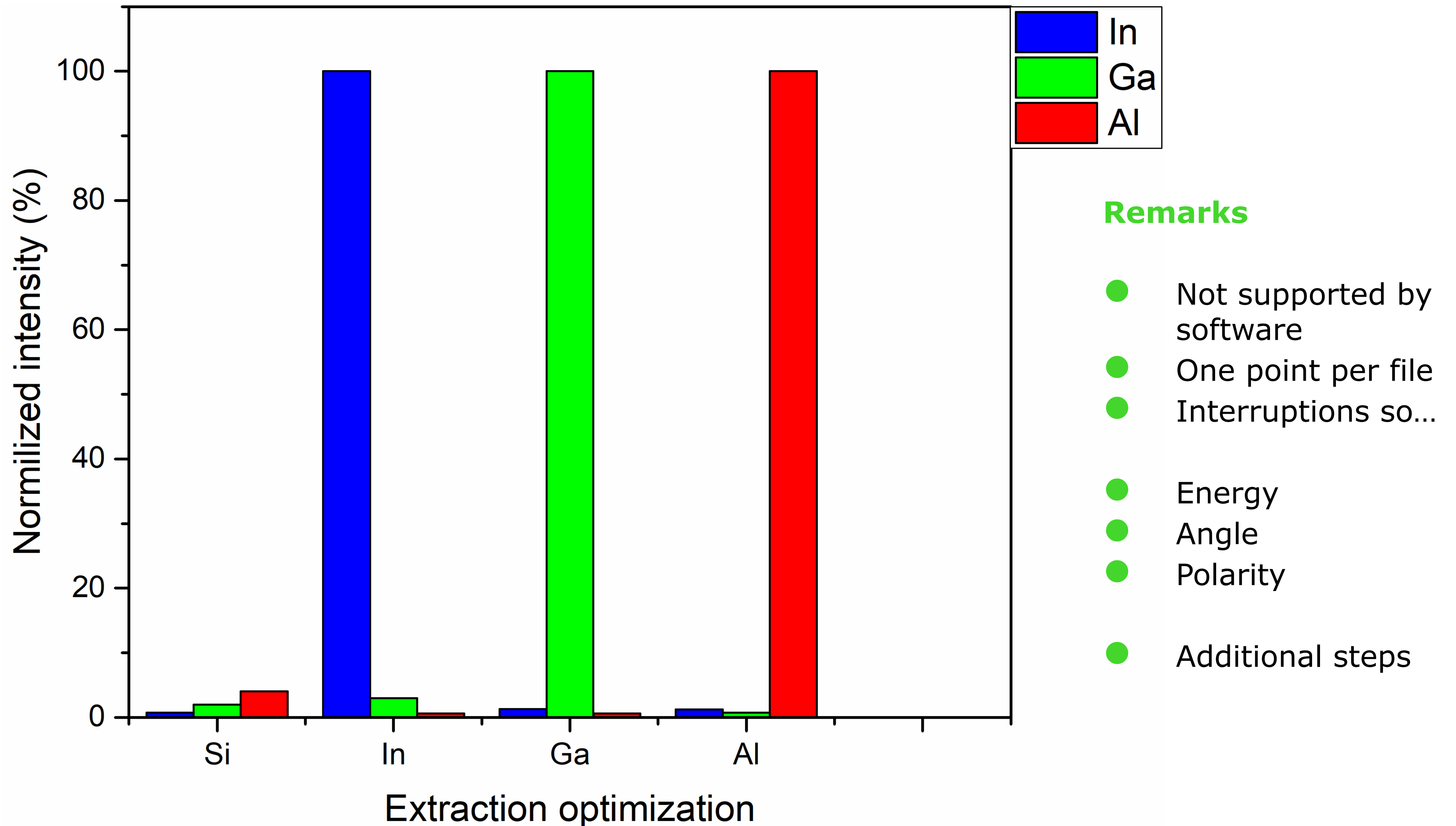
## Optimization

- Mixing effect – lower impact energy -> Preferential sputtering and crater roughness
- Crater roughness – higher impact energy -> mixing effect
- Primary beam deterioration – higher beam density -> poor depth resolution
- Poor depth resolution – where to begin?
- Is it possible to optimize?

## Paradigm shift

- Mixing effect – high incident angle
- Crater roughness – ion polishing
- Primary beam deterioration – beam service
- Poor depth resolution – impact energy modulation

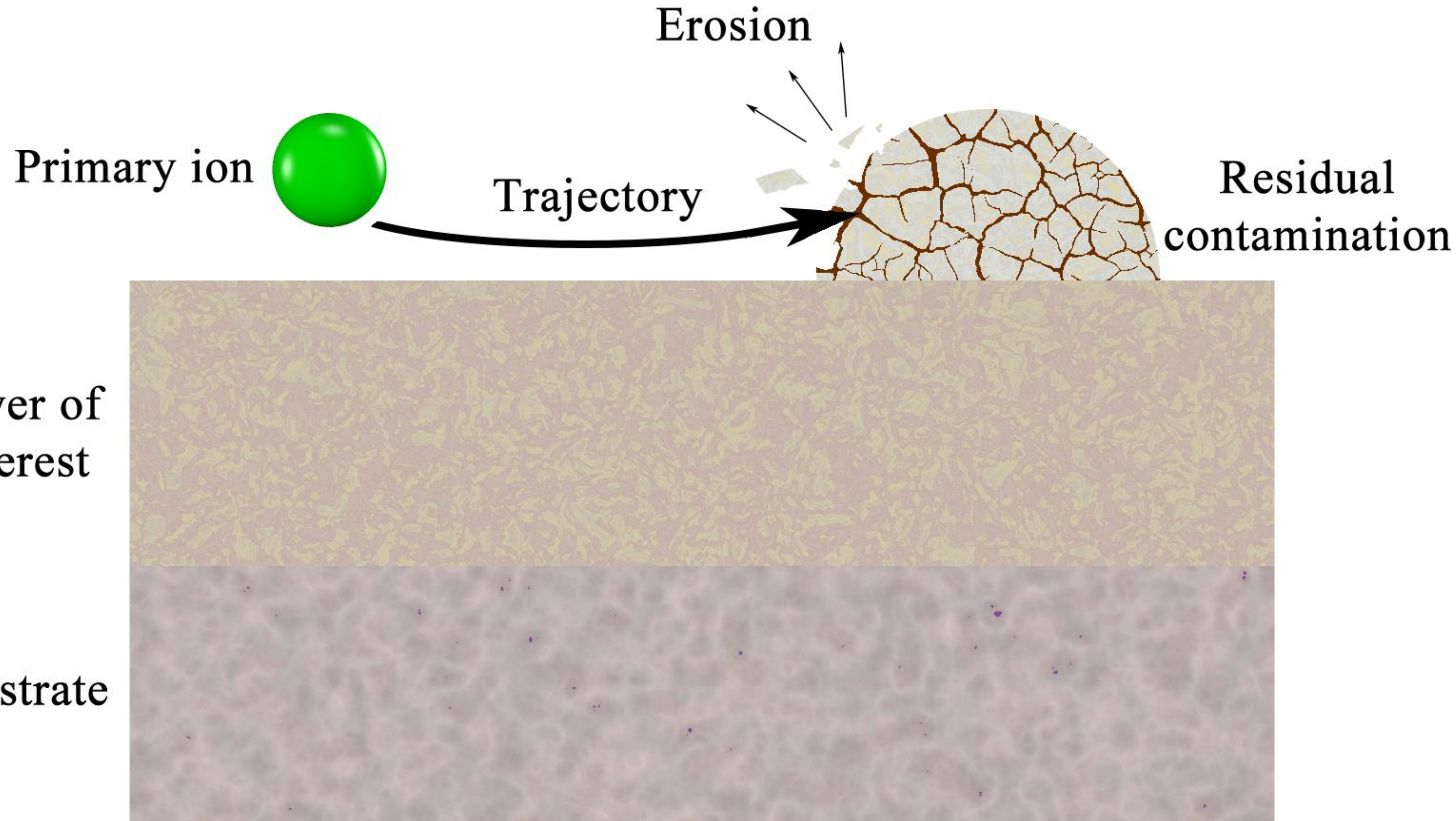
# 500 eV, 69° incident angle – extraction parameters





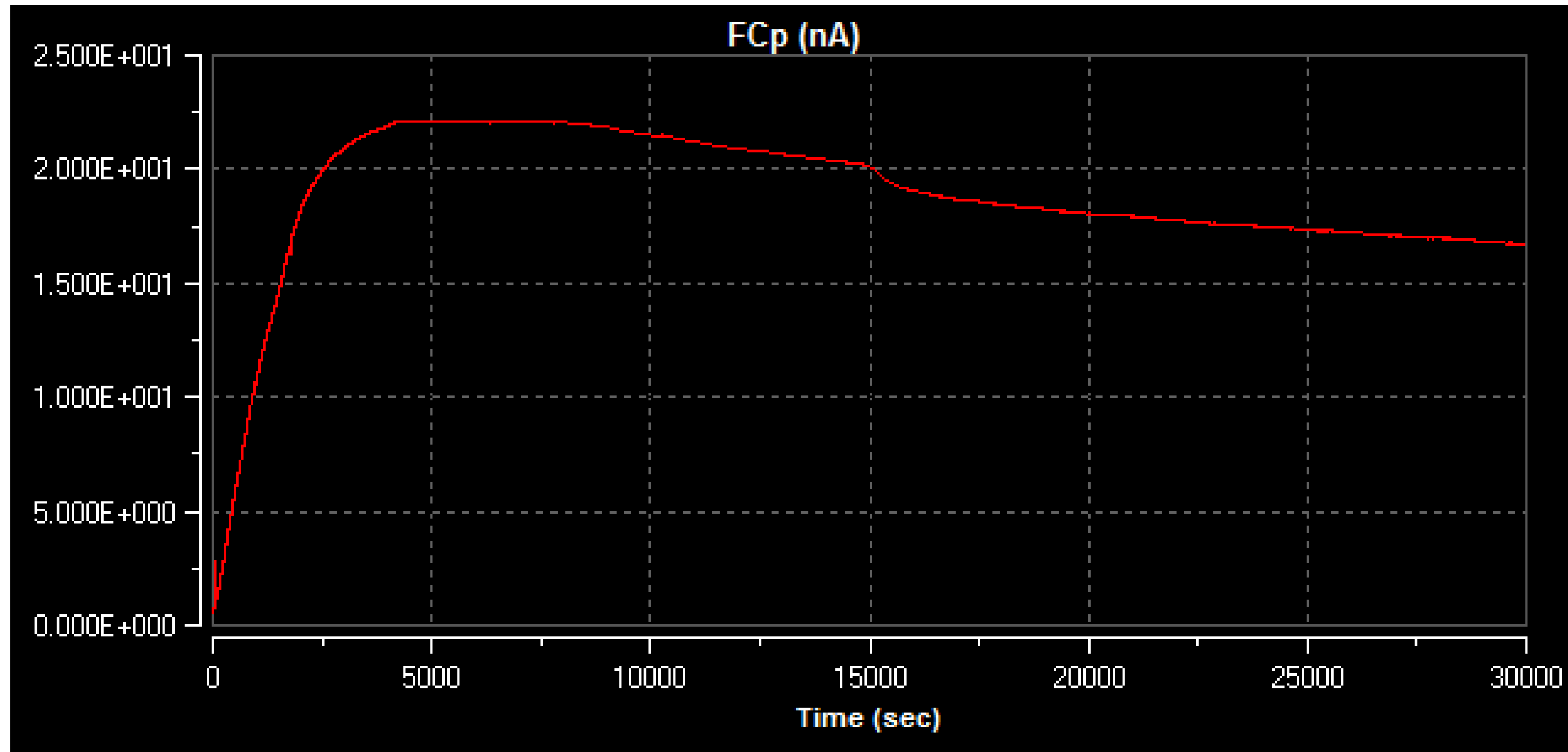


# Ion polishing



## Idea

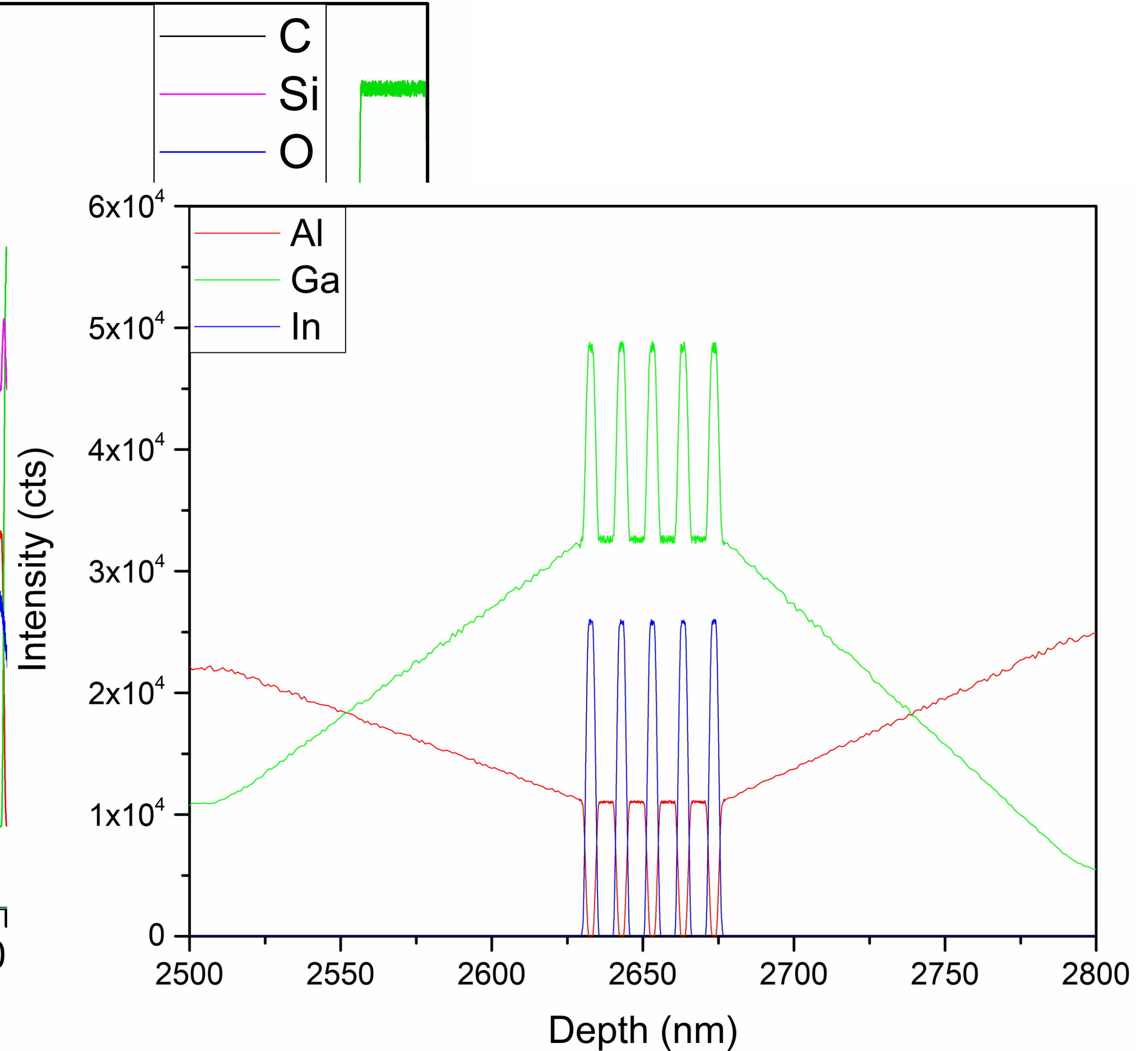
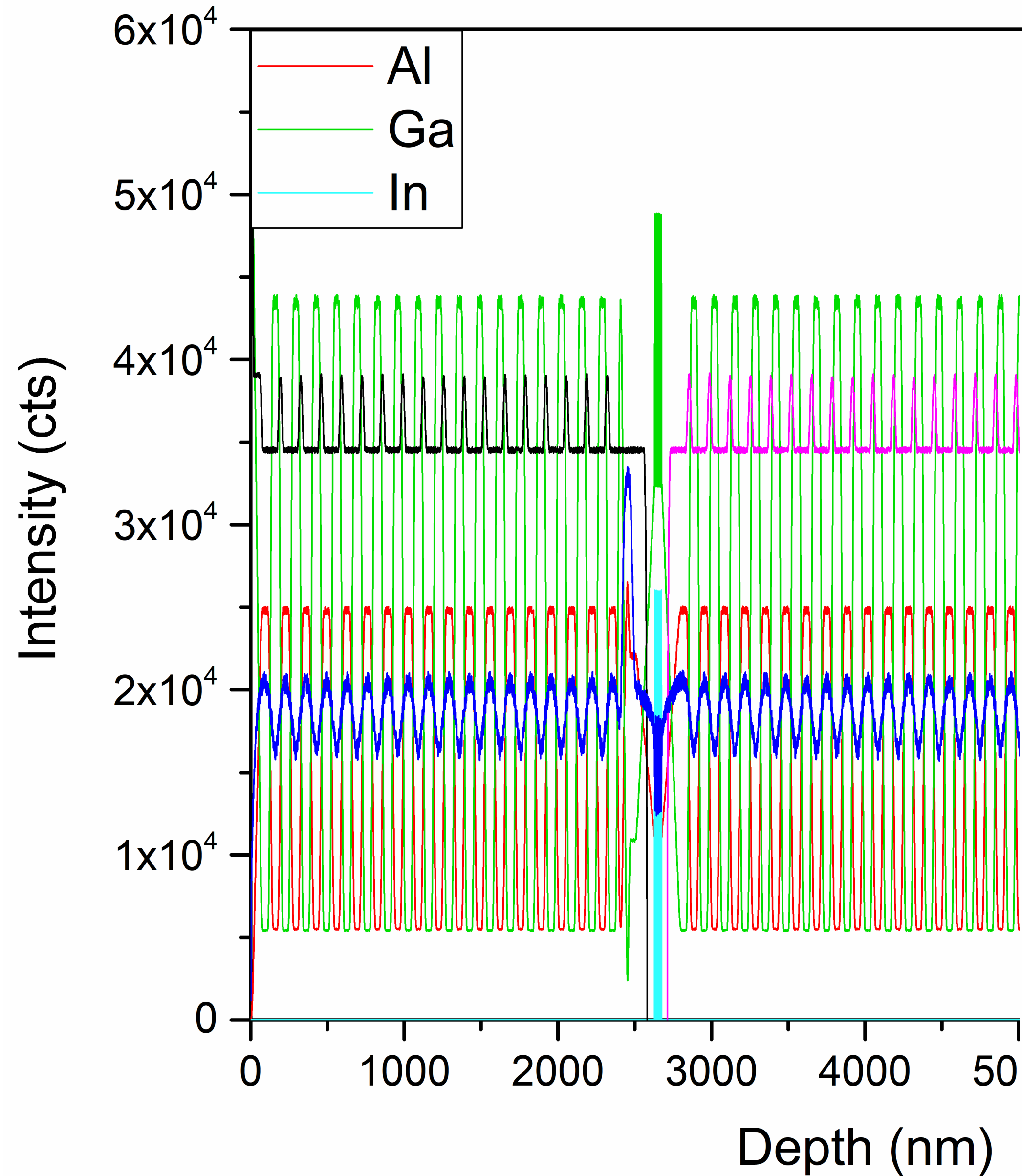
- High Energy (2-3 keV)
- High incident angle (75°)
- 96.5% of p || to the surface!
- Offset voltage
- No damage to the surface
- Cleaning
  
- Every 0.5 – 1 hour
- Fully automated



## Idea

- Safe value (15 nA)
- Every 0.5 – 1 hour
- Fully automated





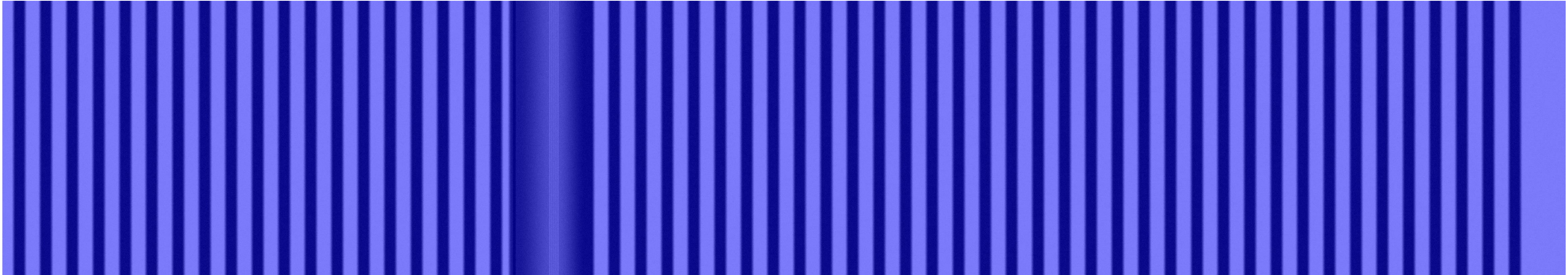




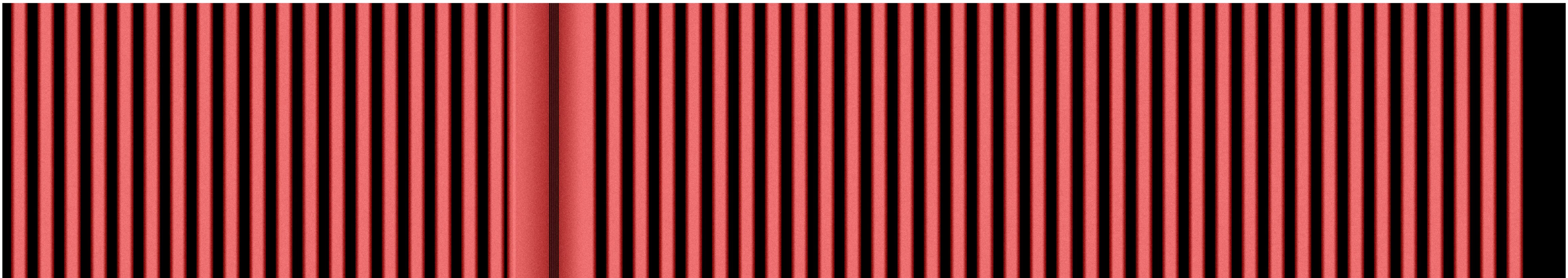
# Science meets art

<https://www.cameca.com/company/newsandevents/2023-calendar-competition/march>

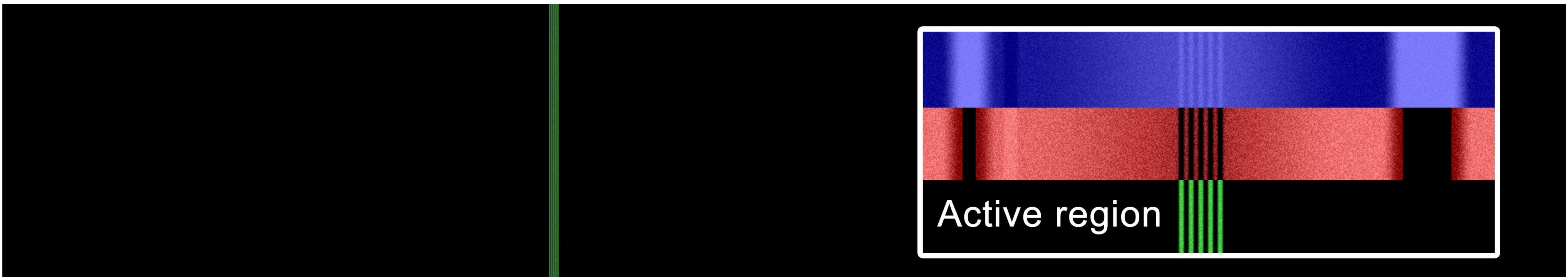
Ga



Al

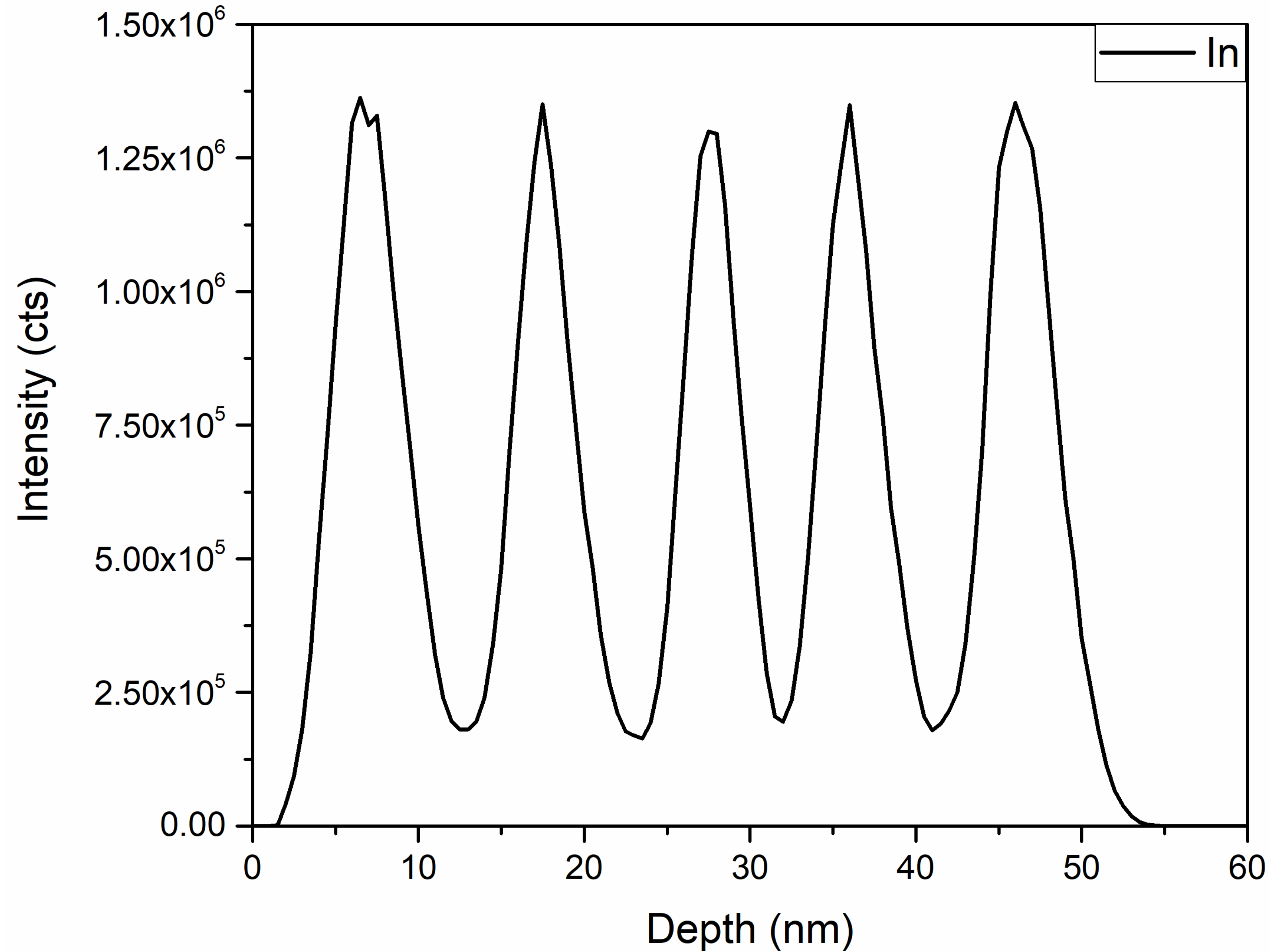


In



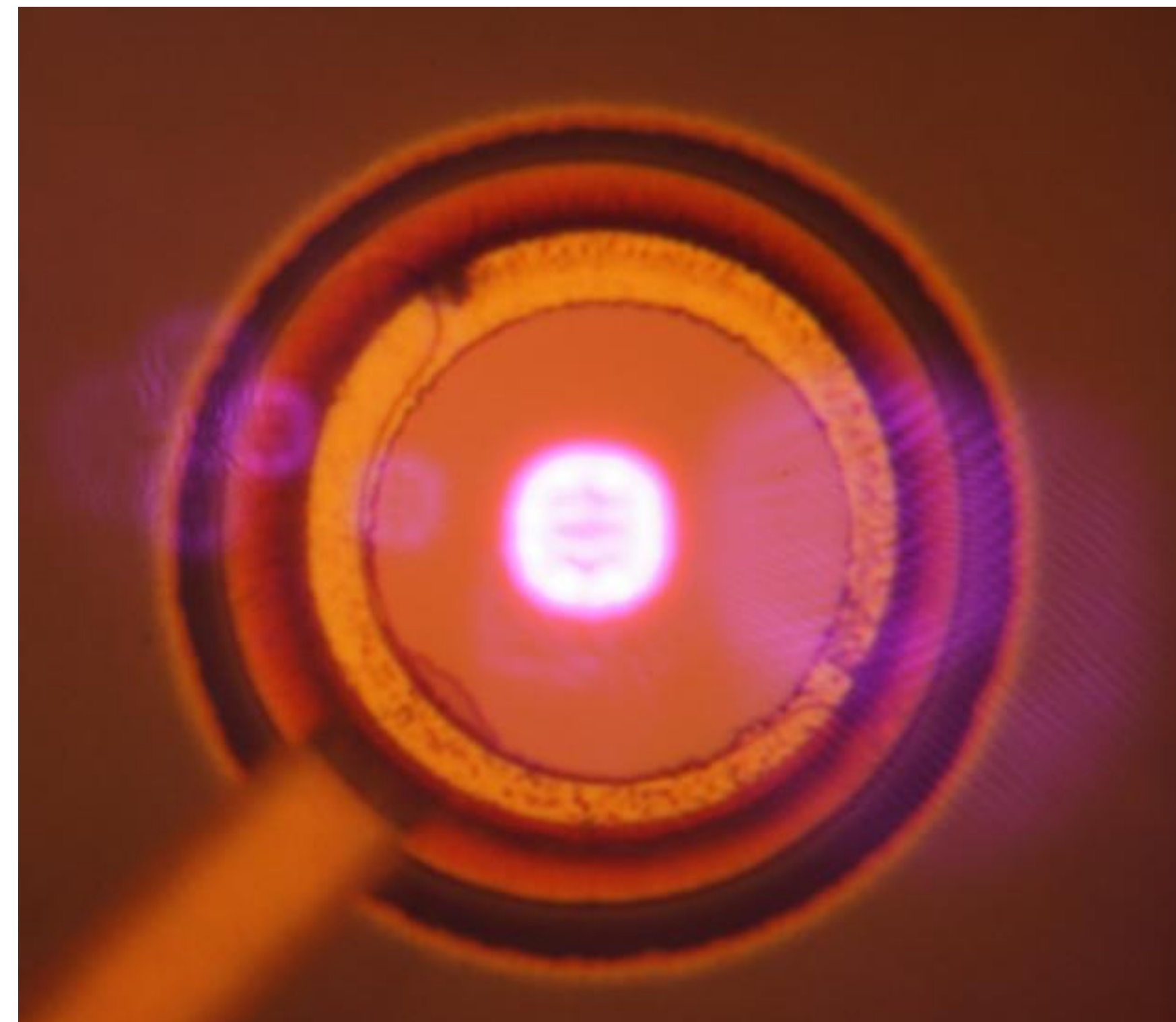
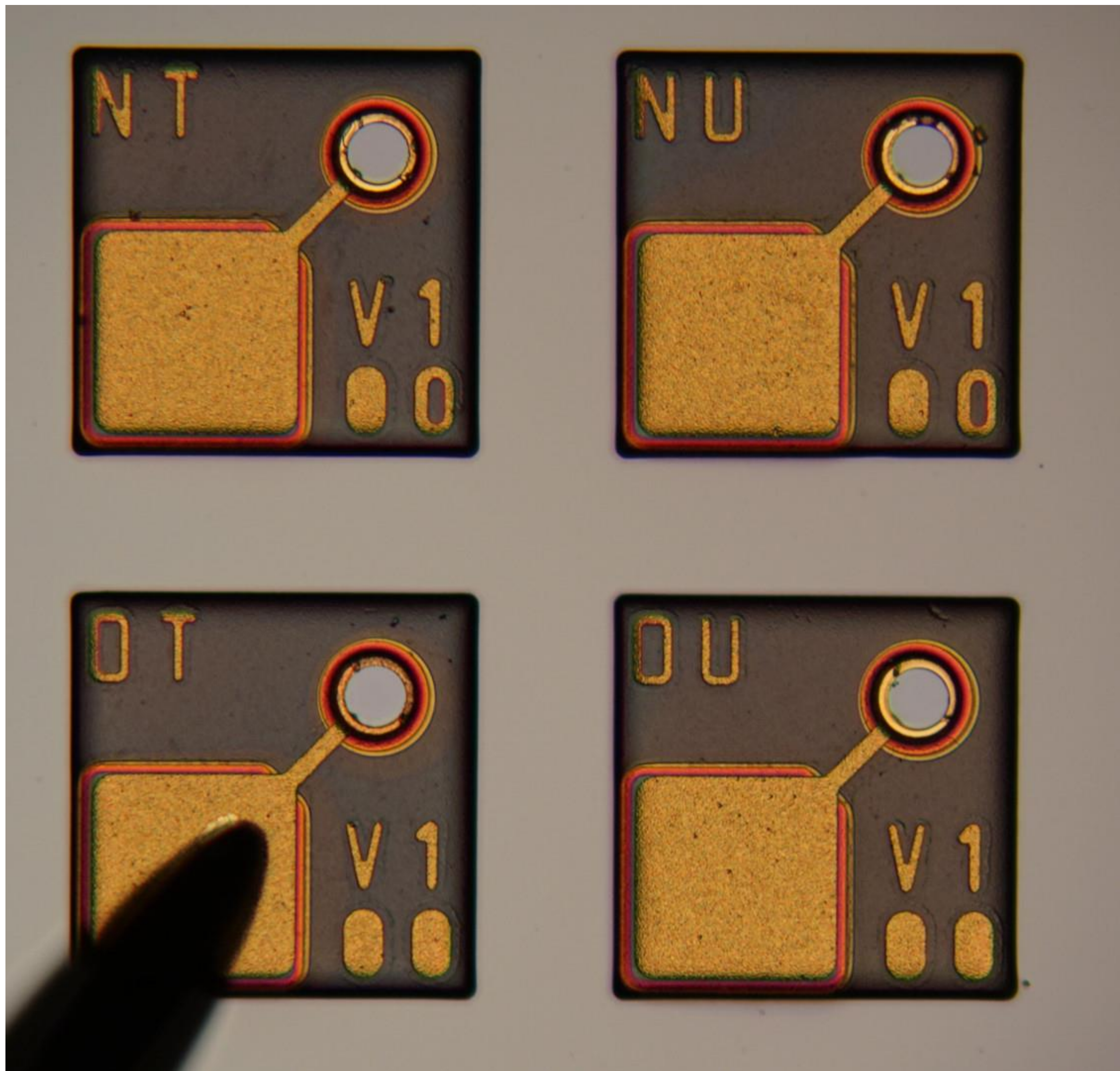


# Impact energy modulation – is it important?

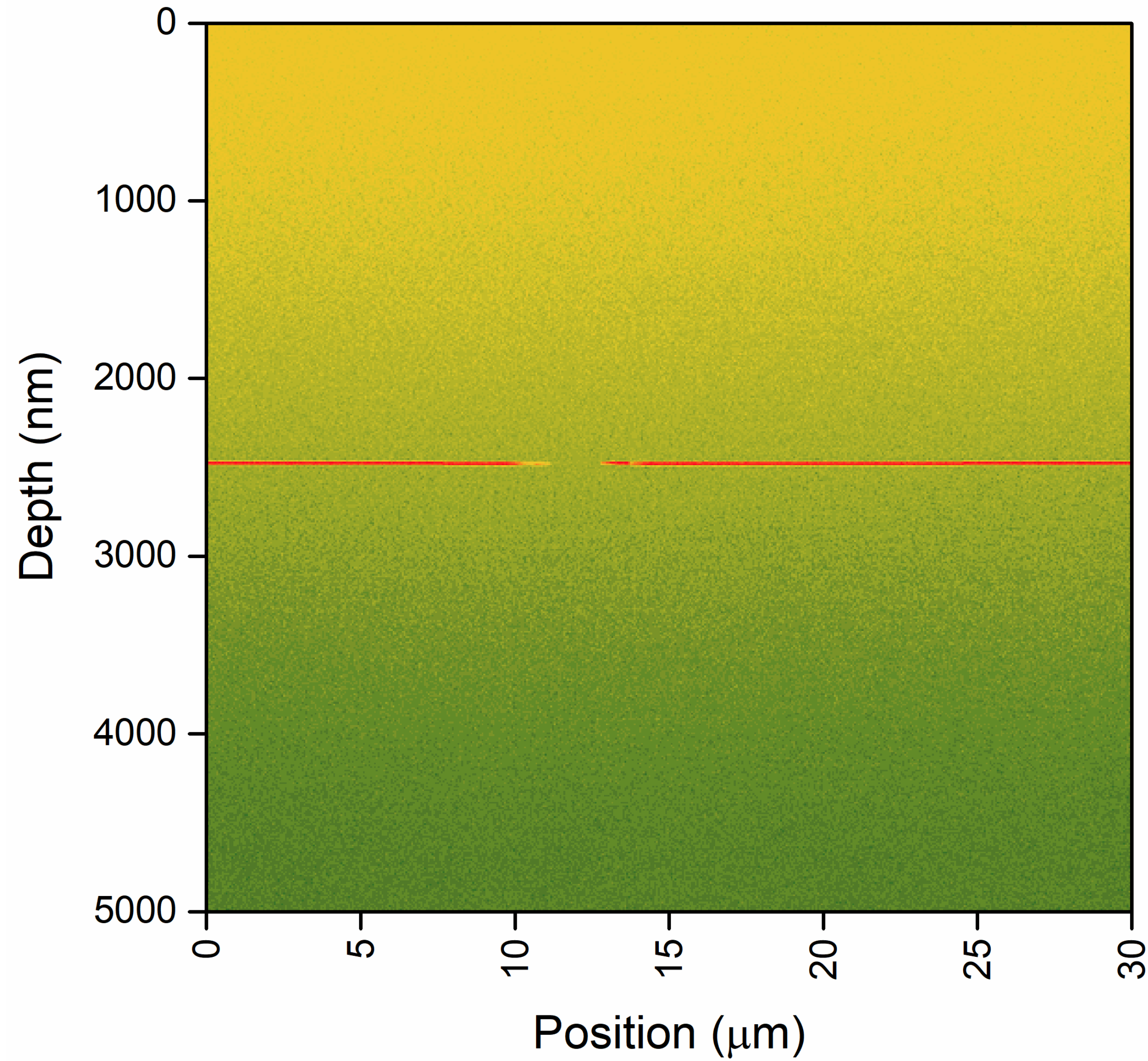


# Aperture

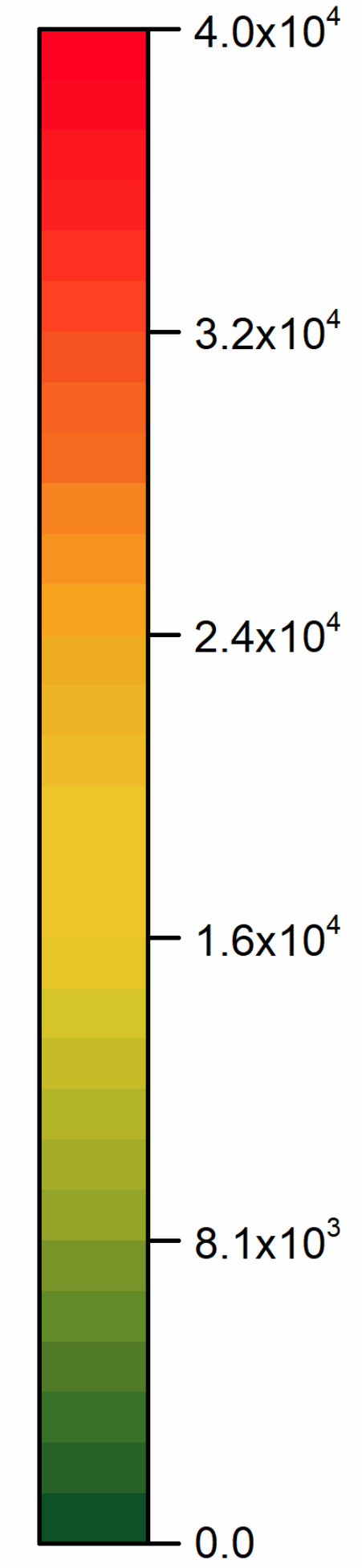
Łukasiewicz  
IMiF







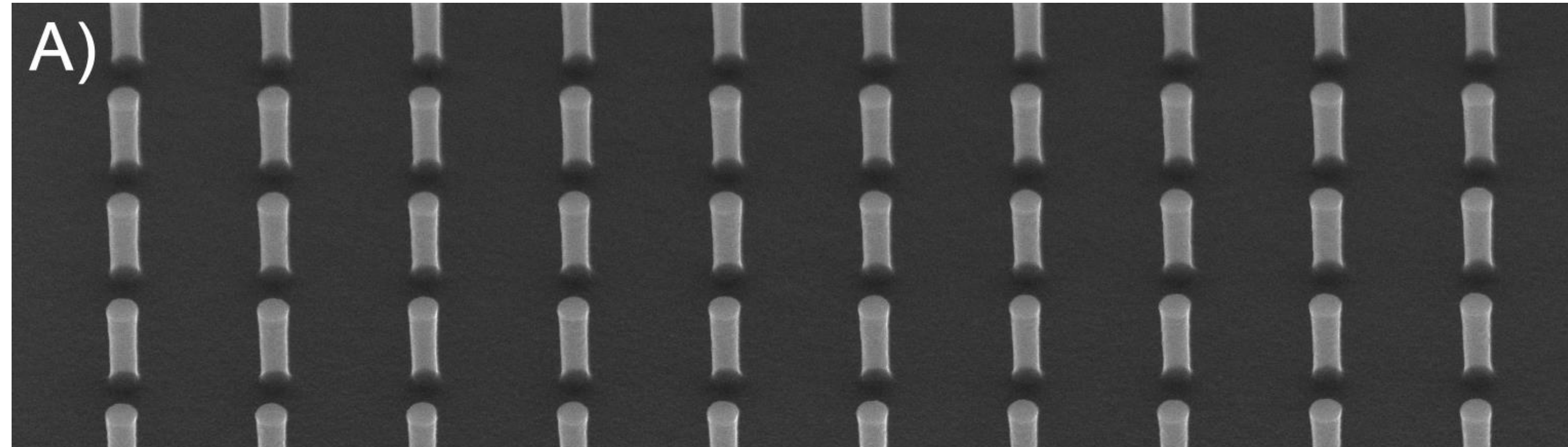
Oxygen counts





Łukasiewicz  
IMiF

# Array of nanowires



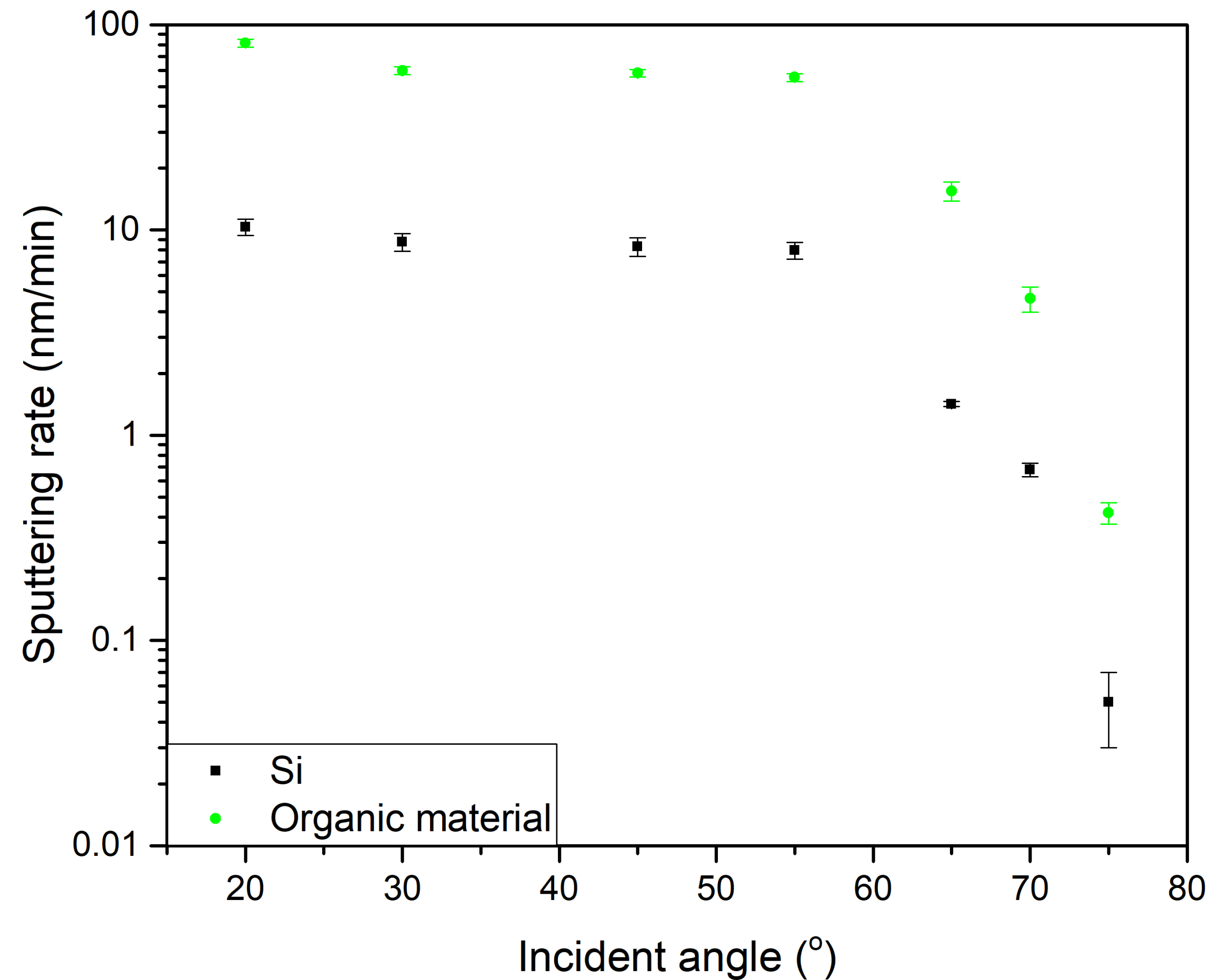
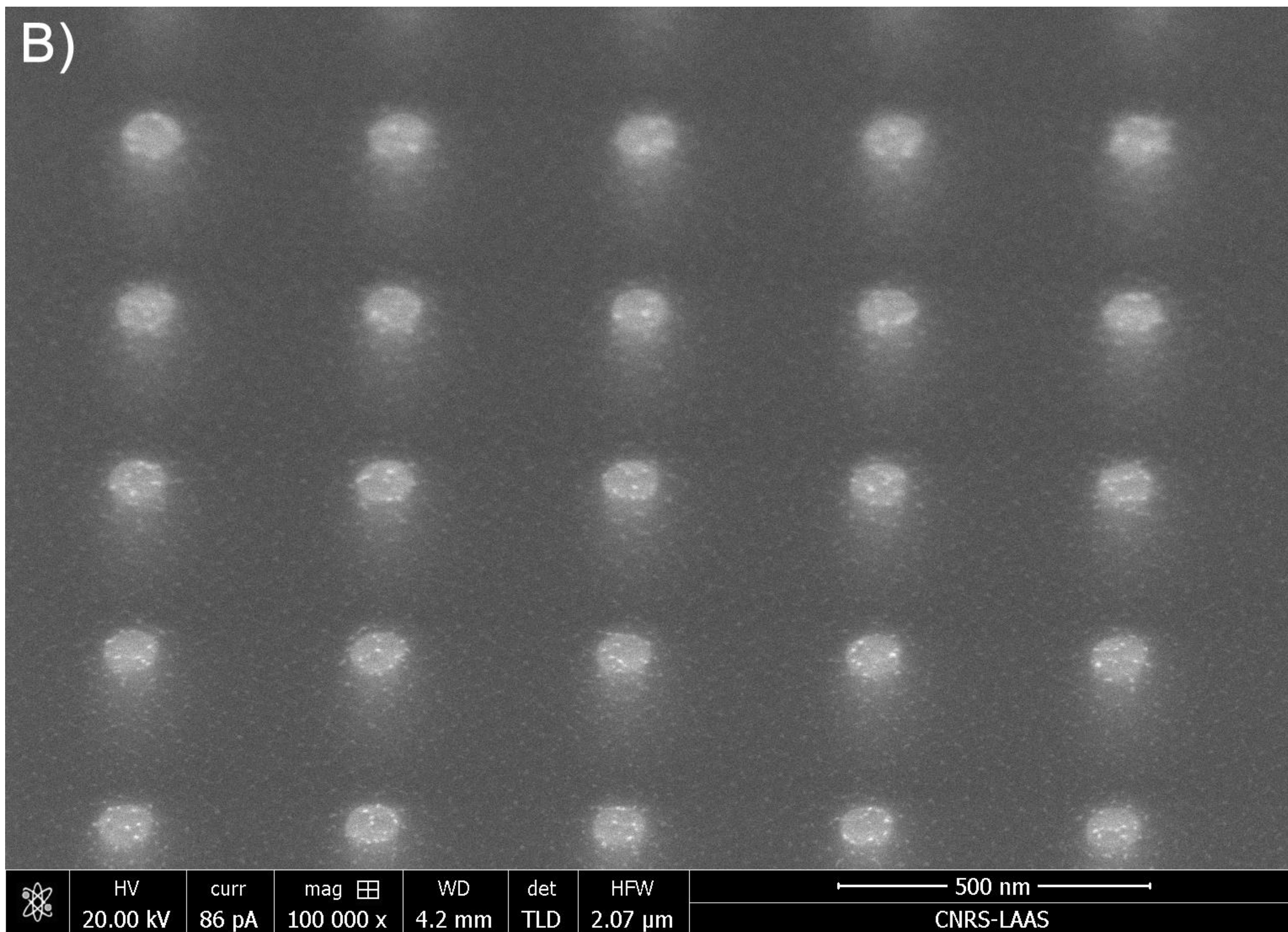
## Fabrication

- Top-down approach
- p-type substrate  
 $B \sim 3.88 \times 10^{19} \text{ atoms/cm}^3$
- Varying oxidation steps
- Boron segregation!

Name	oxidation	temperature (°C)	time (min)	NW diameter (nm)	NW height (nm)
as fabricated	-	-	-	70	270
dry	dry	860	66	60	240
wet	wet	850	5	58	247
gate	wet + dry	850 725	5 20	53	241

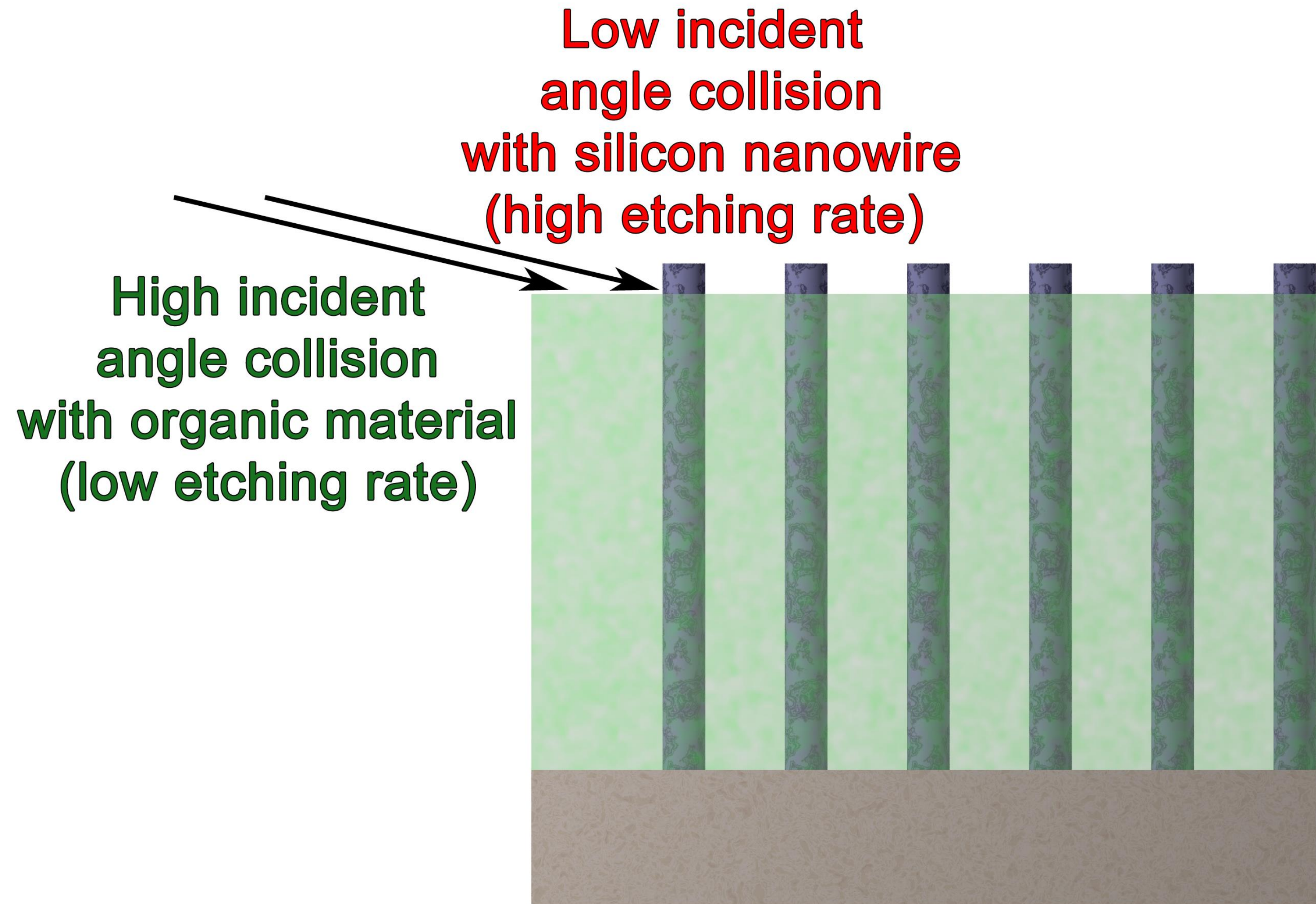
	HV 20.00 kV	curr 86 pA	mag 50 000 x	WD 4.2 mm	det TLD	HPW 4.14 μm	1 μm	CNRS-LAAS
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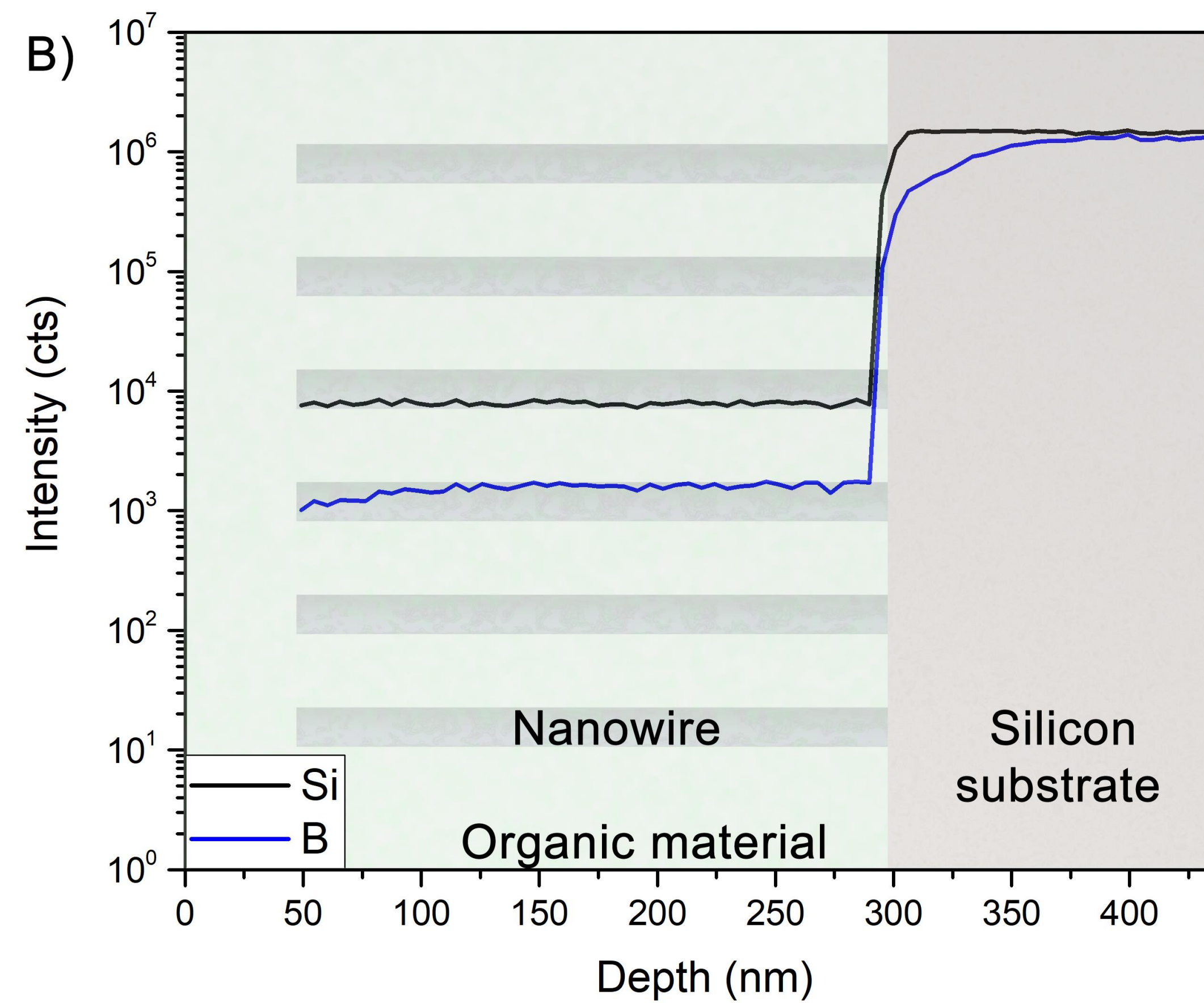
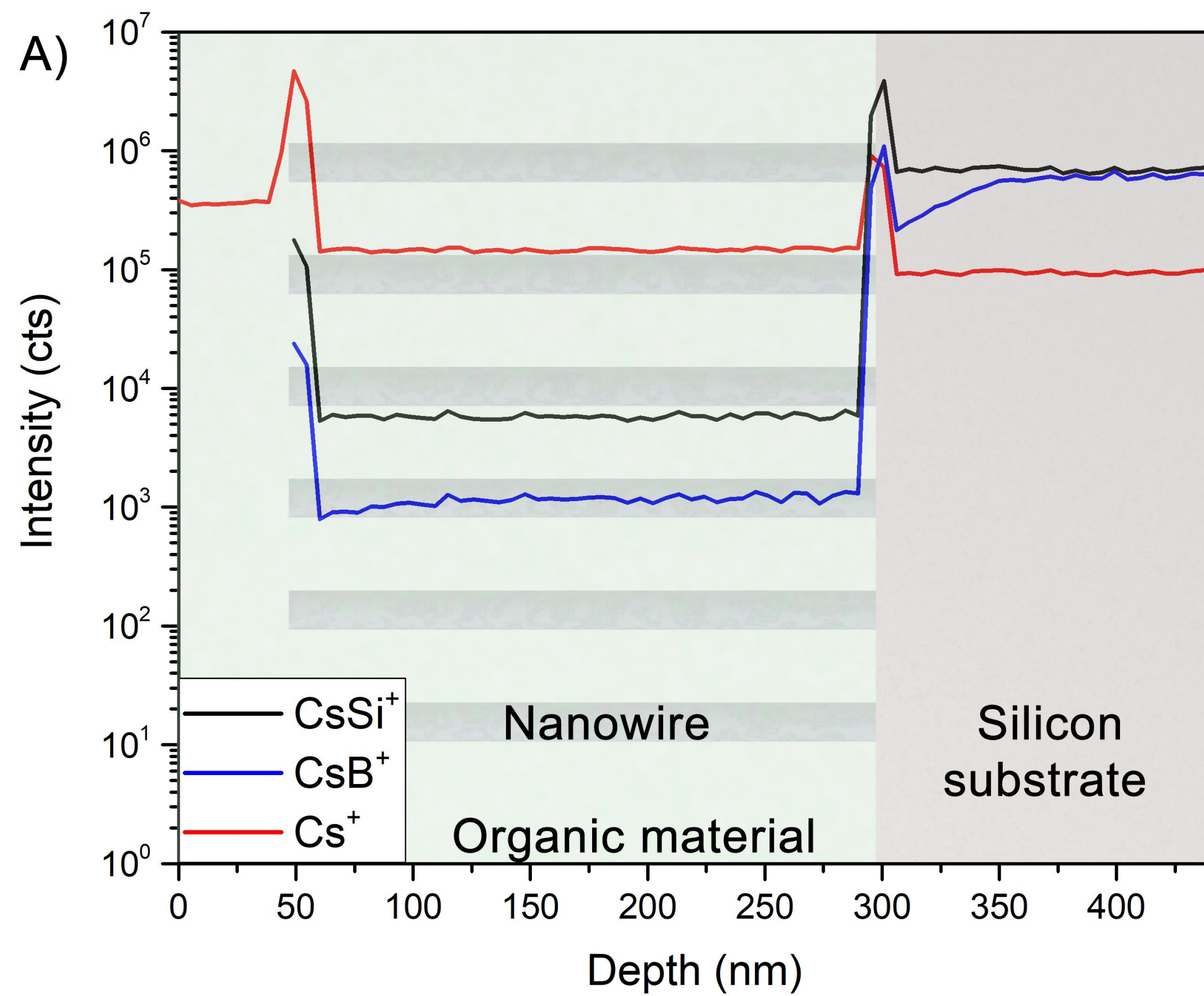




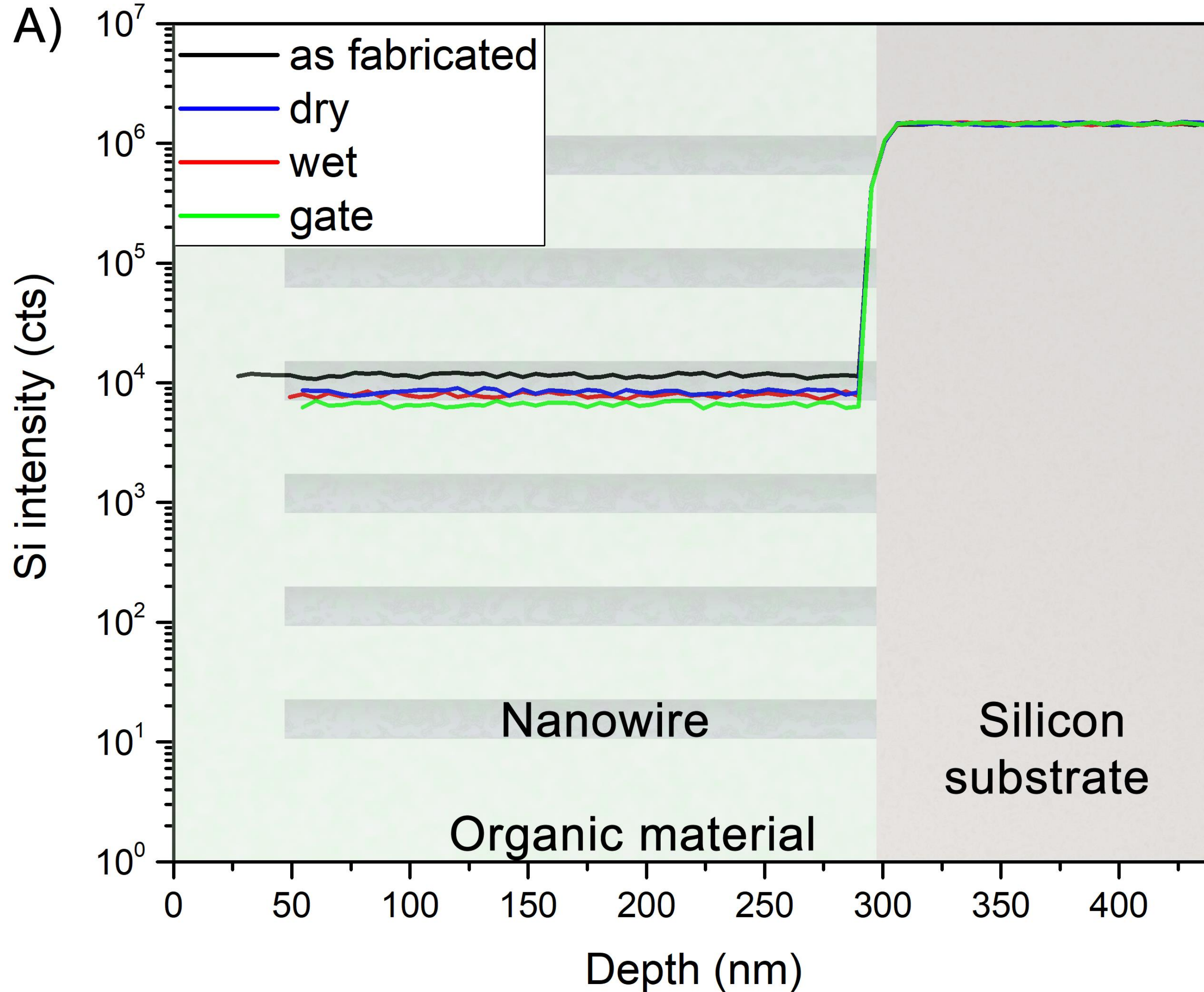
# SIMS measurements on 3D structures







# Silicon signal

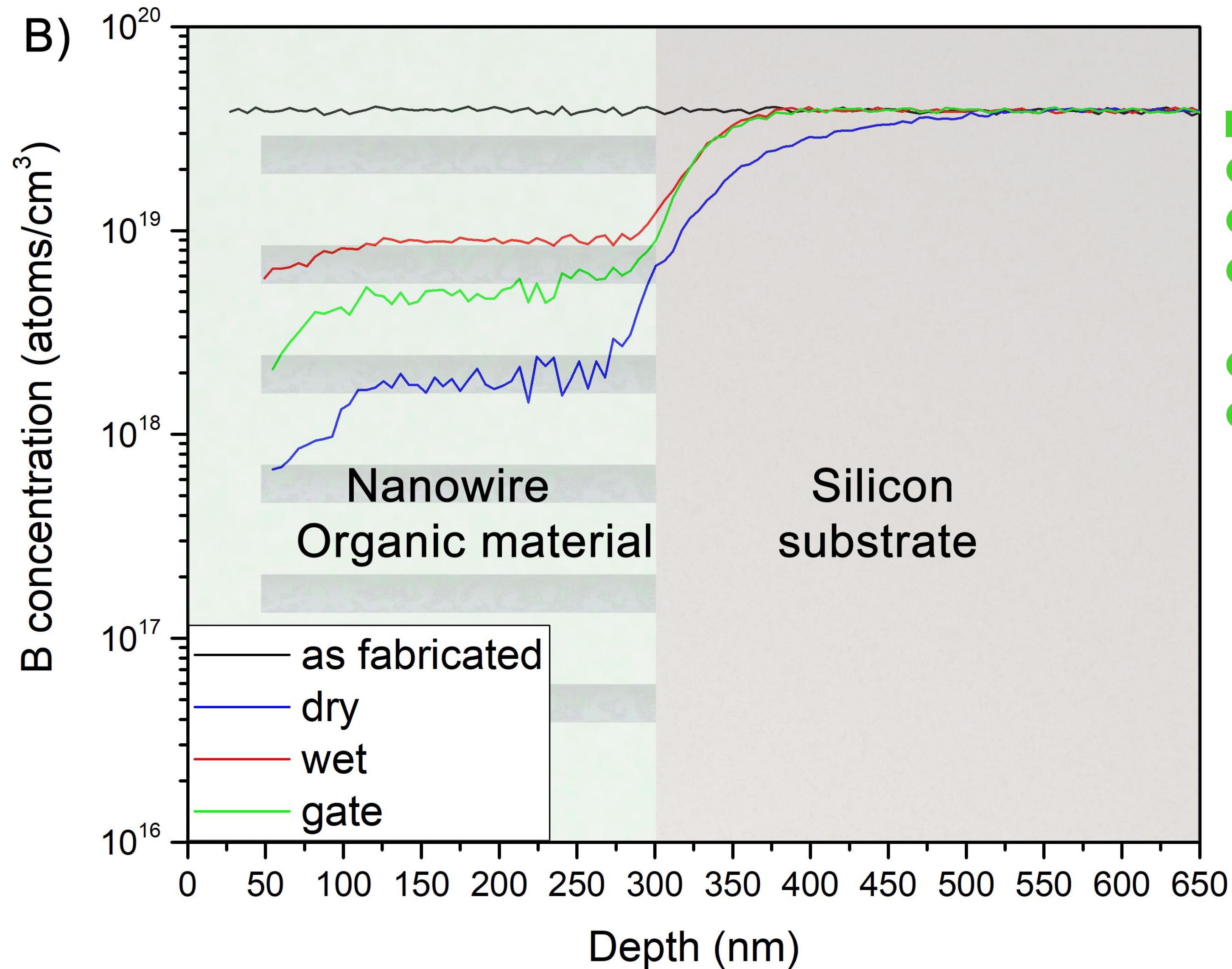


## Remarks

- Intensity  $\sim d^2$
- Very high quality
- As fabricated:  $70.1 \pm 0.6$  nm (70)
- Dry:  $59.9 \pm 0.7$  nm (60)
- Wet:  $57.8 \pm 0.7$  nm (58)
- Gate:  $52.9 \pm 0.8$  nm (53)



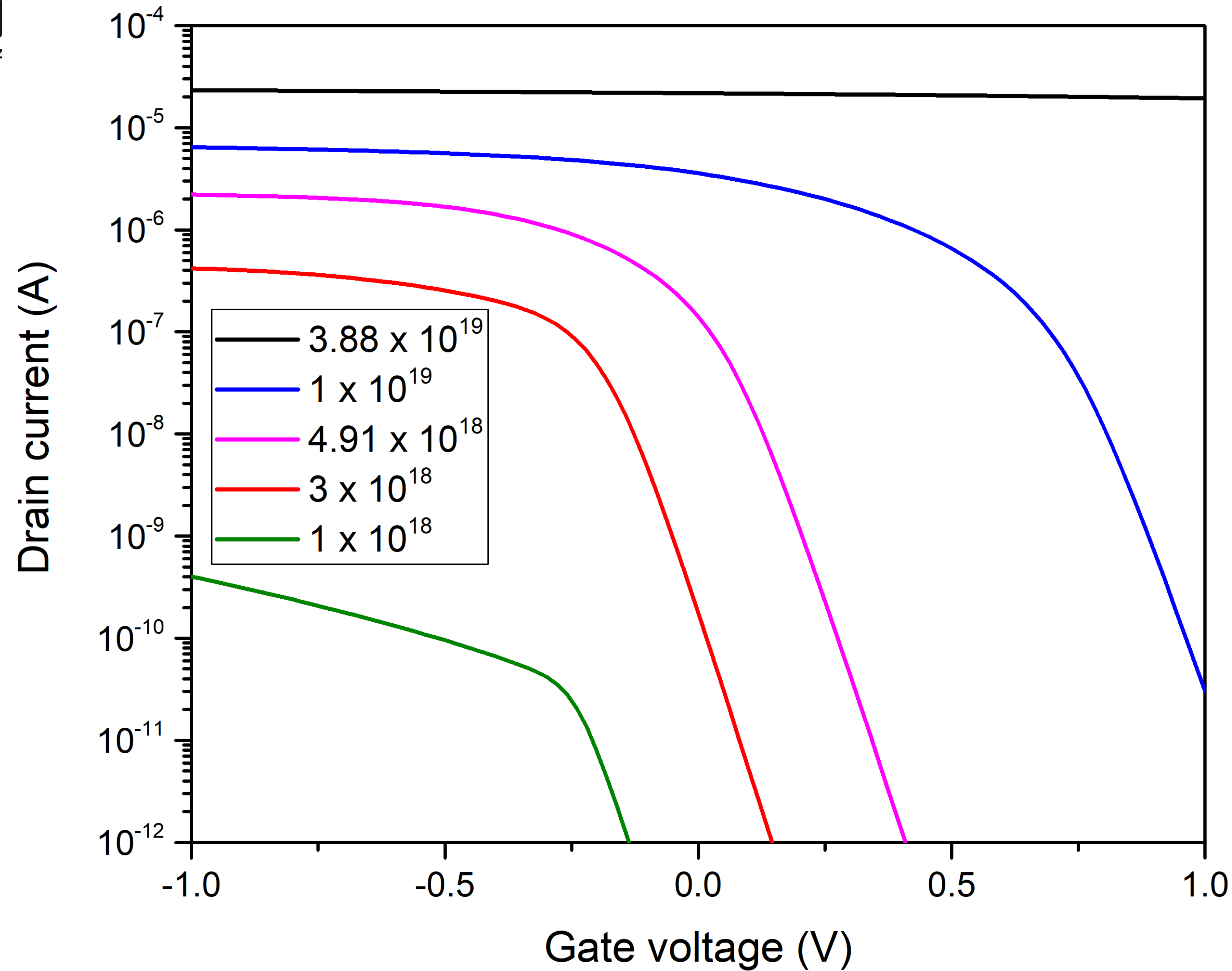
# Boron signal



## Remarks

- Clear depletion of boron
- Affects the substrate and NWs
- Depends strongly on oxidation time
- Good SNR (>8.3 dB)
- Detection limit  
5 × 10<sup>16</sup> atoms/cm<sup>3</sup>  
for array 1000 × 1000 NWs

# Gata-all-around nanowire field effect transistor



## Remarks

- Not possible to switch off with the initial doping
- Small differences in doping  
Significant changes in operation!

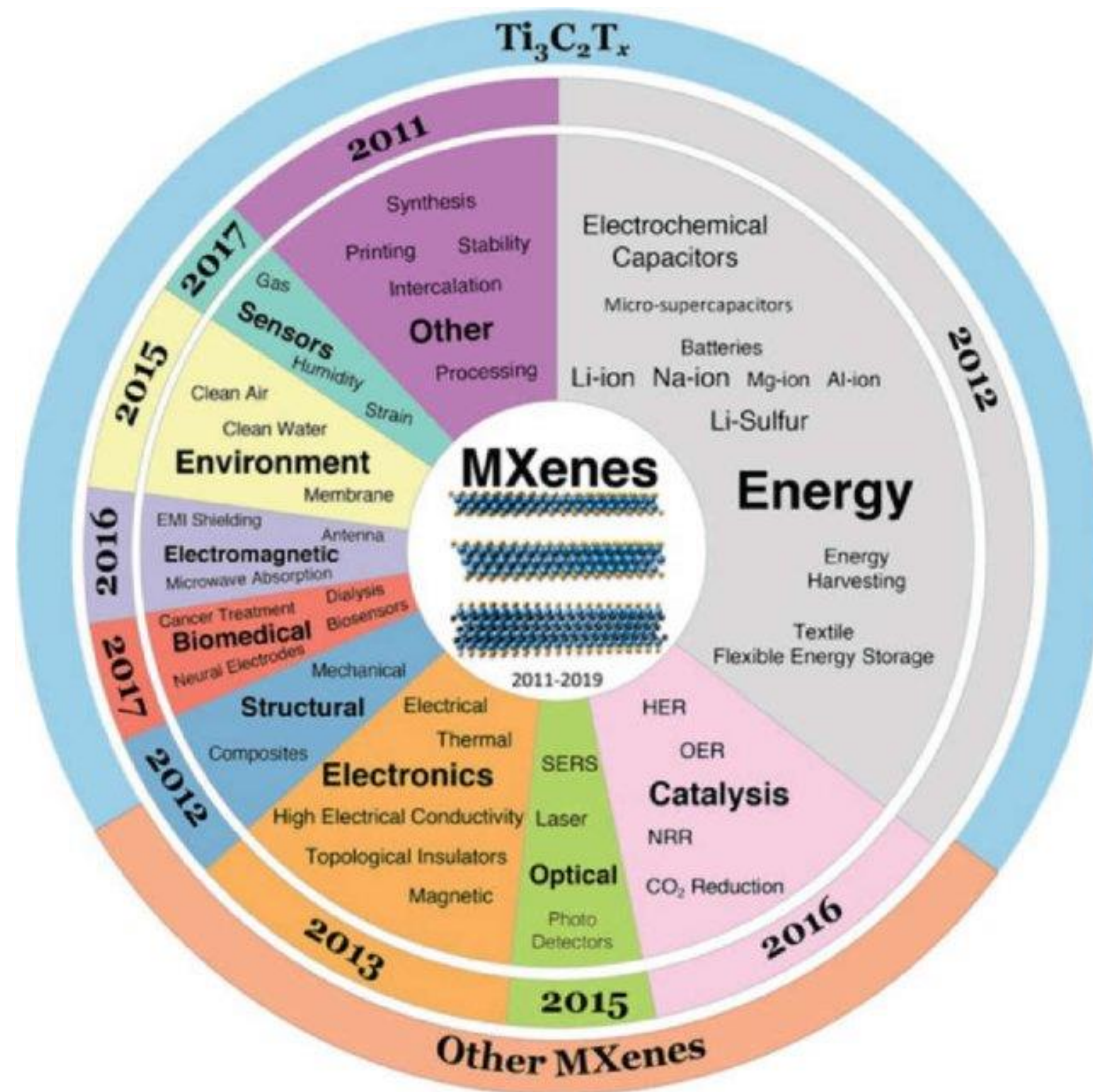
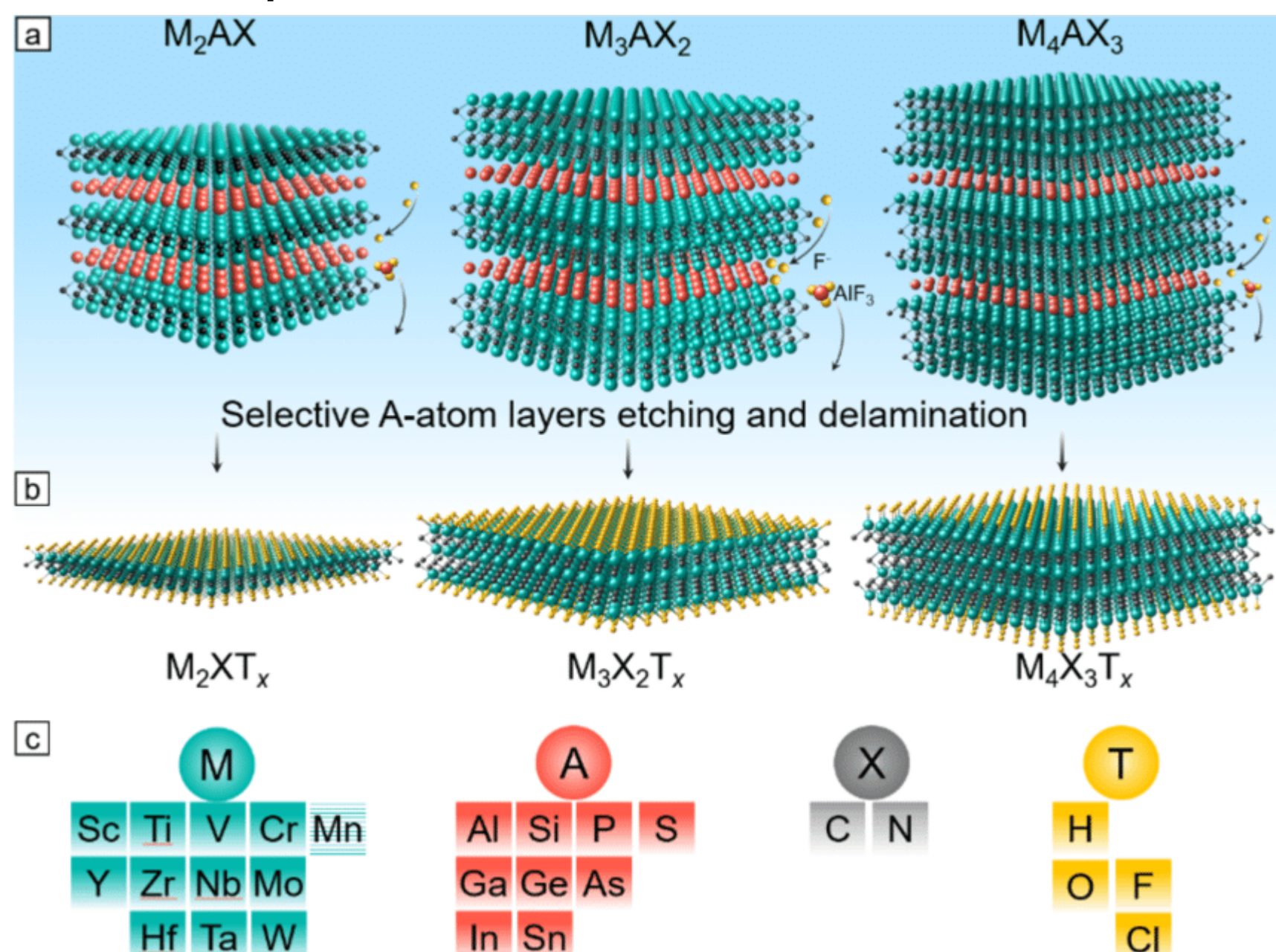


# Graphene/SiC case

- MXenes: a new family of two-dimensional (2D) transition metal carbides, carbonitrides and nitrides
- Synthesized from a MAX phase



Prof. Yury Gogotsi



<https://nano.materials.drexel.edu/research/synthesis-of-nanomaterials/mxenes/>

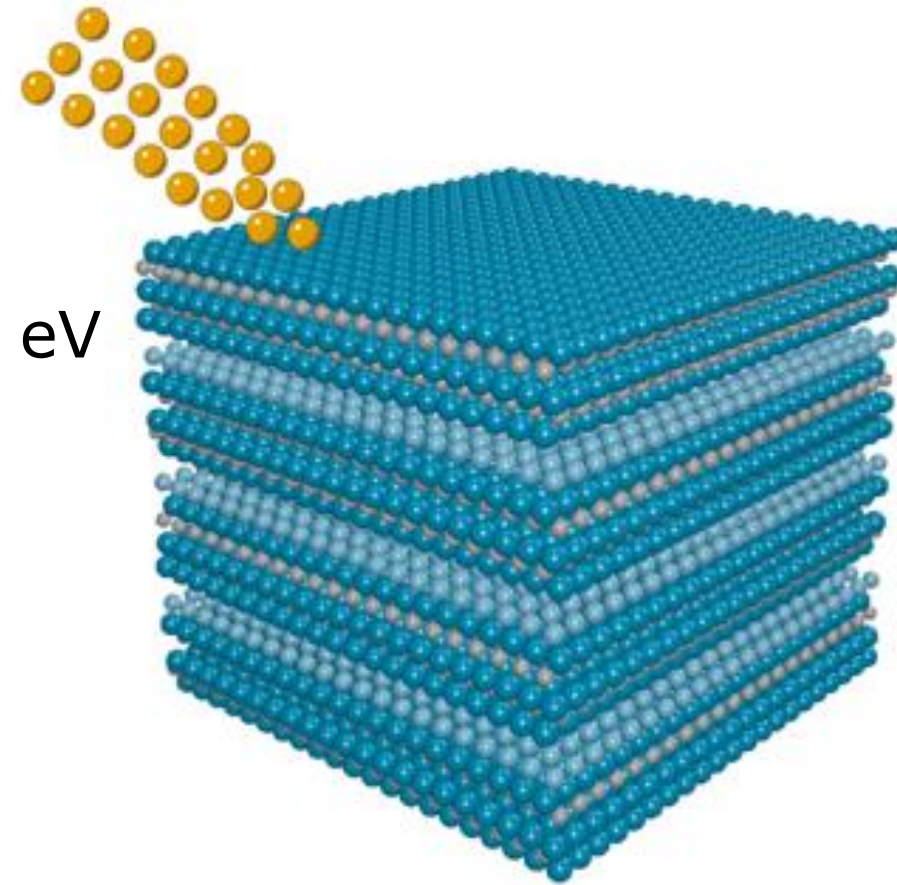




# How to measure MAX/MXene using SIMS? $\text{Ti}_3\text{AlC}_2$ case

<https://www.nature.com/webcasts/event/secondary-ion-mass-spectrometry-characterization-of-max-and-mxene-samples/>

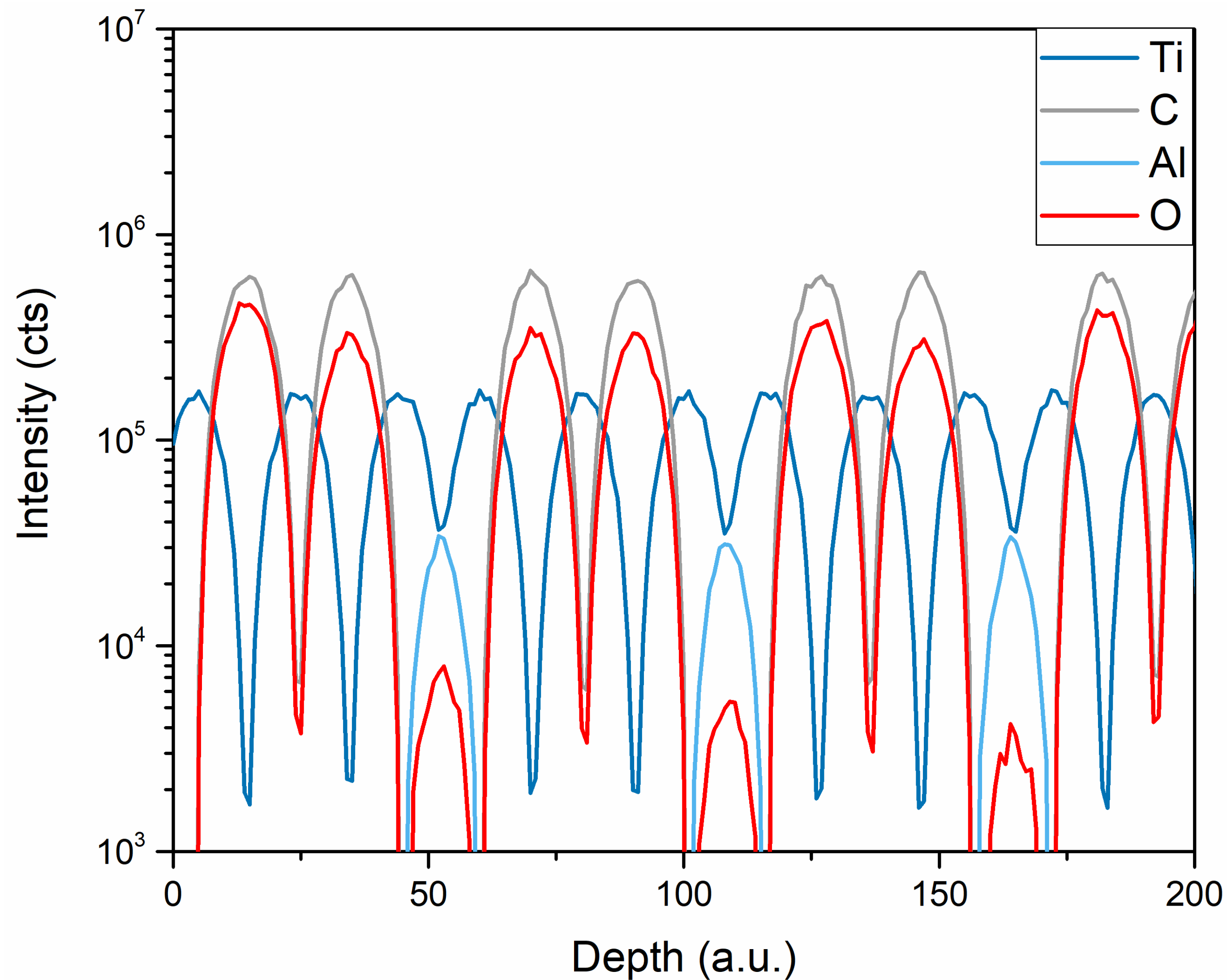
Primary  $\text{Cs}^+$  ion



Impact energy 100 eV

Incident angle  $75^\circ$





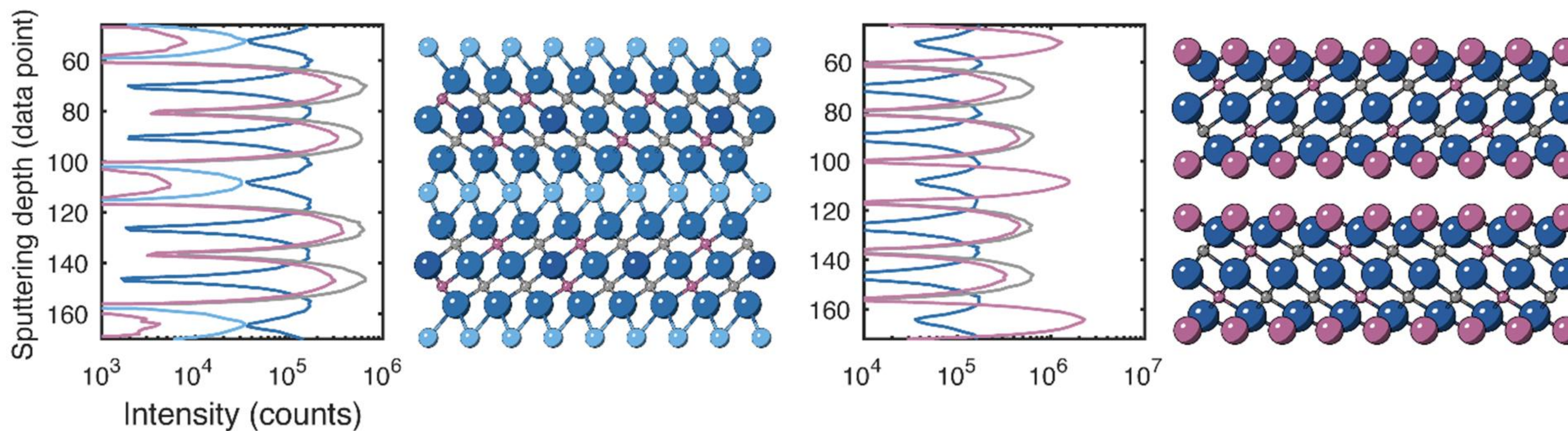
## Remarks

- Much better quality
- Atomic depth resolution!
- Fully reproducible
- Oxygen signal!!!

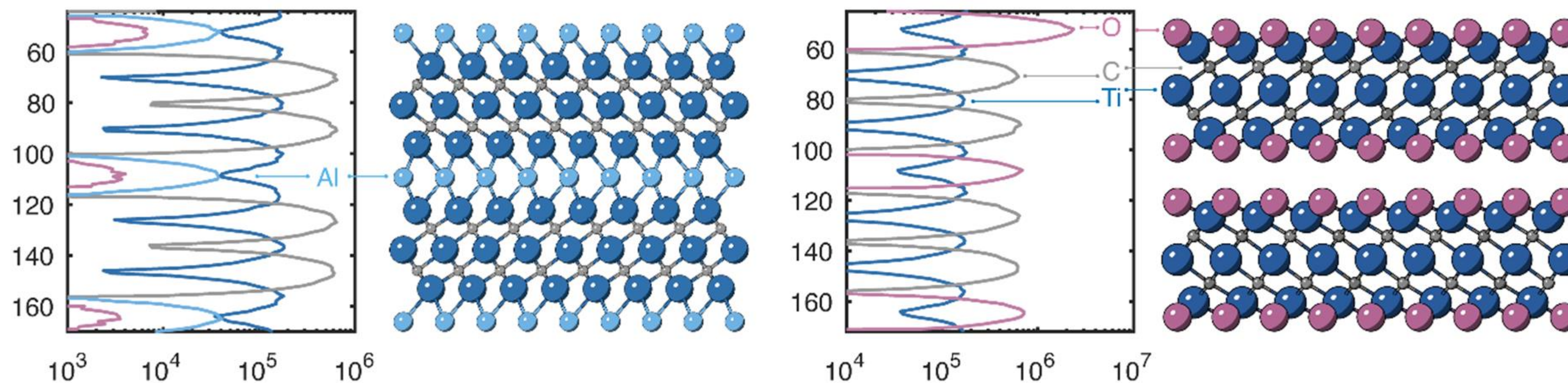


# Carbides? Oxycarbides!

## Conventional MAX/Mxene



## Synthesis with Al excess – Mathis et al. ACS Nano 2021, 15, 4, 6420–6429





# Contents

**1. Principles of SIMS**

**2. Basic applications**

**3. Quantitative analysis**

**4. CAMECA SC Ultra**

**5. Examples**

**6. Conclusions**

# Conclusions

- Powerful characterization technique
- Possibility of measurement artifacts
- Need to plan the experiment
- State-of-the-art instrument
- Dedicated procedures (time-consuming but worth it!)
- Superior depth resolution (even atomic!)



**Thank you for your attention**

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